

Air-light exposure of Cu(In,Ga)Se₂ thin film absorber layers and the effects on complete solar cells

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List of Publications

Authored publications

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- [Höl4] T. Hölscher, T. Walter, T. Schneider, M. Maiberg, and R. Scheer, Device simulation of Cu(In,Ga)Se₂ solar cells by means of voltage dependent admittance spectroscopy, *Thin Solid Films*, **669**, 345-350 (2019). → (Paper 4)
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- [Höl7] M. Maiberg, T. Hölscher, S. Zahedi-Azad, and R. Scheer, Theoretical study of time-resolved luminescence in semiconductors. III. Trap states in the band gap, *Journal of Applied Physics*, **118**, (2015).
- [Höl8] M. Maiberg, T. Hölscher, S. Zahedi-Azad, W. Franzel, and R. Scheer, Investigation of long lifetimes in Cu(In, Ga)Se₂ by time-resolved photoluminescence, *Applied Physics Letters*, **107**, (2015).

- [Höl19] M. Maiberg, T. Hölscher, E. Jarzembowski, S. Hartnauer, S. Zahedi-Azad, W. Franzel, and R. Scheer, Verification of minority carrier traps in Cu(In,Ga)Se₂ and Cu₂ZnSnSe₄ by means of time-resolved photoluminescence, *Thin Solid Films*, **633**, 208-212 (2017).
- [Höl10] T. Schneider, T. Hölscher, H. Kempa, and R. Scheer, Determination of the back contact recombination velocity of a Cu(In,Ga)Se₂/ITO interface using bifacial solar cells, in *37th European Photovoltaic Solar Energy Conference*, Online, 621-626 (2020).
- [Höl11] B. Mahmoudi, F. Caddeo, T. Lindenberg, T. Schneider, T. Hölscher, R. Scheer, and A. W. Maijenburg, Photoelectrochemical properties of Cu-Ga-Se photocathodes with compositions ranging from CuGaSe₂ to CuGa₃Se₅, *Electrochimica Acta*, **367**, 137183 (2021).
- [Höl12] S. M. Lyam, T. Hölscher, M. Maiberg, A. Cabas-Vidani, A. Hernandez-Martinez, H. Tampo, and R. Scheer, Dominant recombination path in low-bandgap Kesterite CZTSe(S) solar cells from red light induced metastability, *Journal of Applied Physics*, **129**, 205703 (2021).
- [Höl13] T. Schneider, C. Dethloff, T. Hölscher, H. Kempa, and R. Scheer, Comparison of Mo and ITO back contacts in CIGSe solar cells: Vanishing of the main capacitance step, *Progress in Photovoltaics*, submitted (2021).

Abstract

The present thesis deals with the light induced detrimental modification of Cu(In,Ga)Se₂ (CIGSe) layers in ambient (humid) air. Exposure of bare CIGSe layers to light in ambient air, called air-light exposure (ALE), is often unavoidable during the manufacturing process of solar cells in the laboratory scale as well as in the industrial scale. In this work it can be shown that after short ALE periods of few minutes, a significant reduction of minority charge carrier lifetime measured with time-resolved photoluminescence (TRPL) give reasons for the detrimental effect of ALE on CIGSe for solar cell applications. The vital importance of light during ALE is demonstrated by no reduction of TRPL lifetime even after storage in ambient air and darkness of several hours. From X-ray photoelectron spectroscopy (XPS) a modification of the CIGSe surface chemistry due to ALE is observed. In XPS-measurements the enhancement in photoelectron emission and the lowering in binding energies of the Na 1s and O 1s core levels are characteristic for ALE surfaces. The O 1s emission peak centred at 531.6 eV relates to a detrimental Na-O-CIGSe bonding complex, considered responsible for the ALE induced lifetime reduction in TRPL measurements. This lifetime reduction manifests in inferior J-V-parameters of solar cells based on ALE absorbers. Compared to non-ALE solar cells the relative drop in power conversion efficiency can amount up to 30% depending on ALE time and light intensity. With measurements of open circuit voltage as a function of temperature $V_{oc}(T)$ and time $V_{oc}(t)$, dominating recombination at the absorber/buffer interface (IF) is diagnosed for solar cells with ALE absorbers. Voltage dependent admittance spectroscopy reveals a voltage dependent defect signature, responsible for recombination centres at the interface. Performing 1 dimensional device simulations the considered IF-defects are found to be of acceptor type centred on an energy level of 0.3 eV above the valence band with a defect density of $3.5 \cdot 10^{11} \text{ cm}^{-2}$. On the contrary, solar cells with non-ALE absorbers are not dominated by IF-recombination and hence no interface defects are detected. By application of heat-light soaking (HLS) on ALE impaired solar cells the drop in efficiency can be reversed. HLS for several hours recovers solar cell parameters to a level comparable with non-ALE solar cells. After HLS the dominant role of interface recombination vanishes in $V_{oc}(T)$ - and $V_{oc}(t)$ -measurements accompanied by no detectable IF-defects in voltage dependent admittance spectroscopy. With glow-discharge optical emission spectroscopy (GDOES) it is found that the elimination of dominating IF-recombination due to HLS comes along with an increased concentration of Na at the absorber/buffer interface. Thus, in contrast to ALE, Na exhibits passivating properties during HLS.

Kurzfassung (german abstract)

Die vorliegende Arbeit handelt von der verschlechternden Veränderung von Cu(In,Ga)Se₂ (CIGSe) Schichten, hervorgerufen durch Beleuchtung in Umgebungsluft. Das Aussetzen der freien CIGSe-Oberfläche gegenüber Licht und Umgebungsluft (engl.: air-light exposure = ALE) ist im Herstellungsprozess von CIGSe-Solarzellen oft unvermeidbar, unabhängig ob im Labormaßstab oder im industriellen Maßstab. Dementsprechend kann in dieser Arbeit gezeigt werden, dass schon nach wenigen Minuten ALE eine starke Verringerung der Lebensdauer der Minoritätsladungsträger, gemessen mit zeitaufgelöster Photolumineszenz (TRPL), auftritt. Diese Verringerung in der Lebensdauer lässt wiederum die Vermutung auf eine Verschlechterung der resultierenden Solarzelle zu, welche mit einem ALE Absorber ausgestattet ist. Die gewichtige Rolle des Lichtes während ALE kann durch die Aussetzung der freien CIGSe Oberfläche gegenüber Umgebungsluft in vollkommener Dunkelheit demonstriert werden. Folglich, zeigt sich nach mehreren Stunden Lagerung der CIGSe Schichten in Umgebungsluft und Dunkelheit keine Reduktion der mit TRPL gemessenen Lebensdauern. Durch Röntgenphotoelektronenspektroskopie (XPS) kann gezeigt werden, dass ALE eine Veränderung der Oberflächenchemie der CIGSe Schichten hervorruft. Diese Veränderung ist charakterisiert durch eine erhöhte Photoelektronenemission und eine Verringerung der Bindungsenergien für die Na 1s und O 1s Bindungsniveaus. Das Maximum des O 1s Emissionspeaks liegt für ALE Oberflächen typischerweise bei einer Bindungsenergie von 531.6 eV, welche einer abträglichen Na-O-CIGSe Verbindung zugeordnet wird. Diese Verbindung wird als Ursache der ALE bedingten Lebensdauer verringierungen in TRPL Messungen erachtet. Die ALE bedingte Verringerung der TRPL Lebensdauer des CIGSe Absorbers zeichnet sich ebenfalls in einer Reduktion der charakteristischen Parameter der auf diesen Absorbern basierenden Solarzellen ab. Im Vergleich zu Solarzellen mit unverminderten Absorbern kann die durch ALE hervorgerufene relative Verringerung der Leistungskonversionseffizienz bis zu 30% betragen. Dabei, steht die Größe der Effizienzverringierung in Abhängigkeit der ALE Dauer und der eingestrahelten Lichtintensität während ALE. Durch Messungen der Leerlaufspannung als Funktion der Temperatur $V_{OC}(T)$ und als Funktion der Zeit $V_{OC}(t)$ konnte für Solarzellen mit ALE Absorbern eine erhöhte Rekombination an der Absorber/Puffer Grenzfläche festgestellt werden. Bei der Anwendung von spannungsabhängiger Admittanzspektroskopie zeigte sich zudem für ALE Solarzellen eine spannungsabhängige Defektsignatur, welche charakteristisch für Grenzflächendefekte ist. Mittels 1 dimensionaler Simulation der Solarzelle als elektrisches

Bauelement ließen sich die Parameter der Grenzflächendefekte bestimmen. Die Simulationsergebnisse zeigten, dass die Grenzflächenzustände durch Akzeptoren beschrieben werden können. Das Energieniveau dieser Akzeptoren zentriert sich 0.3 eV oberhalb des Valenzbandes innerhalb der Bandlücke des Absorbers. Die Dichte der Defektzustände beträgt $3.5 \cdot 10^{11} \text{ cm}^{-2}$. Im Gegensatz, weisen Solarzellen, basierend auf CIGSe Absorberschichten die keinem ALE ausgesetzt waren, weder dominierende Grenzflächenrekombination in $V_{oc}(T)$ - und $V_{oc}(t)$ -Messungen auf, noch die Detektion eines Grenzflächendefektes in spannungsabhängiger Admittanzspektroskopie.

Durch Beleuchtung mittels weißem Licht ($0.1 \text{ W} \cdot \text{cm}^{-2}$) und unter erhöhten Temperaturen (80 - 90°C) der kompletten Solarzellen bei geöffneten klemmen, genannt heat-light soaking = HLS, können die Solarzellenparameter von Zellen mit ALE Absorbern auf das Niveau von Zellen mit Absorbern ohne ALE angehoben werden. Die Verbesserung der Solarzellenparameter nach HLS gehen einher mit der nicht mehr vorhandenen Dominanz von Grenzflächenrekombination in $V_{oc}(T)$ - und $V_{oc}(t)$ -Messungen, sowie dem Ausbleiben des mit der Gleichspannung variierenden Signals eines Grenzflächendefektes in spannungsabhängiger Admittanzspektroskopie. Mittels Glimmentladungsspektroskopie (engl.: glow-discharge optical emission spectroscopy = GDOES) angewendet vor und nach HLS zeigt sich eine durch HLS hervorgerufene Anreicherung von Natrium an der Absorber/Puffer Grenzfläche. Daher kann für Natrium, im Gegensatz zu ALE, eine passivierende Rolle während HLS geschlussfolgert werden.

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List of symbols and abbreviations

AE	Air exposure
A_i	Diode quality factor of the particular recombination current density
ALE	Air-light exposure
α	Absorption coefficient of light
A^*	Richardson constant of thermionic emission theory
BC	Region in the proximity of the back contact
CBD	Chemical bath deposition
$C_{i,j}$	Capacitance normalized to the cross-sectional area with $i = \text{QNR, SCR, BC}$ and $j = \text{a, b, hrw, lrw}$
$\chi_{e,i}$	Electron affinity of particular layer ($i = \text{a, b, hrw, lrw}$)
CIGSe	Copper indium gallium diselenide, Cu(In,Ga)Se_2
DA	Dark annealing (tempering of devices at high temperatures $\approx 90^\circ\text{C}$ in darkness)
ΔE_C	Conduction band offset in between 2 semiconductors with different electron affinities
$D_{n,a}$	Diffusion length of electrons within the absorber
E_A	Activation energy of the saturation current density J_0
E_F	Equilibrium Fermi-level
E_{Fn}, E_{Fp}	Quasi-Fermi level of electrons or holes
$E_{g,i}$	Band gap energy of the particular semiconductor ($i = \text{a, b, hrw, lrw}$)
ϵ_0	Vacuum permittivity
$\epsilon_{r,i}$	Relative permittivity of particular semiconductor ($i = \text{a, b, hrw, lrw}$)
EQE	External quantum efficiency
$E_{z,i}$	Electric field component in z-direction
η_C	Collection efficiency of generated charge carriers
η_{cell}	Solar cell efficiency (analogous: PCE)
FF	Fill factor
$\gamma_{A,if}, \gamma_{D,if}$	Degree of ionized acceptor or donor states at the interface
G_n, G_p	Generation rate of electrons or holes
HLS	Heat light soaking (long time illumination of devices under increased temperatures $\approx 90^\circ\text{C}$)
hrw	high resistive window layer (i-ZnO)
IF	Interface
i-ZnO	intrinsic (undoped) Zincoxide (IZO)
J_{ph}	Collected photo current density

J_{SC}	Short circuit current density
$J_0, J_{01}, J_{02}, J_{0,i}$	Saturation current densities ($i = \text{QNR}, \text{SCR}, \text{IF}$)
J_{00}	Reference current density
k_B	Boltzmann constant
$\lambda_{D,i}$	Debye length of majority charge carriers
L_n, L_p	Diffusion length of electrons or holes
lrw	low resistive window layer (ZnO:Al)
$N_{A,a}$	Shallow acceptor density of the p-absorber
$N_{D,i}$	Shallow donor density of the buffer ($i = b$) or window layers ($i = \text{hrw}, \text{lrw}$)
$N_{d,i}$	Density of volume defects in the particular semiconductor ($i = a, b, \text{hrw}, \text{lrw}$)
$N_{d,if}$	Surface density of defect states at interfaces
$n_{i,j}$	Intrinsic charge carrier density of particular semiconductor ($j = a, b, \text{hrw}, \text{lrw}$)
NI	Recurrent signature in admittance spectroscopy of CIGSe solar cells
N_V, N_C	Effective density of states of the valence band or conduction band
ω_0	Characteristic angular frequency of capacitance steps
PCE	Power conversion efficiency
Φ_B	Energetical barrier for charge carriers
ϕ_i	Electro static potential within a specific region
$\Phi_{if,a}^p$	Hole barrier at the front interface of the absorber
Φ_m	Work function of metal contacts
PL	Photoluminescence
QNR	Quasi-neutral region
R_n, R_p	Recombination rate of electrons or holes
SCR	Space charge region
σ_n, σ_p	Capture cross section of electrons or holes
SIMS	Secondary ion mass spectroscopy
SLG	Soda lime glass
S_n, S_p	Recombination velocity of electrons or holes
SRH	Shockley-Read-Hall
$\tau_{n,a}$	Lifetime of electrons within the p-type absorber layer
TRPL	Time-resolved photoluminescence
V_{BC}	Built-in voltage of a Schottky barrier at the back contact
V_{bi}	Built-in voltage (complete potential drop in between absorber and low resistive window layer)
V_{OC}	Open circuit voltage
w_a	Depletion width of the absorber
$w_{i,j}$	Width of a specific region ($i = \text{SCR}, \text{QNR}, \text{BC}$) within a semiconductor ($j = a, b, \text{hrw}, \text{lrw}$)
XPS	X-ray photoelectron emission spectroscopy
ZnO:Al	Aluminium doped Zincoxide (AZO)

1. Introduction

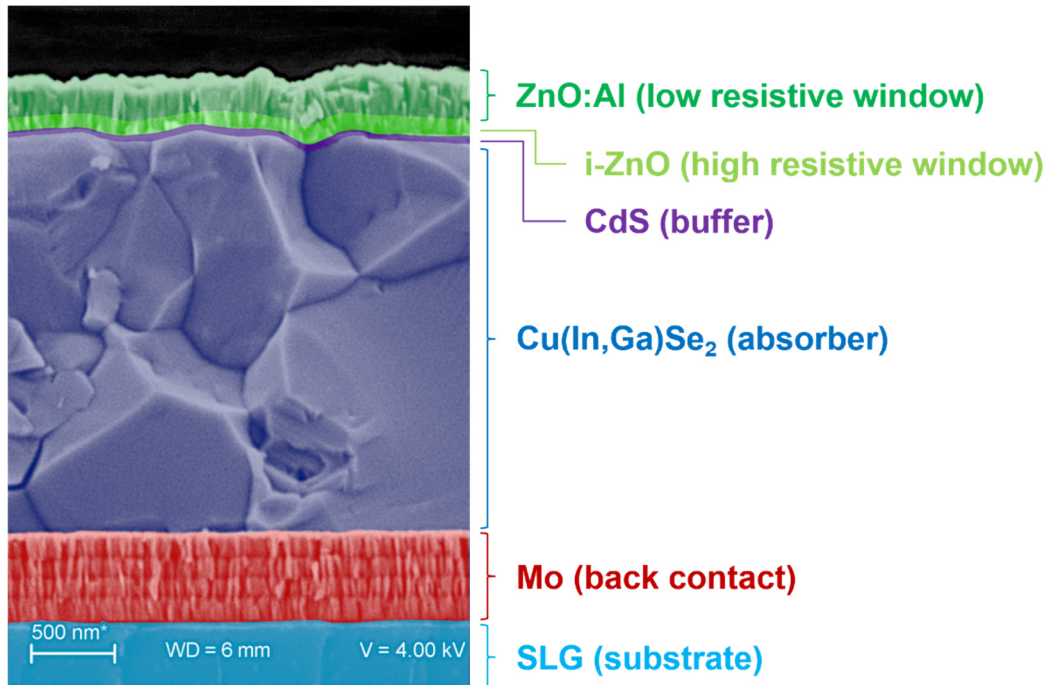


Figure 1 Scanning electron microscopy cross-section of a Cu(In,Ga)Se₂ solar cell fabricated at the Martin-Luther-University. The incorporation of Sodium into the absorber layer took place by diffusion from the soda lime glass substrate (SLG) through the Mo back contact at high temperatures (> 600°C).

Power conversion efficiencies (PCE) of 19.2% [1] at module scale have been demonstrated for photovoltaic thin film devices based on the p-type absorber material Cu(In,Ga)Se₂ (CIGSe). Despite the question of abundance of elements like Indium or Gallium and existing PCE's decisively below crystalline Silicon based modules with 24.4% [1], there are nevertheless several reasons making CIGSe photovoltaic technology interesting for consumers, investors and manufactures.

1. The *energy payback time* of CIGSe solar cells is lower than of Silicon devices (2.2 years, solar irradiance: 1000 kWh·m⁻²·y⁻¹ [2]) and shows further potential to be reduced by reducing deposition temperatures and thicknesses of functional layers [3-6].
2. *Flexible solar cells* on metallic or synthetic foils with > 20% PCE at the laboratory scale have been reported [7]. Prospectively by establishing the roll-to-roll deposition technique lower production costs could be achieved.

3. CIGSe shows a high “resistivity” against impurities [8, 9], wherefore minor requirements have to be imposed on the cleanliness of the production environment and the purity of source materials [10, 11].
4. The radiation hardness makes CIGSe solar cells attractive for space applications [12]. In combination with flexible substrates solar sails in space becomes imaginable, but also for earthbound applications like sails for deep-sea vessels or sunshades.
5. Aesthetics aspects are the anthracite-hued visitation of CIGSe modules or the possibility of semi-transparent (flexible) solar cells, making CIGSe suitable for architectural configurations.

Thus, CIGSe implicates a high potential to filling gaps of the photovoltaic market, which cannot be satisfied by the current Si technology. This may even allow a higher cost-structure. From the scientific point of view there are still fundamental open questions in despite of a more than 40 years ongoing CIGSe research history. Figure 1 shows a scanning electron microscopy (SEM) cross-section of a CIGSe solar cell with the typical layer sequence from top to bottom: Aluminium doped ZnO (AZO) / intrinsic ZnO (i-ZnO) / CdS / CIGSe / Mo / soda lime glass (SLG). Obviously the imperfect microstructure with small and large grains, vertical and horizontal grain-boundaries of the CIGSe absorber layer can be seen in Figure 1. It is still under debate, why the electronic properties of polycrystalline CIGSe solar cells with >22% PCE [13, 14] are at the same level or even beyond to their epitaxial counterparts with 19 – 20% PCE [15], [16, 17]. Would this imply an unexpected beneficial effect of grain-boundaries to the electrical quality of the absorber material? Some researchers mention that defects and impurities segregate at grain boundaries, resulting in a small defect density within the grain interior [18-20]. However, preponderantly the benign electronic properties of grain-boundaries like charge carrier transport enhancement channels or separation of electrons and holes preventing from recombination due to charge accumulation are considered as the main reasons for achieving high efficiency polycrystalline CIGSe solar cells [17, 21-23].

On the other hand owing to the complexity of the device structure with its numerous layers and interfaces (compare Figure 1) a sufficient modelling of the electronic cell properties is impeded [24]. In the case of the CIGSe layer this is aggravated by inadequately specified transport parameters like minority charge carrier lifetime and mobility. Hence, depending on the measurement conditions/techniques lifetimes in the range from 0.1 ns to several hundred nanoseconds [25, 26], as well as mobilities from 0.01 to 1000 $\text{cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$ are reported [27, 28]. In the case of time-resolved photoluminescence (TRPL) measurements Maiberg et al. [29],[Höl17],[Höl19] showed that the decay time observed on bare CIGSe layers does not

correspond directly to the “real” minority charge carrier lifetime. Thus experimental TRPL decay times of CIGSe absorbers are no direct indication for the quality of the resulting solar cells (under the assumption of a constant quality of the buffer/window layer stack). Reasons for this grievance are manifold and mostly intrinsically like i.e. electron trap states within the band gap, charge carrier separation due to internal electric fields, or spatially and energetically distributed recombination centres, influencing the shape and the duration of TRPL-transients. Thus, a firstly simple appearing measurement like the minority charge carrier lifetime with TRPL delivers entirely consistent results only by means of numerical simulation. This reflects the complexity of the polycrystalline CIGSe material system by itself.

That’s why it is not surprising that the efficiency enhancement of CIGSe solar cells has been reached with more or less empiric methods [30]. For instance in the early 1990s the observation of the beneficial effect of alkaline metals – for the first time Sodium – to the CIGSe absorber material took place under lucky circumstances. An apriori parasitic incorporation of Sodium during the CIGSe growth process was effected by the usage of impure soda lime glass (SLG) substrates instead of costly highly pure substrates without Sodium [31]. Thus the promotional impact of Sodium on CIGSe solar cells is based on the cost-saving aspects of SLG rather than on a scientific motivation. The unintentional Sodium-doping of CIGSe layers conducted to an immense raise of the power conversion efficiencies. In 1993 Chen et al. [32] reported a record efficiency of 13.7% for devices without Sodium. While at the same time Hedström et al. [33] demonstrated 16.9% due to the incorporation of Sodium from the SLG substrate.

Later on, after 2010, the additional or substitutional incorporation of heavier alkaline metals (K, Rb, Cs) with specifically pre- and post-deposition techniques revealed a further enhancement of power conversion efficiencies [13, 34, 35]. In 2017 Solar Frontier achieved the prolonged highest efficiency of 22.9%¹ for solar cells fabricated under laboratory conditions [1]. However, the mechanisms behind the impact of alkaline metals on the electronic properties of CIGSe are not yet fully understood and highly discussed in the CIGSe community (section 2.1.3).

¹ For comparison the latest laboratory record efficiency of multi-crystalline silicon solar cells amounts 22.3% as well as 26.7% in the case of single crystal silicon [1].

1.1. Air exposure of CIGSe layers

One key factor of manufacturing high efficiency CIGSe solar cells is reported by Jackson et al. [36]. They improved their baseline efficiency by reducing the retention time of the uncovered CIGSe absorber in ambient air. It is usual during the laboratory and industrial manufacturing of CIGSe solar cells that the uncoated CIGSe layer comes into contact with the environmental atmosphere i.e. before and during processing the CdS buffer layer [37, 38].

TRPL-experiments of several groups revealed a strong reduction of the minority charge carrier decay times after air exposure of CIGSe layers [39-43]. Shirakata et al. [44] observed a decreasing steady state photoluminescence (PL) intensity in combination with diminishing TRPL decay times by progressive air exposure. Further, as compared to as-fabricated CIGSe layers they monitored with secondary ion mass spectroscopy (SIMS) for air exposed CIGSe layers an increased amount of Sodium, Hydrogen and Oxygen at the very CIGSe surface [44]. In this connection Heske et al. [45, 46] demonstrated with X-ray photoelectron spectroscopy (XPS) the formation of a Na–O–CIGSe complex after annealing at room temperature of CIGSe layers with co-adsorbed H₂O and Na. Both groups suggested, based on their results, that the oxygenation of Sodium at the CIGSe surface induces recombination active defect states, reducing the PCE of the completed solar cell due to interface recombination. However, an experimental evidence for this suggestion has not been presented.

Metzger et al. [25, 40] bridged the gap between TRPL decay time degradation and solar cell impairment of air exposed CIGSe layers. They were able to refer a minority charge carrier lifetime reduction from 40 ns directly after fabrication to 0.3 ns after 21 h air exposure to a decreased PCE from 16% down to 5%, but without figuring out the mechanism behind solar cell deterioration [40].

Braunger et al. [47, 48] noticed that air humidity plays an important role during air exposure. They found a high impairment of PCE for completed solar cells with CIGSe absorbers exposed to humid air ($R_H = 100\%$, $t = 20$ d) at room temperature. Instead, cells with absorbers exposed to dry air at 200°C ($t = 4$ h) revealed an improvement of device performance. With XPS measurements they showed that surfaces of Sodium containing CIGSe absorbers exhibit oxides of Na, In, and Ga after dry air annealing. In comparison CIGSe surfaces without Sodium are not oxidized in dry air. In the case of humid air exposure, the oxygenation of all elements, except Cu, is independent from the Sodium content. Further the formation of elemental Se at the CIGSe surface is found and referred to the solar cell impairment [47].

1.2. Air-light exposure of CIGSe layers

Consequent upon the preceding results of air exposure experiments this thesis goes one step beyond and uncovers the decisive role of light during air exposure, named as air-light exposure (ALE). In the previous section the experimentalists investigated the influence of air exposure to CIGSe layers without consideration of the illumination state of the samples. A first indication of a light enhanced degradation of CIGSe layers due to illumination was reported by Metzger et al. in Ref. [25]. They observed during TRPL measurements an expedited reduction of minority charge carrier lifetime under high intense laser light excitation in ambient air. Further with steady state PL measurements Regesch et al. [49] pointed out that the decreasing quasi-Fermi level splitting due to air exposure is accelerated if the CIGSe layers are additively illuminated. In this study epitaxial grown CIGSe absorbers served as Sodium free references and exhibited identical reduction of the quasi-Fermi level splitting. For this reason, Regesch et al. excluded a critical role of Sodium on the degradation process [49].

In contrast the underlying hypothesis of this work is based on the participation of Sodium in ALE and is introduced by the following list.

1. Air-light exposure of bare CIGSe layers causes a physico-chemical modification of the CIGSe surface inducing recombination active states within the band gap at the surface. A crucial role during ALE plays Sodium.
2. The modification of the CIGSe surface after ALE survives the subsequent steps of solar cell fabrication and drives the completed device into interface recombination.
3. The illumination dependent metastability of CIGSe based hetero structures is accompanied with the migration of Sodium within the device, mainly the absorber. Thus the ALE impaired solar cell can be repaired due to sodium segregation at the CIGSe-CdS interface initiated by heat light soaking (HLS) under open circuit conditions.

The above mentioned hypothetical aspects were proven in chapter 4 of this cumulative thesis. The key challenge was to differentiate between enhanced surface or enhanced bulk recombination due to ALE in sections 4.1, 4.2, and 4.3. This could not be answered by XPS and TRPL measurements alone and required the deduction from interface recombination dominated solar cells towards surface recombination dominated absorber layers. The applied characterisation methods to absorbers and solar cells from different CIGSe batches with identical physico-chemical properties are introduced and discussed in chapter 3. Voltage

dependent admittance spectroscopy is a suitable method to characterize spatial narrow defect states like interface states and is thus examined more in detail in the subsection 3.2. Based on the measurement results of voltage dependent admittance spectroscopy a simulation model of the electronic device properties was introduced by *SCAPS 3.3.06* in 4.4. The intention of this model is to uncover the electronic properties of interface states in devices with air-light exposed absorbers. In the following section 2 the physical fundamentals of chapter 3 and 4 are given. A conclusion of the thesis is drawn in chapter 5, suggestions for prospective investigation methods with preliminarily results are compiled in chapter 6.

2. Fundamentals

This section deals with the physical background of the functionality of solar cells and the basics for the investigative study of the ALE effect on CIGSe layers and solar cells in this work. First, section 2.1 outlines the fundamental properties of $\text{Cu}(\text{In,Ga})\text{Se}_2$ solar cells. Subsequently, in section 2.2 the principles of a $\text{p-n}^- \text{-n-n}^+$ -hetero-junction are examined by means of a hypothetical hetero-structure given in Table A - 4. Finally section 2.3 gives an overview about the loss mechanisms in CIGSe solar cells.

2.1. $\text{Cu}(\text{In,Ga})\text{Se}_2$ -based solar cells

In the following section the material properties of the investigated thin film solar cells are presented. The structure and the fabrication methods are demonstrated in section 2.1.1 on the basis of a standard laboratory cell manufactured at the Martin-Luther-University (MLU). Subsequently, in sections 2.1.2 - 2.1.5 the specifics of the object of interest in this work, namely the CIGSe absorber are examined more in detail. The chapter will be closed with an overview of the possible recombination domains for this type of solar cell in section 2.3.

2.1.1. Architecture and preparation techniques

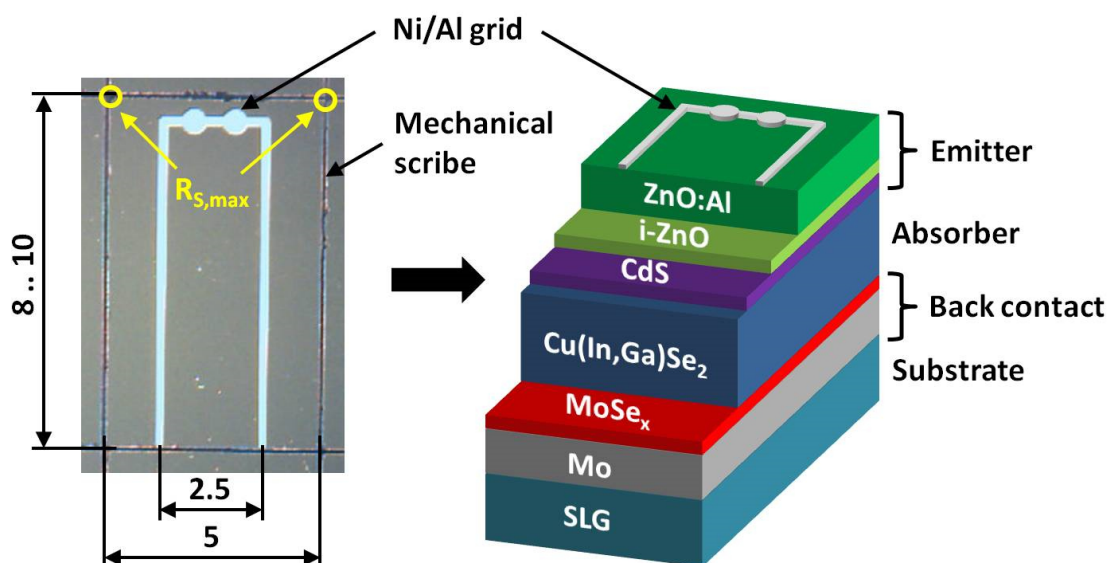


Figure 2 Left hand side: Topview of a thin film solar cell manufactured at the MLU and defined by mechanical scribing. Stated dimensions are in units of mm. Right hand side: A not true to scale schematic depiction of the layer stack. Thickness specifications of the films are written within the text.

The left hand side of Figure 2 presents the top view of a typical Cu(In,Ga)Se_2 thin film solar cell fabricated at the MLU. Next to it on the right hand side of Figure 2 is a schematic sketch of the underlying layer stack. The functionalities and characteristics of each layer are briefly declared in the following subsections, more detailed descriptions can be derived from the literature [50-53].

Molybdenum coated SLG substrate

Next to the budget-friendly availability a further advantage of soda lime glass (SLG) is the very well matching thermal expansion coefficient with respect to Mo and CIGSe. With a fraction of $\approx 15\%$ Na_2O the incorporation of Na into the CIGSe layer via diffusion from the SLG substrate is a long-standing standard method (see section 2.1.3). Coating of 1 to 3 mm SLG slices with 0.5 to 1 μm Mo is usually performed by sputtering, less common by thermal evaporation. Reasons, why Molybdenum serves as the back-contact, are due its stability in a Selenium atmosphere, no incorporation into the CIGSe layer and cost effectiveness [50]. However, during the In,Ga rich growth (i.e. the first stage in Figure 3) of the CIGSe absorber the formation of MoSe_x ($x \approx 2$) at the Molybdenum surface takes place [54]. This reaction is further catalyzed by the presence of Na [55, 56]. Typical MoSe_x thicknesses from 10 to 100 nm are observed forming an interfacial layer between CIGSe and Mo [55, 57, 58].

Cu(In,Ga)Se_2 absorber layer

There exist manifold variants of manufacturing CIGSe thin films with the aim to improve the cost effectiveness or process stability. Thus, several deposition techniques have been demonstrated from selenization of sputtered In, Ga and Cu layer stacks, over inkjet printing through to electro deposition [52]. However, the co-evaporation of the elemental constituents is the common method applied in various laboratories [4]. As well, co-evaporation can be categorized into subgroups like 1-stage, 2-stage or 3-stage processes [50, 52].

In the following the 3-stage process, shown in Figure 3, is described more in detail, because this is the standard technique of growing CIGSe absorbers at the MLU [59]. The 3-stage process was invented by the *National Renewable Energy Laboratory* (NREL) in the mid of the 1990's [60]. During the first stage a $(\text{In,Ga})_x\text{Se}_y$ ($x \approx 2$, $y \approx 3$) precursor is formed by evaporating elemental In and Ga under Selenium excess. In the second stage the deposition of In and Ga is intermitted and Cu + Se is supplied until the CIGSe layer becomes copper rich $[\text{Cu}]/([\text{In}] + [\text{Ga}]) = \text{CGI} > 1$. For an enhanced copper diffusion the substrate temperature is increased close to the softening point of the SLG substrate (at the MLU: $T \approx 625$ °C).

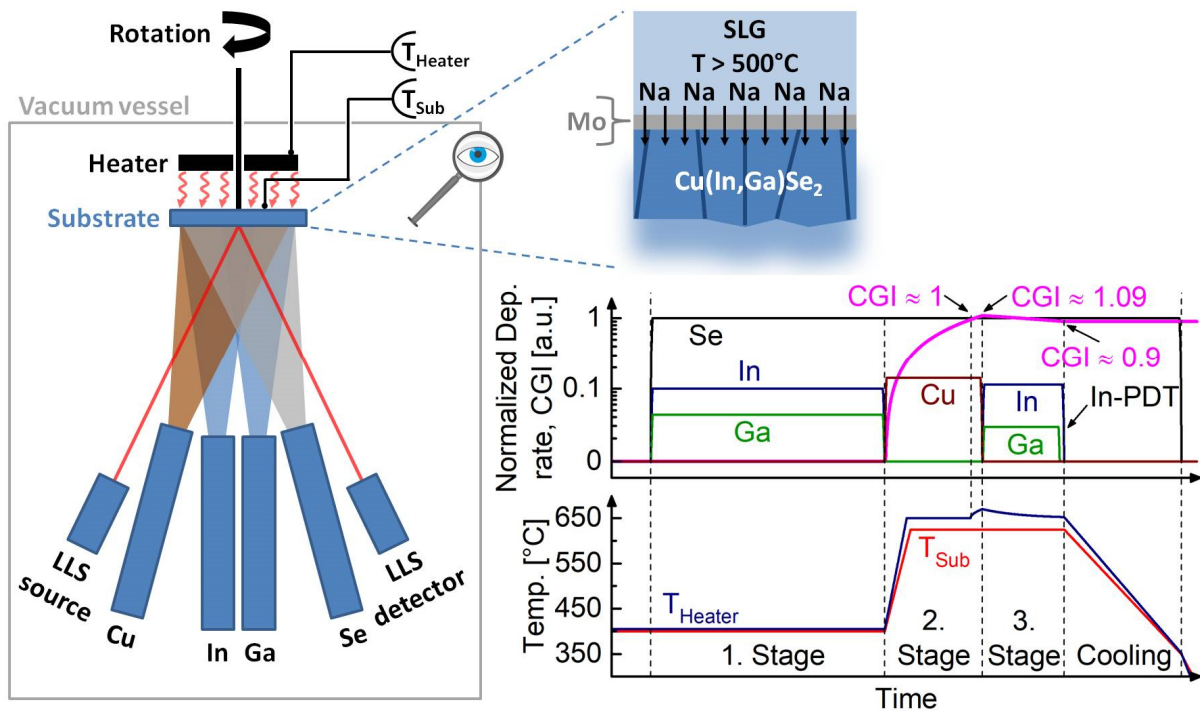
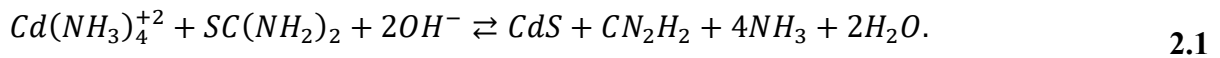


Figure 3 Left hand side: Principle of the co-evaporation process technique for manufacturing Cu(In,Ga)Se_2 absorber layers. Copper fraction within the CIGSe layer becomes controllable with a laser light scattering (LLS) system and by monitoring the temperature of the substrate heater (T_{Heater}). Right hand side: Magnification of the substrate, illustrating the incorporation of Sodium from the SLG substrate into the growing CIGSe layer at high process temperatures and the time regime of the 3-stage process. The deposition rates are normalized to the Se-rate.

Ordinarily, the CGI should not exceed 1.09 at the end of the second phase to achieve high quality solar-grade CIGSe layers at the end [61]. In the third stage the final copper poor composition of $\text{CGI} \approx 0.9$ is defined by evaporating again In + Ga + Se in the absence of a Cu-flux. Additionally, at the end of the 3rd phase a finishing is performed by depositing a few atomic layers of In + Se (In-PDT) [62]. Afterwards, the sample cools down to 350°C under Se supply and thereafter in vacuo to room temperature [59]. For composition control during growth visible red laser light scattering (LLS) is utilized, indicating the stoichiometric points ($\text{CGI} = 1$) by knees in the monitored curves of the scattered light intensity. The reason for an altered scattering amplitude is the formation and vanishing of a quasi-liquid Cu_xSe ($x \approx 2$) phase changing the optical properties and morphology of the CIGSe surface [63]. It is presumed that Cu_xSe enhances diffusion processes for recrystallisation. Monitoring the temperature (heating power) of the substrate heater as depicted in Figure 3 supports the signal processing of the LLS system. With infra-red LLS ($E_{\text{ph}} < E_{\text{g,CIGSe}}$) the thickness of the grown CIGSe layer becomes determinable.

CdS buffer layer

The emitter stack of the completed solar cell in Figure 2 begins with a CdS layer of usually 50 nm thickness. Providing CIGSe with a CdS coating is performed in general by the chemical bath deposition (CBD) technique, due to its reliability of achieving highly efficient solar cells [52]. Reasons are founded on (1) closed dense layers even for layer thicknesses in the range of 10 nm [64] as well as (2) the removal of natural oxides from the CIGSe surface [50, 65]. The parent substances for the CdS-CBD process are $\text{Cd}(\text{CH}_3\text{COO})_2$ (cadmium acetate), $\text{CH}_4\text{N}_2\text{S}$ (thiourea) and NH_4OH (ammonia solution) dissolved in water. At the beginning of the deposition process the CIGSe samples are embed into the solution at room temperature (cold start [50]). Subsequently, the beaker with solution + samples is immediately inserted into a water bath of 60 °C. After 8 min a ca. 50 nm thick CdS layer has been formed and the deposition process is interrupted by taking out the samples from the beaker. Abundant residuum on the CdS surface is rinsed off with deionised water and the samples are dried with a nitrogen stream. The heterogeneous CdS growth is constituted by the following chemical equation [66]:



The functionality of the CdS buffer layer are after [50] (section 5.2.8) and [53] (section 7.3.4):

1. Protecting the CIGSe surface (hetero junction) against chemical reactions or damages initiated by the ZnO deposition process.
2. Type inversion of the CIGSe near-surface region either due to diffusion of Cd into the CIGSe, creating Cd_{Cu} donor states or due to the removal of natural oxides, leaving positive charged states behind at the very CIGSe surface.
3. Making the provisional product CIGSe + CdS storable and transportable even under ambient conditions.
4. Passivation of recombination active surface states by impurities like oxygen or hydrogen.

Attaching to bullet item 3, it has been revealed that ALE of CdS covered CIGSe layers does not diminish the quality of completed solar cells.

Unfortunately CdS has a direct band gap of $E_{\text{g,CdS}} \approx 2.4$ eV, limiting the quantum efficiency of solar cells within the short wavelength range of the solar spectrum. Further, the bad

reputation of Cadmium motivates the research of alternative buffer layers like Zn(O,S), (Zn,Mg)O and In₂S₃ to mention the established ones [4, 67, 68].

ZnO window and Ni/Al metal grid

A bi-layer consisting of 50 – 100 nm high-resistance undoped i-ZnO (i denotes intrinsic) and 350 – 400 nm low-resistance Al-doped ZnO:Al finalises the emitter of the solar cell in Figure 2. In general film deposition is realised via sputtering methods of pure ZnO and ZnO:Al₂O₃ targets. Both layers exhibit a high transparency in a wide range of the solar spectrum due to the ZnO's wide band gap of $E_{g,ZnO} \approx 3.3$ eV. It is proposed by Rau and Schmidt [69] that the low lateral conductivity of i-ZnO separate inferior operating locations or micro-shunts from higher performing regions of the solar cell, resulting in increased fill factor and open circuit voltage. The role of the highly conductive ZnO:Al is to ensure a loss-free transport of the collected photo current to the grid fingers. Prerequisite in that case is a high doping level. However, if the Al doping concentration of ZnO:Al reaches the percentage range, light absorption by free carriers comes into play. Increasing the ZnO's absorptivity of longer wavelengths ($\lambda \geq 1 \mu\text{m}$) and reducing the solar cell's quantum efficiency in this spectral range [50]. Thus, electrical and optical properties have to be balanced for solar grade ZnO:Al layers. Considering a homogenous ZnO:Al layer with a free carrier concentration of $n = 5 \cdot 10^{20} \text{ cm}^{-3}$ and a mobility of $\mu_n = 20 \text{ cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$ then with the conductivity $\sigma = q \cdot \mu_n \cdot n$ the specific resistance results to $\rho_s \approx 6 \cdot 10^{-4} \Omega \cdot \text{cm}$, which is 4 orders of magnitude higher than the resistivity of aluminium or copper. The region of maximum series resistance $R_{s,\text{max}}$ is indicated by the yellow open circles in Figure 2 located at the top corners of the solar cell, approximately 1.5 mm away from the metal grid. Additionally, further the series resistance is increasing towards the left and right edges as well as towards the middle of the two longer grid fingers. Due to variable current paths the calculation of the local dependent series resistance is not trivial and treated further in section 3.2.

The metal grid is deposited by thermal evaporation in vacuum and consists of a 50 nm Ni layer followed by a ca. 1.5 μm Al layer and finally again a 50 nm Ni cap-layer. Improved adhesion and prevention to the formation of Al₂O₃ at the ZnO/Al interface is ensured by the first Ni coating. Capping the Al layer with a second Ni layer increases the resilience of the metal grid to injuries by contacting the solar cell with measurement probes for electrical characterisation.

2.1.2. Basic properties of Cu(In,Ga)Se₂ absorber layers

Cu(In,Ga)Se₂ is a I-III-VI₂ compound semiconductor and crystallises in the tetragonal chalcopyrite structure, depicted in Figure 4 a). This structure type can be deduced by stacking 2 unit cells of the zinc blende (ZnS) structure on top of each other. Thus, the ratio of the lattice constants in Figure 4 a) results to $c/a \approx 2$. Due to the different binding strength of Cu-Se and (In,Ga)-Se the tetragonal arrangement is distorted and the c/a -ratio amounts ≈ 2.01 for CIGSe and ≈ 1.96 for CGSe [70, 71]. Further, it can be derived from Figure 4 a) that the coordination number of each element is 4. Hence, the metal atoms (Cu, In, Ga) hold 4 bonds with Selenium, whereas every Se atom holds 2 bonds with 2 different Cu atoms and further 2 bonds with 2 different group-III atoms. The valence band is formed by hybridisation of the Cu 3*d*- and Se 4*p*-orbitals. Group-III *s*-orbitals and Selenium *sp*-hybrid states provide the conduction band. At the Γ -point in the centre of the Brillouin zone the valence band maximum and conduction band minimum can be found, allowing a direct transition for the smallest energy gap [16, 50, 72].

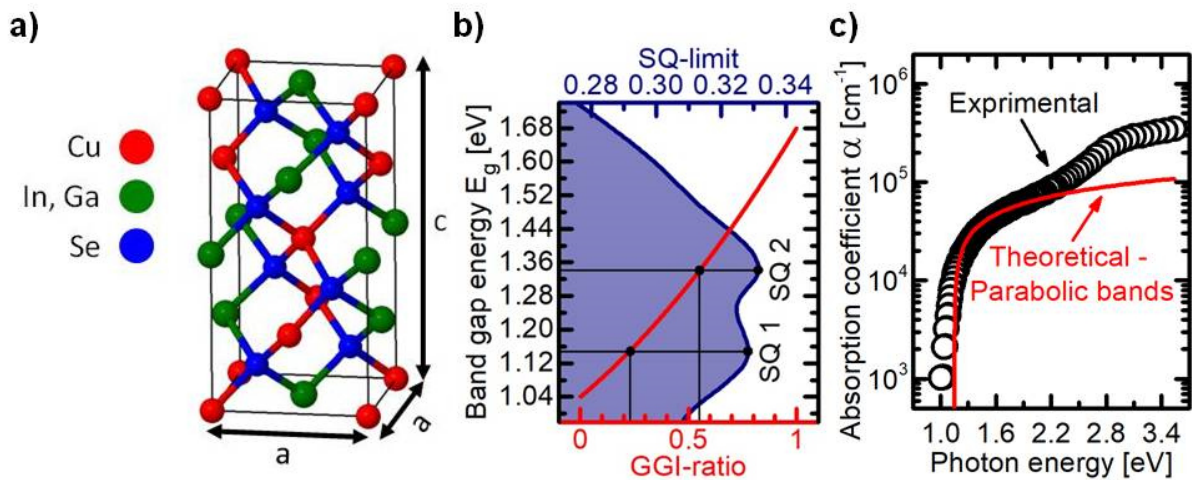


Figure 4 (a) Unit cell of the tetragonal chalcopyrite structure compiled with the software *PDF4* using ICDD-No./Ref.: 04-016-4109. (b) Band gap energy as a function of the GGI-ratio calculated after equation 2.2, with SQ 1 at $E_g = 1.15$ eV, GGI = 0.23 and SQ 2 at $E_g = 1.34$ eV, GGI = 0.55 matching the local maxima of the Shockley-Queisser limit, drawn up with computed values tabulated in Ref. [73]. (c) Theoretical approximated optical absorption coefficient with equation 2.3 for an optical band gap of $E_g = 1.15$ eV (GGI = 0.23). For comparison experimental data from spectroscopic reflectance and transmittance measurements examined on a CIGSe layer with 250 nm thickness and a GGI-ratio of 0.23 in Ref. [74].

Material composition

As previously mentioned, solar grade CIGSe layers are fabricated with a final Cu-poor composition ($\text{CGI} \approx 0.9$). This causes an intrinsic p-type doping of the CIGSe material due to the formation of shallow acceptor states in the form of copper vacancies V_{Cu} . Typical doping densities are in the range of 10^{15} to 10^{17} cm^{-3} [75-79], by contrast for a CGI-ratio of 0.9 the stoichiometry would account for a density of $V_{\text{Cu}} \approx 10^{21} \text{ cm}^{-3}$. Hence, the formation of compensating donor states like In_{Cu} or Ga_{Cu} antisites in Table 1 are imaginable. However, V_{Cu} exhibits the lowest formation energy of the latter impurities under Se excess growth [80-82], and thus the CIGSe layer becomes intrinsic p-type with doping densities conformable to solar cell applications.

For CIGSe there is no miscibility gap with regard to Indium and Gallium, wherefore elemental ratios of $[\text{Ga}]/([\text{Ga}] + [\text{In}]) = \text{GGI} = 0 \dots 1$ can be arbitrary adjusted. Correspondingly the band gap can be varied in the range from 1.04 eV for CIGSe ($\text{GGI} = 0$) to 1.68 eV for CGSe ($\text{GGI} = 1$). The band offsets $\Delta E_{\text{V,C}}$ between CIGSe and CGSe are obtained by first-principle calculations with $\Delta E_{\text{V}} \approx 0.04 \text{ eV}$ and $\Delta E_{\text{C}} \approx 0.6 \text{ eV}$ [82]. Hence, the Ga content in CIGSe effects mainly the position of the conduction band. The band gap energy as a function of the Ga content can be given by the following equation [83]:

$$E_g(x) = (1 - x) \cdot 1.04 \text{ eV} + x \cdot 1.68 \text{ eV} - b \cdot x \cdot (1 - x) \quad 2.2$$

where x denotes the GGI-ratio and $b \approx 0.21 \text{ eV}$ the bowing parameter. As depicted in Figure 4 b) this gives the ability to tune the CIGSe band gap in terms of matching the local maxima of the Shockley-Queisser (SQ) limit. The SQ limit is derived from the principle of detailed balance of single junction solar cells and qualifies the highest achievable power conversion efficiency as a function of the band gap energy [84]. Recent calculation of the SQ limit considering an air mass spectrum of AM 1.5 G² reveals 2 local maxima in Figure 4 b) with 32.85% for $E_g = 1.15 \text{ eV}$ (SQ 1) and 33.16% for $E_g = 1.34 \text{ eV}$ (SQ 2) [73].

² The AM 1.5 G spectrum defines the spectrum of solar light after passing through 1.5 thicknesses of the atmosphere directly and an additional fraction of scattered light. Thus, compared to direct irradiation (AM 1.5 D) the AM 1.5 G spectrum reveals an increased intensity in the short wave length range. The calculation of the detailed balance limit was conducted by Shockley and Queisser with the simplification of a 6000 K black body spectrum, modelling the solar light. This assumption delivers 1 maximum at 30.66% power conversion efficiency for $E_g = 1.32 \text{ eV}$ and an overestimation of the efficiency limit for $E_g > 2 \text{ eV}$. Instead, using the AM 1.5 G spectrum 2 maxima with increased efficiencies appear, caused by characteristic absorption lines and high extinction of the ultra violet spectral range [73].

Apart from the SQ-limit, commonly CIGSe solar cells with an integral GGI-ratio in the range of ≈ 0.3 reveal the highest conversion efficiencies. Increasing the Ga content further usually degrades the solar cell efficiency, which can be referred either to higher recombination losses within the bulk caused by Ga_{Cu} antisites or an unfavourable band alignment and Fermi-level position at the CIGSe/CdS interface [85-89].

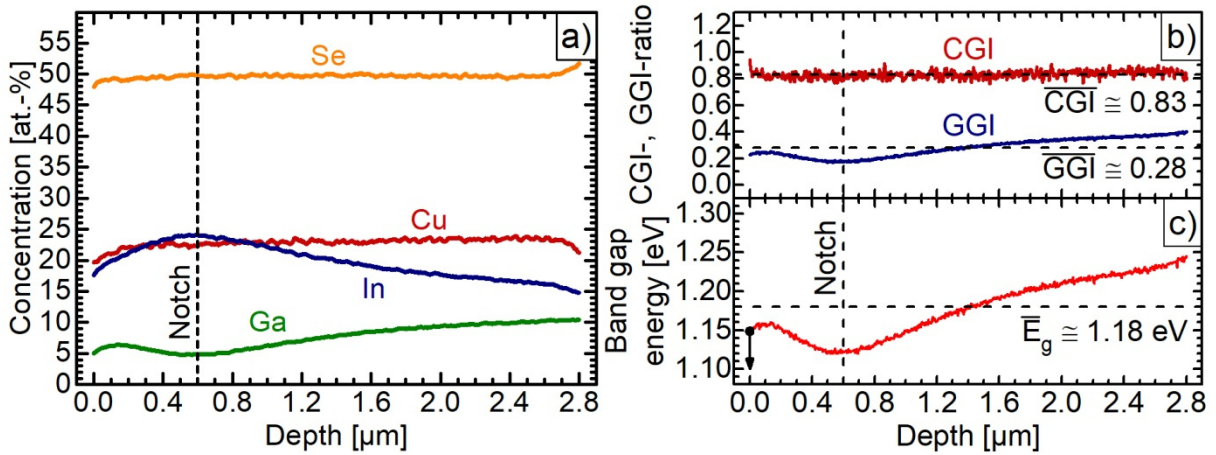


Figure 5 (a) GDOES-measurement of the depth dependent elemental concentrations obtained on a MLU standard CIGSe sample. (b) CGI- and GGI-ratio deduced from the elemental concentrations of (a). (c) Band gap energy E_g as a function of depth calculated with the GGI-ratio in (b) and equation 2.2.

A noteworthy feature of CIGSe layers fabricated with a 3-stage process is the self-adjusted V-shaped depth dependent Ga and In concentrations. Figure 5 b) shows the GGI-ratio as a function of depth obtained on a MLU standard CIGSe sample by glow discharge optical emission spectroscopy (GDOES). With equation 2.2 the band gap energy and in particular the energetic position of the conduction band varies likewise with the GGI-ratio in Figure 5 c). Reason for the graded band alignment is the sequence arrangement of the 3-stage process. During the 2nd stage reaction of $\text{Cu} + \text{Se}$ with the $(\text{In,Ga})_2\text{Se}_3$ precursor causes a directed diffusion of Cu-atoms towards the back contact and in the 3rd phase an opposite diffusion of Cu towards the surface. Migration of Cu depends on film stoichiometry and temperature. The movement of Cu is ensured either over vacancies V_{Cu} (Cu-poor) or via interstitial lattice sites Cu_i (Cu-rich) [90]. In the same way a diffusion of In and Ga to make space for the incorporation of copper takes place. By ab-initio calculations Witte et al. [91] came to the conclusion that the diffusion barrier of Ga in CIGSe is distinctly above the diffusion barrier of In in CGSe, which is assigned to the different ionic radii of Ga and In [91]. This may explain the observation of Schroeder et al. [92] that Ga diffusion is effected by metal vacancies with V_{Cu} in the Cu-poor phase and V_{In} in the Cu-rich phase. Further the In-diffusibility is found to

be higher than the Ga-diffusibility in the CIGSe host lattice [93]. Hence, the In atoms are more probably driven to the surface due to the incorporation of Cu and a maximum of In-concentration at the notch-position in Figure 5 a) exists. The opposite case can be observed for the Ga-concentration in Figure 5 a). However, in spite of a V-shaped GGI-profile the band gap energy at the surface can be estimated to $E_g \approx 1.15$ eV as indicated by the arrow at zero depth in Figure 5 c).

Effective density of states

The theoretical absorption coefficient $\alpha(\hbar\omega)$ of CIGSe (GGI = 0.23) in Figure 4 c) was computed with equation 2.3. This equation is derived in Ref. [94] from the excitation probability of electrons within the valence band into the conduction band by photons.

$$\alpha(\hbar\omega) = \frac{(2m_{comb}^*)^{\frac{3}{2}}}{2\pi\epsilon_0 c_0 n} \cdot \frac{q^2 p^2}{\hbar^2 m_0^2} \cdot \frac{1}{\hbar\omega} (\hbar\omega - E_g)^{\frac{1}{2}} \quad 2.3$$

After Ref. [95] the matrix element p^2 can be obtained from the following relation $p^2 = m_0/2 \cdot \hbar\omega (m_0/m_{comb}^* - 1)$, where $m_{comb}^* = (1/m_n^* + 1/m_p^*)^{-1}$ is the combined effective mass within the conduction band (m_n^*) and the valence band (m_p^*). For the theoretical absorption coefficient in Figure 4 c) the effective masses were fixed to $m_n^* = 0.1 \cdot m_0$ and $m_p^* = m_0$ with m_0 the mass of free electrons. Further material parameters in equation 2.3 are $E_g = 1.15$ eV the band gap energy and $n = 3$ the refractive index. Physical constants in equation 2.3 are ϵ_0 the dielectric constant, c_0 the vacuum velocity of light, q the elemental charge and \hbar the reduced Planck constant. The photon energy is given with the angular frequency by $\hbar\omega$.

Measurements of Weinert et al. [96] and calculations by Persson [97] confirm the fairly good estimation of $m_n \approx 0.1 \cdot m_0$ and a nearly isotropic character of m_n at the Γ -point. On the other hand the hole mass shows a high anisotropy at the Γ -point due to the non-degeneracy of the valence bands in this point [16, 97]. However, the theoretical curve in Figure 4 c) fits well to the experimental data [74] in the range of 1.2 to 2 eV, accordingly the approximation of $m_p \approx m_0$ should be appropriate for electrical simulations of CIGSe solar cells. Hence, the effective densities of states of the CIGSe material system can be evaluated to $N_C \lesssim 10^{18} \text{ cm}^{-3}$ and $N_V \gtrsim 10^{19} \text{ cm}^{-3}$. In the case of higher photon energies > 2 eV a deviation of theoretical and experimental data in Figure 4 c) is attributed to the modified band curvature for high \vec{k} values; especially the valence band drifts abruptly away from the parabolic approximation [16].

On the other hand, absorption of photons with energies below the band gap energy can be ascribed to Urbach tails due to lattice distortion by thermal vibrations of atoms. Both scenarios can be regarded by extension of equation 2.3 with semi-empirical quantities (see Ref. [50] section 4.2.4).

Defect properties and non-radiative recombination

As listed in Table 1, there is a plethora of possible intrinsic point defects within the CIGSe lattice. Hence, it can be assumed that defect related recombination plays a crucial role on the efficiency of CIGSe solar cells. For the Cu-poor material the preferential defect formation of group-III metals on copper sites denoted with $\text{III}_{\text{Cu}}(0/+1)$ and $\text{III}_{\text{Cu}}(+1/+2)$ as well as the defect complex $(\text{In}_{\text{Cu}} + \text{V}_{\text{Cu}})(0/+)$ can be taken into account. In the case of stoichiometric or Cu-rich material the formation possibility of Cu-interstitials Cu_i as well as Cu_{III} antisites should increase. Calculated transition energies of defects caused by extrinsic dopants or impurities are given in the theoretical studies of Refs. [98-103].

Table 1 Overview of intrinsic point defects within the CIGSe lattice.

Defect	Type	Transition	Defect level E_d		Reference
			CIGSe (III = In)	CGSe (III = Ga)	
V_{Cu}	Acceptor	0/-1	$E_V + 0.03 \text{ eV}$	$E_V + 0.01 \text{ eV}$	[80, 82, 104]
V_{III}	Acceptor	0/-1	$E_V + 0.17 \text{ eV}$	$E_V + 0.19 \text{ eV}$	[80, 82]
		-1/-2	$E_V + 0.41 \text{ eV}$	$E_V + 0.38 \text{ eV}$	
Cu_{III}	Acceptor	0/-1	$E_V + 0.29 \text{ eV}$	$E_V + 0.29 \text{ eV}$	[80, 82, 105, 106]
		-1/-2	$E_V + 0.58 \text{ eV}$	$E_V + 0.61 \text{ eV}$	
III_{Cu}	Donor	0/+1	$E_C - 0.25 \text{ eV}$	$E_C - 0.49 \text{ eV}$	[80, 82, 107-110]
		+1/+2	$E_C - 0.34 \text{ eV}$	$E_C - 0.69 \text{ eV}$	
Cu_i	Donor	0/+1	$E_C - 0.20 \text{ eV}$	$E_C - 0.21 \text{ eV}$	[80, 82, 108, 111]
$\text{In}_{\text{Cu}} + \text{V}_{\text{Cu}}$	Donor	0/+1	$E_C - 0.20 \text{ eV}$	–	[80, 108, 111]

Recombination over trap states within the band gap is treated by the Shockley-Read-Hall (SRH) formalism. Both, radiative and non-radiative trapping processes of charge carriers within the bands are included in the SRH-theory [112]. For solar cells non-radiative recombination is more critical than radiative recombination due to the generation of heat during this recombination process. In theory non-radiative transitions are dominating in the case of a strong electron-lattice coupling [113]. Hence, the energy surfaces of the excited and ground state for a recombination centre are displaced in the configurational coordinate diagram and contact or even intersect each other [114]. Accordingly, reaching the pitch point of the energy surfaces the excited centre can change over to the ground state as shown for the $V_{\text{Se}}^{2+} \rightarrow V_{\text{Se}}^0$ transition in CIGSe by Wei and Zhang [115]. Subsequently, due to multi-phonon interactions the centre relaxes into the equilibrium configuration of the ground state [116]. A quantitative dimension of non-radiative recombination in CIGSe can be obtained by the external quantum efficiency η_{ext} of i.e. electroluminescence (EL) or photoluminescence (PL) measurements at room temperature. The internal luminescence efficiency η_i is given by Ref. [117] to:

$$\eta_i = \frac{\tau_{\text{nrad}}}{\tau_{\text{nrad}} + \tau_{\text{rad}}} \approx \frac{\tau_{\text{nrad}}}{\tau_{\text{rad}}}, \quad \tau_{\text{rad}} \gg \tau_{\text{nrad}} \quad 2.4$$

where τ_{nrad} , τ_{rad} denote the lifetimes due to non-radiative and radiative recombination, respectively. Typical external luminescence efficiencies of CIGSe solar cells with PCE's from 19% to 20% lie in the range of $\eta_{\text{ext}} \approx 3 \cdot 10^{-4} \dots 2 \cdot 10^{-3}$ [118, 119]. Approximating a radiative recombination coefficient of $B \approx 5 \cdot 10^{-11} \text{ cm}^3 \text{ s}^{-1}$ (confirmed by the measured absorption data in Figure 4 c)) and a net doping concentration of $p_0 \approx 10^{16} \text{ cm}^{-3}$ then the radiative lifetime can be approximated with $\tau_{\text{rad}} = (B \cdot p_0)^{-1} = 2 \text{ } \mu\text{s}$. Thus, with the above mentioned external quantum efficiencies and equation 2.4 a lower limit of the non-radiative lifetime can be expected in the range of $\tau_{\text{nrad}} \approx 0.5 \dots 5 \text{ ns}$. An upper limit of τ_{nrad} results to 50 ns under the assumption of an insufficient light emission with $\eta_{\text{ext}} \approx 0.1 \cdot \eta_i$ as observed on silicon solar cells [117].

Charge carrier mobilities

An important role on device simulations plays the mobility of charge carriers, especially in the case of re-modelling admittance measurements. The measured hole and electron mobilities – as pointed out in chapter 1 – range over several orders of magnitude from 0.01 to $1000 \text{ cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$ [27, 28, 120-123]. In consideration of numerous microstructural

imperfections of CIGSe layers scattering at ionized or neutral impurities should dominate the hole and electron mobilities. A compilation of temperature dependent hole mobilities measured by several groups in Ref. [120] reveals (1) a distinct higher hole mobility for single crystal samples with $\mu_p = 100 \dots 1000 \text{ cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$ than for polycrystalline layers with $\mu_p = 0.1 \dots 10 \text{ cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$, which is also confirmed by the results of Ref. [122]. And (2) the temperature dependence of the hole mobility for single crystal CIGSe follows an $T^{-3/2}$ trend as in the utilized simulation model of Paper 4 in section 4.4. The maximum of the hole mobility is found to be at temperatures of $T \lesssim 150 \text{ K}$. However, in the case of polycrystalline films no general tendency of the hole mobility varying with temperature can be observed [120].

The reduced mobilities of polycrystalline samples are ascribed to grain boundaries, acting as barriers especially in the case of lateral current transport like in Hall measurements [122]. But also time of flight (TOF) or voltage dependent TRPL measurements with dominating vertical transport reveal electron and hole mobilities not exceeding the upper limit of $5 \text{ cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$ [120, 121].

2.1.3. Impact of Sodium

As implied in chapter 1, doping of CIGSe layers with alkaline metals (here Sodium) is a crucial process element to achieve high efficiency thin film solar cells. The mechanisms behind the beneficial effects of Sodium are not fully understood. It is ensured that Na increases the majority charge carrier density of CIGSe films by more than 1 order of magnitude [9, 124-126]. Even epitaxial grown CIGSe layers reveal a higher p-conductivity due to Na incorporation [15, 127]. There exist several models to describe the principles of the Na doping effect:

1. Neutralizing of compensating donor defects at interfaces, grain boundaries or lower-dimensional lattice defects within the bulk. Either by hindering the formation of donor defects like In_{Cu} due to occupation of V_{Cu} during growth [19, 128] or by reducing the amount of V_{Se} due to a higher incorporation of Se via NaSe_2 as well as a Na-catalyzed oxygenation of V_{Se} creating O_{Se} acceptor states in contact with ambient air [48, 129-131].
2. Formation of acceptor-like impurity levels by occupation of lattice sites like Na_{In} or Na_{Se} . However, Na_{Se} is energetically levelled nearly below the conduction band edge

giving an inefficient acceptor level [99, 100]. Thus, it can be considered that neutralizing V_{Se} outweigh the enhancement of p-type doping due to Na_{Se} .

3. As has been shown by Yuan et al. [132] the solubility of Sodium within the CIGSe crystal system is increased at high process temperatures ($T \gtrsim 400$ °C). The soluble Sodium concentration

$$c(Na) = N_s \exp\left\{\frac{\Delta H}{k_B T}\right\} \quad 2.5$$

is determined by the available sites N_s of the host system, the formation energy ΔH and the temperature T . Occupation of copper vacancies $Na + V_{Cu} \rightarrow Na_{Cu}$ shows the lowest formation energy. According to equation 2.5 during cooling down to room temperature the solubility of Sodium declines, and precipitation of Na at interfaces or grain boundaries takes place. Hence, an increased amount of V_{Cu} is existent within the bulk, scaling up the majority charge carrier density [132].

As previously mentioned the formation of $MoSe_x$ at the back contact is promoted by Na, further effects due to Na-doping are listed below.

1. CIGSe films grown in the presence of Na tend to prefer the desired 112-orientation [133], resulting in a higher saturation current density compared to films with a preferred 220/204-orientation [134].
2. Sodium expands the α -phase region of the binary CIGSe phase diagram towards lower copper concentrations [53].
3. Due to the formation of Na_2Se_x during the deposition process the development of the CIGSe phase is decelerated [135], but on the other hand the incorporation of Se is increased [136], reducing likewise the emergence of compensating V_{Se} defects.
4. Sodium impedes the Ga-In interdiffusion during the growth process, resulting in a more pronounced Ga gradient for films grown in the presence of Na [137].

2.1.4. Incorporation of Sodium

Commonly doping CIGSe with Sodium is performed through to 3 different methods with: (1) diffusion from the SLG substrate, (2) pre-deposition of a NaF precursor and (3) post-deposition of NaF directly afterwards the CIGSe growth process.

1. Diffusion from the SLG substrate

This technique requires high substrate temperatures close to the softening point of the SLG [48]. By analogy with Figure 3 during the MLU standard process this condition is reached at the beginning of the second stage, where the substrate temperature is heated up from 400°C to 625°C. The first barrier for the out-diffusing Na ions is the Mo back contact. It is presumed that the transport of Na ions takes place over Mo grain boundaries [50]. Therefore, the sputter conditions of the Mo layers effectuate the incorporation of Sodium into CIGSe layers. Optimal electronic properties of CIGSe solar cells are obtained with a Sodium content of 0.1 at.-% [138, 139]. To achieve this optimum of Na-concentration it is either necessary to adapt the Mo layer to the CIGSe growth process or vice versa [140, 141].

2. NaF precursor

The usage of alternative substrates without Sodium or lower process temperatures necessitates other strategies for incorporation of Sodium. One possibility is given by evaporating a thin NaF precursor in the range of few to multiple ten nano-meters on top of the Mo back-contact before starting the CIGSe deposition process. Similar to the SLG technique, the presence of Sodium during formation of the CIGSe film influences the film structure (preferred 112-orientation) and enhances grain growth [142, 143].

3. NaF post-deposition treatment (PDT)

Actually to allow Ga diffusion at low substrate temperatures Rudmann et. al. [137] invented the PDT-technique. In that case after processing the CIGSe film an additional deposition sequence follows by evaporating NaF + Se on top of the CIGSe surface, where the in-diffusion of Sodium takes place. The additional Selenium flux forestalls the loss of Selenium and its compounds of the CIGSe layer during PDT. Figure 6 shows the beneficial impact of Na-PDT on the TRPL-lifetime of a bare CIGSe layer even after an exposition period of 1 day to ambient air before Na-PDT. On the other hand shows Figure 6 the detrimental impact of ALE on the TRPL-lifetime after Na-PDT. Instead, no reduction of the TRPL-lifetime is observable in the case of CIGSe layers without Na (not shown).

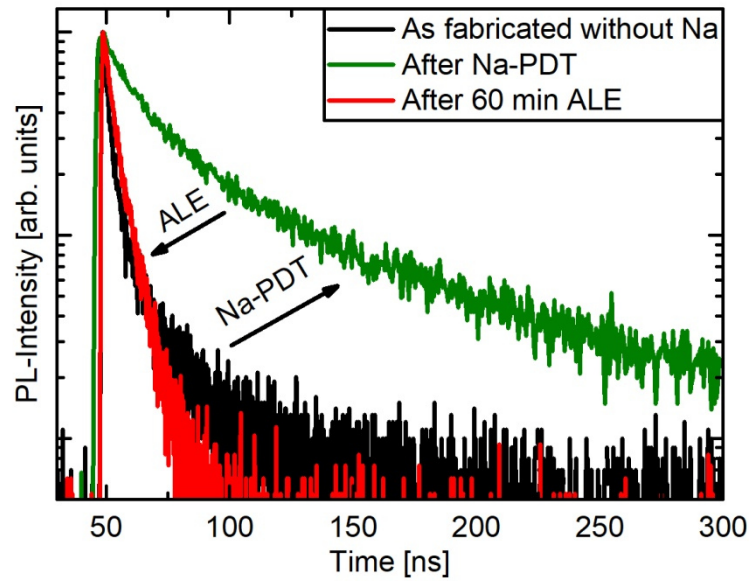
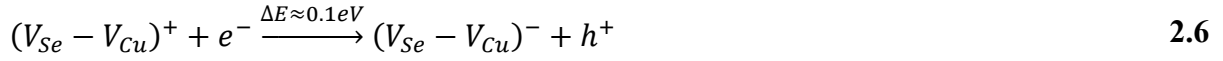


Figure 6 Impact of Na-PDT and ALE on the photoluminescence transient behaviour of a very same CIGSe sample. Na-PDT was performed after 1 day storage time of the bare CIGSe layer in ambient air and darkness.

2.1.5. Metastable properties

A unique characteristic of CIGSe solar cells is the occupation of different states depending on the history of illumination. Usually the J-V-parameters of completed solar cells are improving after light-soaking (LS), which is explained by an increased doping density of the CIGSe film [144]. The metastable relaxation of the solar cell takes place during dark annealing (DA) at room temperature or above. LS with red light³ below the absorption edge of the CdS film gives the ability to separate the light induced modification of the absorber layer from the light induced modification of the buffer/window layers. In the following the widely accepted metastability model of Lany and Zunger [145] is introduced. This model is based on the configurational change of the di-vacancy complex ($V_{Se}-V_{Cu}$) due to the following reactions with holes (h^+) or injected electrons (e^-).

³ Next to the red light effect there exists also a blue and white light effect, implying metastable properties as well for the emitter layers. However, not only light causes metastable changes of CIGSe devices, correspondingly similar modifications of CIGSe solar cells are observed under voltage biasing in forward direction (\approx light soaking) and in reverse direction (\approx dark annealing) For further information see Ref. [50] sections 6.2.4.3 – 6.2.4.7.



Equation 2.6 describes the conversion from a donor to an acceptor state due to electron injection by LS and equation 2.7 the reverse reaction due to DA (relaxing). Both donor and acceptor configurations are shallow levels and can severely modify the majority charge carrier density. The theoretical predicted activation energy in equation 2.7 is experimentally well confirmed [146, 147]. A problem of the Lany-Zunger model is the high formation energy of V_{Se} for copper poor materials [148], wherefore the required concentration of V_{Se} is debatable. An extension of the Lany-Zunger model is proposed by Erslev et al. [149] involving the In_{Cu} antisite interchanging electrons with the V_{Se} vacancies. Their model is founded on the results generated by capacitance spectroscopic methods, where less formation of deep defects after LS for samples containing Na is observed [149]. In that context the role of sodium is assumed to reduce the lattice disorder caused by In_{Cu} antisites and changing equally the configuration of In_{Cu} to an energy level above the conduction band minimum, reducing the deep defect concentration [107, 149].

2.1.6. Sample preparation for the present study

After providing the background of CIGSe solar cells in the following the manufacturing and handling of samples for ALE studies is described. In this work solely CIGSe samples were investigated with Sodium incorporated from the glass substrate. The investigated solar cells and CIGSe absorber layers of this thesis were grown on a commercially available Mo laminated SLG substrate from *Guardian Thalheim GmbH*. For manufacturing CIGSe films the 3-stage co-evaporation process was applied. After preparation the final ratios of GGI ≈ 0.3 and CGI ≈ 0.85 were determined by energy dispersive X-ray spectroscopy (EDX) on a reference sample of the batch. In the case of solar cells the CBD-CdS process was conducted under a strong dimmed illumination of the laboratory to avoid further unwanted ALE of the uncoated CIGSe layers. This was additionally promoted by preserving the samples in light tight cases. In contrast to section 2.1.1 the i-ZnO and ZnO:Al window layers were fabricated by reactive sputtering at the *Fraunhofer IMWS*. Finally, the deposition of the metal grid for electrical contacting was conducted by electron beam evaporation of Ni and Al in vacuum.

2.2. The p-n⁻-n-n⁺-hetero-junction

To investigate the principles of the functionality of a CIGSe solar cell in the subsequent chapters, this section deals with the p-n⁻-n-n⁺-hetero-junction formed in a CIGSe solar cell with the layer arrangement depicted on the right hand side in Figure 2. The particular domains can be attributed to (1) the p-type CIGSe absorber with an effective acceptor density denoted by $N_{A,a}$. Followed by (2) the weakly doped (n⁻) CdS buffer layer with an effective donor density of $N_{D,b}$. Thereupon forms (3) the moderate n-doped i-ZnO, the high resistive window (hrw) layer with $N_{D,hrw}$. Finally (4) the highly doped (n⁺) AZO with $N_{D,lrw}$ donors completes the solar cell, where lrw denotes low resistive window. The index by upper case characters indicates the type of dopants (A: Acceptor, D: Donor) and lower case characters indicate the functional layer (a: absorber, b: buffer etc.) of the solar cell. The relevance of each layer is discussed in section 2.1.

In contrast to a homo-junction the semiconducting materials are differing in their electro-physical properties with main focus on the band gap energies $E_{g,i}$, the dielectric constants $\epsilon_0\epsilon_{r,i} = \epsilon_i$ and the electron affinities $\chi_{e,i}$ ($i = a, b, hrw, lrw$). These quantities for the respective layer are given in Table A - 4 in the form of a default solar cell model for simulation and calculation of electrical device characteristics.

A requirement to generate the band diagram in the vicinity of the junction like in Figure 7 d) is the alignment of the electrostatic potential ϕ_i within the space charge region (SCR) of the respective layer ($i = a, b, hrw, lrw$). In Figure 7 a) it is assumed that the SCR indicated by the red shading in between absorber/buffer/hr-window is formed by stationary charges due to the depletion of mobile majority charge carriers, which are diffusing into opposite (p-n) or lower (n-n⁺) doped layers at the junctions.

Because of the small thickness d_b and the low net doping concentration $N_{D,b}$ (compensating defects) of the CdS buffer layer it is highly probable that this layer is completely depleted. The latter case can be taken into account if the following inequality is fulfilled.

$$d_b < \frac{\epsilon_b}{\epsilon_a} \sqrt{\frac{2\epsilon_a N_{D,b}}{q^2 N_{A,a} (N_{A,a} + N_{D,b})} \left(\Delta E_C + E_{g,a} - k_B T \ln \left[\frac{N_{C,b} N_{V,a}}{N_{D,b} N_{A,a}} \right] \right)} \quad 2.8$$

Inequality 2.8 can be derived by solving the static potential for the absorber/buffer junction with an infinite extended buffer layer. The right hand side of the inequality in equation 2.8 represents the depletion width (w_b) of the infinite extended buffer layer, forming at the junction to the absorber. $\Delta E_C = \chi_{e,a} - \chi_{e,b}$ denotes the conduction band offset between buffer

and absorber. A further boundary condition for a complete depleted buffer layer follows from the doping density of the hrw-layer and the different electron affinities of hrw-layer and buffer layer. In the case of a moderate doping of the hrw-layer and with $\chi_{e,hrw} > \chi_{e,b}$ it is highly probable that the buffer layer is depleted as well at the buffer/hr-window junction. With the physical quantities in Table A - 4 the right hand side of equation 2.8 results to 2.2d_b, satisfying the inequality. Further is $\chi_{e,hrw} - \chi_{e,b} = 0.1$ eV, that's why the buffer layer of the default model can be considered as completely depleted. This is a useful boundary condition for solving the potential curve of the p-n⁻-n-hero-junction, formed by the absorber, buffer, and hrw-layer. With the Schottky approximation of abrupt junctions the depletion regions can be simplified to spatial box shaped charge distributions as depicted in Figure 7 a). In equations 2.9 and 2.10 the fixed charges $\rho_i(z)$ are linked via the 1 dimensional Poisson equation to the potential $\varphi_i(z)$ and the electric field \vec{E}_i .

$$-\frac{d^2\varphi_a}{dz^2} = \frac{dE_{z,a}}{dz} = \frac{\rho_a(z)}{\varepsilon_a} = \frac{-qN_{A,a}}{\varepsilon_a}, \quad -w_a \leq z < 0 \quad 2.9$$

$$-\frac{d^2\varphi_i}{dz^2} = \frac{dE_{z,i}}{dz} = \frac{\rho_i(z)}{\varepsilon_i} = \frac{qN_{D,i}}{\varepsilon_i}, \quad \begin{cases} i = b & 0 \leq z < d_b \\ i = hrw & d_b \leq z \leq (d_b + w_{hrw}) \end{cases} \quad 2.10$$

The right hand side of equations 2.9 and 2.10 are valid for the depletion regions of the particular layers. Spatially, the borders of the space charge region are localized at w_a within the p-doped absorber and w_{hrw} within the n-doped high resistive window. Under the made assumptions the potential curve of the particular depletion regions can be derived to

$$\varphi_a(z) = \frac{qN_{A,a}}{2\varepsilon_a}(z + w_a)^2 \quad 2.11$$

$$\varphi_b(z) = -\frac{qN_{D,b}}{2\varepsilon_b}z^2 + \frac{qN_{A,a}}{\varepsilon_b}w_az + \varphi_a(0) \quad 2.12$$

$$\varphi_{hrw}(z) = -\frac{qN_{D,hrw}}{2\varepsilon_{hrw}}(z - d_b)^2 + \frac{q(N_{A,a}w_a - N_{D,b}d_b)}{\varepsilon_{hrw}}(z - d_b) + \varphi_b(d_b). \quad 2.13$$

Accordingly, it follows with $\varphi \propto z^2$ a quadratic dependence of the potential from the depth. The boundary conditions of equations 2.11 - 2.13 are defined by the electric field with $E_z(z = -w_a) = E_z(z = d_b + w_{hrw}) = 0$ as well as $\varepsilon_a E_z(z \rightarrow 0^-) = \varepsilon_b E_z(z \rightarrow 0^+)$ and $\varepsilon_b E_z(z \rightarrow d_b^-) = \varepsilon_{hrw} E_z(z \rightarrow d_b^+)$. Further boundary conditions are the continuity of the potentials $\varphi_a(z=0) = \varphi_b(z=0)$, $\varphi_b(z=d_b) = \varphi_{hrw}(z=d_b)$, which is evident from Figure 7 b) and c). A partial depletion of the high resistive window can be tested by finding the zero z_0 of

the negative derivation of equation 2.13 with $-d\phi_{hrw}(z)/dz = E_{z,hrw} = 0$. If $z_0 < d_b + d_{hrw}$ the latter condition becomes true and the high resistive window can be considered as partially depleted, which holds for the model in Table A - 4. In Figure 7 c) the resulting alignment of the potential curve at thermal equilibrium ($T = 300$ K) is depicted for this hetero-structure, where

$$\begin{aligned} qV_{bi} &= q\Delta\phi_{SCR} = q\phi_a(z \leq -w_a) - q\phi_{lrw}(z \geq d_b + w_{hrw}) \\ &= E_{g,a} - k_B T \ln \left[\frac{N_{C,lrw} N_{V,a}}{N_{D,lrw} N_{A,a}} \right] \end{aligned} \quad 2.14$$

denotes the built-in voltage. If an external voltage V_{ext} is applied to the potential curve in Figure 7 c) the built in voltage V_{bi} is either weakened (forward bias) or enhanced (reverse bias). Hence, the voltage dependent potential drop over the complete junction follows with $\Delta\phi_{SCR} = V_{bi} - V_{ext}$. In consequence the depletion width w_a of the absorber becomes a function of the external voltage too. By inserting equations 2.11 and 2.13 into equation 2.14 and utilizing the charge neutrality condition:

$$0 = N_{D,b}d_b + N_{D,hrw}w_{hrw} - N_{A,a}w_a \quad 2.15$$

the depletion width w_a within the absorber can be derived to:

$$w_a(V) = \delta d_b \left(\sqrt{1 + \beta + 2\vartheta \frac{\Delta\phi_{SCR}(V)}{\varphi^*}} - 1 \right). \quad 2.16$$

For a clearer arrangement the Greek symbols in equation 2.16 are substitutions and given by

$$\begin{aligned} \delta &= \frac{\varepsilon_{hrw}/\varepsilon_b - N_{D,b}/N_{D,hrw}}{\varepsilon_{hrw}/\varepsilon_a + N_{A,a}/N_{D,hrw}} \\ \beta &= \frac{N_{D,b}}{\delta N_{A,a}} \\ \vartheta &= \left(\frac{\varepsilon_a N_{A,a}}{\varepsilon_{hrw} N_{D,hrw}} + 1 \right)^{-1} \\ \varphi^* &= \frac{q N_{A,a}}{\varepsilon_a} \delta^2 d_b^2 \end{aligned} \quad 2.17$$

$$\Delta\phi_{SCR}(V) = V_{bi} - V - V_{corr} - \Delta\phi_w$$

where $V_{corr} = k_B T/q$ is a correction term. This correction is based on the screening effect of majority carriers on the electric field at the edges of the depletion region [150].

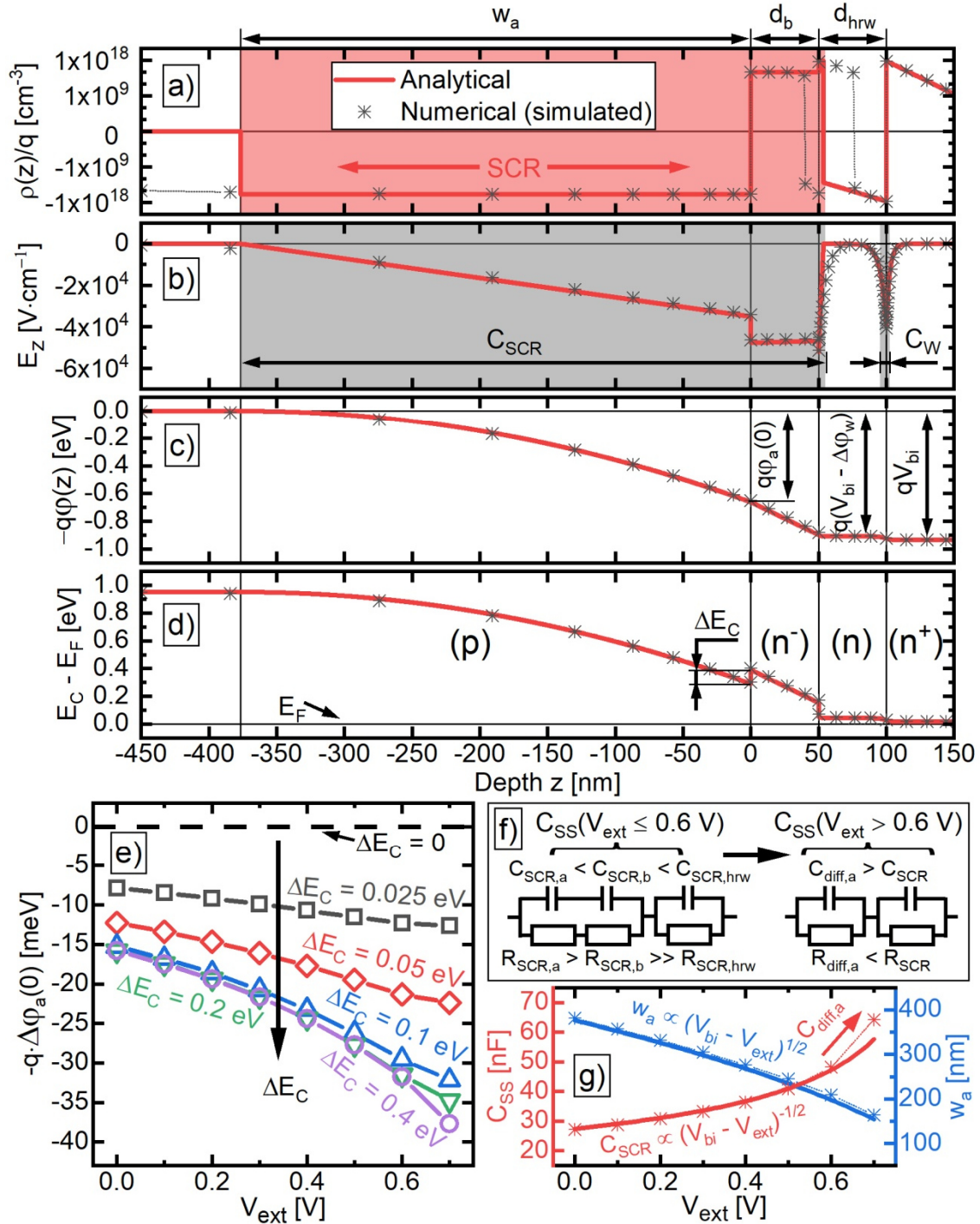


Figure 7 Characteristics of a p-n-n⁺-hetero-junction with (a) the charge distribution, where the red shading indicates the SCR with the Schottky approximation of abrupt junctions, (b) the electric field in z-direction, where the grey shadings indicate the regions for capacitance calculations. (c) depicts the induced band-bending, resulting in (d) the alignment of the conduction band. (e) shows the voltage dependent gain in band-bending $-q \cdot \Delta\phi_a(0)$ at the absorber surface induced by the conduction band offset ΔE_C between absorber and buffer layer. (f) displays on the left hand side the equivalent circuit for the p-n-n-hetero-junction ($C_{SS} = C_{SCR}$) indicated by the light red and grey shading in (a), respectively (b). The equivalent circuit on the right hand side in (f) represents the case of an additional diffusion-capacitance $C_{diff,a}$ in series to the junction-capacitance C_{SCR} . (g) compares simulated (symbol + line) and calculated (solid line) voltage dependent curves of the complete device capacitance C_{SS} in steady state ($\omega \rightarrow 0$) and the depletion width w_a of the absorber. All data are obtained on the default model in Table A - 4 without interface states.

Due to the much higher doping density of the high resistive window with respect to the absorber the correction term was utilized analogous to the case of a one sided junction. When calculating potentials with w_a the correction term has to be set to zero ($V_{\text{corr}} = 0$). Otherwise the potential drop $\Delta\phi_{\text{SCR}}$ over the complete junction would be reduced by V_{corr} , which is physical inconceivable. Thus, V_{corr} has to be regarded if the depletion width w_a is the subject of interest. In the last equation of equations 2.17 $\Delta\phi_w$ represents the potential drop between the 2 window layers as indicated in Figure 7 c). Owing to the high doping densities of the window layers $\Delta\phi_w$ can be considered as voltage independent. The height of this potential step is

$$\Delta\phi_w = \frac{k_B T}{q} \ln \left[\frac{N_{D,lrw} N_{C,hrw}}{N_{D,hrw} N_{C,lrw}} \right]. \quad 2.18$$

In Figure 7 a) the electron accumulation within the hr-window and the electron depletion within the lr-window, responsible for $\Delta\phi_w$, are decaying exponentially from $z = d_b + d_{hrw}$ in bulk-direction of the particular layer. A derivation for the analytical solutions of the hr-lr-window junction in Figure 7 a) - d) is given in Appendixes A.1.

Further, simulated data points in Figure 7 a) reveal on the buffer side an accumulation of negative charges (electrons) at the buffer/hr-window junction ($z \lesssim d_b$). This is in contradiction to the assumption of a complete depleted buffer layer. The reason for this effect is the more than 2 orders of magnitude lower effective doping density of the buffer layer with $N_{D,b} = 1 \cdot 10^{15} \text{ cm}^{-3}$ compared to the hr-window layer with $N_{D,hrw} = 7.1 \cdot 10^{17} \text{ cm}^{-3}$. Nonetheless, with respect to Figure 7 b) - d) the assumption of a complete depleted buffer layer produces only a minor difference between simulated and calculated data curves, especially at the absorber-buffer interface, which is of major interest in this work (see section 2.3.3). Figure 7 d) shows the resulting band diagram of the hetero-structure given in Table A - 4. The band alignment differs from the potential curve by a positive band offset with $\Delta E_C = 0.1 \text{ eV}$ between absorber and buffer layer. ΔE_C results from the reduced electron affinity with $\chi_{e,a} - \chi_{e,b} = 0.1 \text{ eV}$ assumed for the buffer layer. On the other hand, a compensating band offset with $\Delta E_C = -0.1 \text{ eV}$ is formed between buffer and high resistive window. Thus, the band offset does not enter into equation 2.14 for calculating V_{bi} . However, differences in the electron affinity effect additional bending of the bands due to accumulation of charge carriers (here electrons) at the particular side of junction with higher electron affinity. An analytical solution for a voltage dependent depletion region in combination with a band-offset is hard to achieve. Thus, in the following the phenomenology of a band offset at the absorber/buffer interface is

treaten qualitatively by means of simulated potentials at the absorber surface $z = 0$ in Figure 7 e). It can be confirmed in Figure 7 e) that the positive band-offset induces an additional voltage dependent downward band-bending $-q\Delta\phi_a(0)$ at the absorber surface. The change in band-bending is referenced to no band offset with $\Delta E_C = 0$ and estimated with $-q\Delta\phi_a(0) = -q[\phi_a^{\Delta E_C}(0) - \phi_a^{\Delta E_C=0}(0)]$. In Figure 7 e) at equilibrium $-q\Delta\phi_a(0)$ levels off for $\Delta E_C \geq 0.1$ eV. However, with increasing bias-voltage V_{ext} in forward direction the impact of ΔE_C rises on $-q\Delta\phi_a(0)$ due to an enhanced accumulation of electrons at the absorber surface. This is relevant for voltage dependent recombination rates over interface states, depending strongly on the respective charge carrier densities at the interface. Hence, this subject is picked up again in section 2.3.3.

Capacitances of the space charge regions

The grey shadings in Figure 7 b) indicate the analogon of the space charge regions to 2 parallel plate capacitors, where holds $E_z \neq 0$ for the electric field in between the two plates and $E_z = 0$ outside of the plates. In line with this, one plate is placed at $z = -w_a$ and the other plate at $z = d_b + w_{hrw}$ indicated by C_{SCR} in Figure 7 b). Due to 3 different dielectric materials defining the junction-capacitance C_{SCR} it is reasonable to divide C_{SCR} further into a series connection of capacitances with homogeneous dielectric properties. The corresponding equivalent circuit for low forward bias-voltages follows on the left hand side of Figure 7 f) and is subsequently explained in this section. With the general approach for the capacitance

$$C = \epsilon_0 \epsilon_r \frac{\oiint \vec{E} d\vec{A}}{\int \vec{E} d\vec{s}} \quad 2.19$$

the respective area normalized capacitance $C_{SCR,i}$ ($i = a, b, hrw$) of each depletion region can be derived to

$$C_{SCR,a} = \frac{\epsilon_a}{w_a}, \quad C_{SCR,b} = \frac{\epsilon_b}{d_b}, \quad C_{SCR,hrw} = \frac{\epsilon_{hrw}}{w_{hrw}}. \quad 2.20$$

The total capacitance C_{SCR} follows from the steady state ($\omega = 0$, with ω the angular frequency of the applied voltage signal) solution of the equivalent circuit depicted on the left hand side in Figure 7 f). By using the complex admittance Y the total capacitance of the equivalent circuit correspond to $C_{SCR} = \text{Im}(Y)/\omega$. For 2 separate parallel circuits connected in series (see section 3.2) the limit of $\text{Im}(Y)/\omega$ for $\omega \rightarrow 0$ yields the capacitance in steady state. Consequently, the following equation can be derived for C_{SCR}

$$C_{SCR} = \frac{(C_{SCR,a}^{-1} + C_{SCR,b}^{-1})^{-1} (R_{SCR,a} + R_{SCR,b})^2 + C_{SCR,hrw} R_{SCR,hrw}^2}{(R_{SCR,a} + R_{SCR,b} + R_{SCR,hrw})^2} \quad 2.21$$

$$C_{SCR} \cong \left(\frac{1}{C_{SCR,a}} + \frac{1}{C_{SCR,b}} \right)^{-1}.$$

In equation 2.21, the resistances $R_{SCR,i}$ ($i = a, b, hrw$) become available by integrating the inverse of the conductivity $\sigma(z) = |q\mu_n n(z)|$ over the particular depletion region (see equation 2.25). The reason that the conductivity within the SCR is entirely based on electrons follows from the band-diagram in Figure 8 on page 32. Due to the high valence band offset of ≈ 1 eV in between the absorber and buffer layer a charge balancing via holes between the depletion edge of the absorber ($z = -w_a$) and the depletion edge of the buffer ($z = d_b$) can be excluded. This explains, why $C_{SCR,a}$ and $C_{SCR,b}$ as well as $R_{SCR,a}$ and $R_{SCR,b}$ are connected in series in 2 separate lines connected in parallel, yielding the equivalent circuit ($V_{ext} \lesssim 0.6$ V) depicted on the left hand side of Figure 7 f). For the conduction band alignment in Figure 7 d) the resistances in equilibrium follow from numerical integration to $R_{SCR,a} \approx 6 \cdot 10^{10} \Omega \cdot \text{cm}^2$, $R_{SCR,b} \approx 0.15 \Omega \cdot \text{cm}^2$, and $R_{SCR,hrw} \approx 2 \cdot 10^{-7} \Omega \cdot \text{cm}^2$. In accordance with equation 2.21 this 17 orders of magnitude lower resistance of the hr-window effects a negligible contribution of $C_{SCR,hrw}$ to C_{SCR} . Inserting equations 2.16 and 2.20 into equation 2.21 the junction-capacitance can be expressed as a function of voltage by

$$C_{SCR}(V) = \frac{\varepsilon_a \varepsilon_b}{\varepsilon_b w_a(V) + \varepsilon_a d_b} = \left[\frac{d_b}{\varepsilon_b} + \frac{\delta d_b}{\varepsilon_a} \left(\sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{SCR}(V)}{\varphi^*}} - 1 \right) \right]^{-1}. \quad 2.22$$

From equation 2.22 it can be concluded that C_{SCR} depends solely on the inverse depletion width w_a of the absorber and hence on the inverse square root of $V_{bi} - V$ as labelled in Figure 7 g). Due to the highest resistance with $R_{SCR} \approx 10^{11} \Omega \cdot \text{cm}^2$ of the absorber/buffer junction within the complete device it can be concluded that the device capacitance in steady state C_{SS} equals to C_{SCR} as shown in Figure 7 g) for $V_{ext} \lesssim 0.6$ V.

Further, with the previous consideration it will be attempted to demonstrate that the contribution of the window-junction capacitance C_W to the complete device capacitance C_{SS} becomes negligible. In Figure 7 b) C_W , indicated by the grey shading, is located in between the z -coordinates of the $1/e^2$ -decay of the electric field E_z . These borders are derived with equation 2.19. Both, the depletion width within the lr-window as well as the accumulation width within the hr-window are corresponding to 2 times the Debye-length λ_D given in equation 2.23.

$$\lambda_{D,i} = \sqrt{\frac{\varepsilon_i k_B T}{q^2 N_{D,i}}} , \quad i = hrw, lrw \quad 2.23$$

In accordance with equation 2.20, the capacitances of the 2 regions can be estimated with $C_{W,i} = \varepsilon_i / 2\lambda_i$ ($i = hrw, lrw$). Because of the high availability of electrons within the window junction the equivalent circuit of this junction can be expected as 2 separate parallel circuits $R_{W,hrw} \parallel C_{W,hrw}$ and $R_{W,lrw} \parallel C_{W,lrw}$ connected in series. The capacitance C_W of this series connection can be derived with equation 2.24 and C_W can be expected as independent from the external voltage.

$$C_W = \frac{C_{W,hrw} R_{W,hrw}^2 + C_{W,lrw} R_{W,lrw}^2}{(R_{W,hrw} + R_{W,lrw})^2} \quad 2.24$$

However, due to $R_{W,hrw} \approx R_{W,lrw}$ the capacitance C_W will not reduce to $C_{W,hrw}$ or $C_{W,lrw}$ as in the case of $C_{SCR} \cong (C_{SCR,a}^{-1} + C_{SCR,b}^{-1})^{-1}$ in equation 2.21. Thus, the resistances $R_{W,hrw}$, $R_{W,lrw}$ have to be determined by integrating the inverse conductance $1/\sigma(z)$ over the particular region of the junction. As shown in equation 2.25 this equals to an integration of the inverse electron density $1/n(z)$ under the assumption that the contribution of holes to the conductance is negligible for the window layers.

$$R_{W,i} = \pm \int_{\mp 2\lambda_{D,i}}^0 \frac{1}{\sigma_i(z^*)} dz^* = \pm \int_{\mp 2\lambda_{D,i}}^0 \frac{1}{|q\mu_{n,i}n_i(z^*)|} dz^* , \quad i = hrw, lrw \quad 2.25$$

To simplify the integration procedure in equation 2.25 the z -coordinate is substituted by $z^* = z - d_b - d_{hrw}$. In spite of this, the analytical integration of $1/n(z)$ is hard to achieve because of $n(z) \propto \exp\{q\phi(z)/k_B T\}$ and $\phi(z) \propto \exp\{z/\lambda_D\}$. That's why, from numerical integrations the resistances have been estimated to $R_{W,hrw} \approx 3 \cdot 10^{-7} \Omega \cdot \text{cm}^2$ and $R_{W,lrw} \approx 1 \cdot 10^{-7} \Omega \cdot \text{cm}^2$. With the particular capacitances $C_{W,hrw} \approx 1.9 \mu\text{F} \cdot \text{cm}^{-2}$ and $C_{W,lrw} \approx 3.1 \mu\text{F} \cdot \text{cm}^{-2}$ the complete capacitance of the window-junction can be determined to $C_W \approx 1.3 \mu\text{F} \cdot \text{cm}^{-2}$. By utilizing again the complex admittance (see section 3.2) the resistance for $\omega \rightarrow 0$ of the complete window-junction follows with $R_W = R_{W,hrw} + R_{W,lrw} = 4 \cdot 10^{-7} \Omega \cdot \text{cm}^2$. Repetitively, due to the series connection of $R_{SCR} \parallel C_{SCR}$ and $R_W \parallel C_W$ the complete device capacitance C_{SS} becomes available with equation 2.24 by replacing the respective resistances and capacitances. Independent from the external voltage it follows that $R_{SCR} \gg R_W$ and hence $C_{SS} \cong C_{SCR}$.

On the other hand, if the external voltage exceeds 0.6 V the simulated device capacitance C_{SS} (symbol + scattered line) in Figure 7 g) begins to deviate from the analytical solution C_{SCR}

(solid line) calculated with equation 2.22. Responsible for this increased capacitance is the diffusion capacitance $C_{\text{diff},a}$ caused by injection of minority charge carriers into the absorber bulk. A closer examination of $C_{\text{diff},a}$ is given in the next section 2.2.1.

2.2.1. Ideal diode current

A solar cell situated at its working point is subjected to physical processes comparable to a diode biased with a respective external voltage. Usually, the voltage of the working point is in proximity to the open circuit voltage V_{OC} . Under V_{OC} -condition the diode-current balances the generated photo-current. For this purpose, the present section derives with the ideal diode current in forward direction an expression for V_{OC} of an ideal solar cell.

The band diagram and charge carrier densities of a solar cell in steady state biased with $V_{\text{ext}} = 0.7 \text{ V}$ in forward direction are depicted in Figure 8 (a) and (b). Approximately, the difference $E_{\text{Fn}} - E_{\text{Fp}} = q \cdot V_{\text{ext}}$ of the quasi-Fermi levels is constant within the SCR ($E_z < 0 \text{ V/cm}$). Inside of the quasi-neutral regions ($E_z \approx 0 \text{ V/cm}$) QNR_a and QNR_{hrw} the recombination of injected minority charge carriers is characterized by decreasing minority charge carrier densities with increasing distance to the SCR edge. This causes a gradient of the respective quasi-Fermi level $E_{\text{Fn},a}$ and $E_{\text{Fp},\text{hrw}}$ within QNR_a and QNR_{hrw} . The strength of the gradient represents the rate of recombination and is accordingly a characteristic factor of the diode current. In Figure 8 a) it is apparent that $\nabla E_{\text{Fn},a} \ll \nabla E_{\text{Fp},\text{hrw}}$. As a result, the minority charge carriers within the absorber have to be regarded for the derivation of the diode current.

In Figure 8 b) a more than 2 orders of magnitude lower minority charge carrier density with respect to the majority charge carrier density at the SCR edge ($z = -w_a$) indicates the case of low injection (l.i.). Thus, the quasi-Fermi level $E_{\text{Fp},a}$ for holes remains constant inside of QNR_a . By using the Schottky approximation the existing injection of electrons at $z = -w_a$ becomes comparable to the absorption case of light with high photon energies i.e. $E_{\text{ph}} \approx 3 \cdot E_{\text{g},a}$. In that case the depth dependent generation rate $G_{n,a}$ becomes spatially narrow and negligible within the QNR. This reduces the continuity equation for injected excess-electrons $\Delta n_a(z)$ inside of QNR_a to

$$\frac{\Delta n_a(z)}{\tau_{n,a}} = D_{n,a} \frac{d^2 \Delta n_a(z)}{dz^2} \quad 2.26$$

with $D_{n,a}$ the diffusion coefficient and $\tau_{n,a}$ the lifetime of electrons within the absorber.

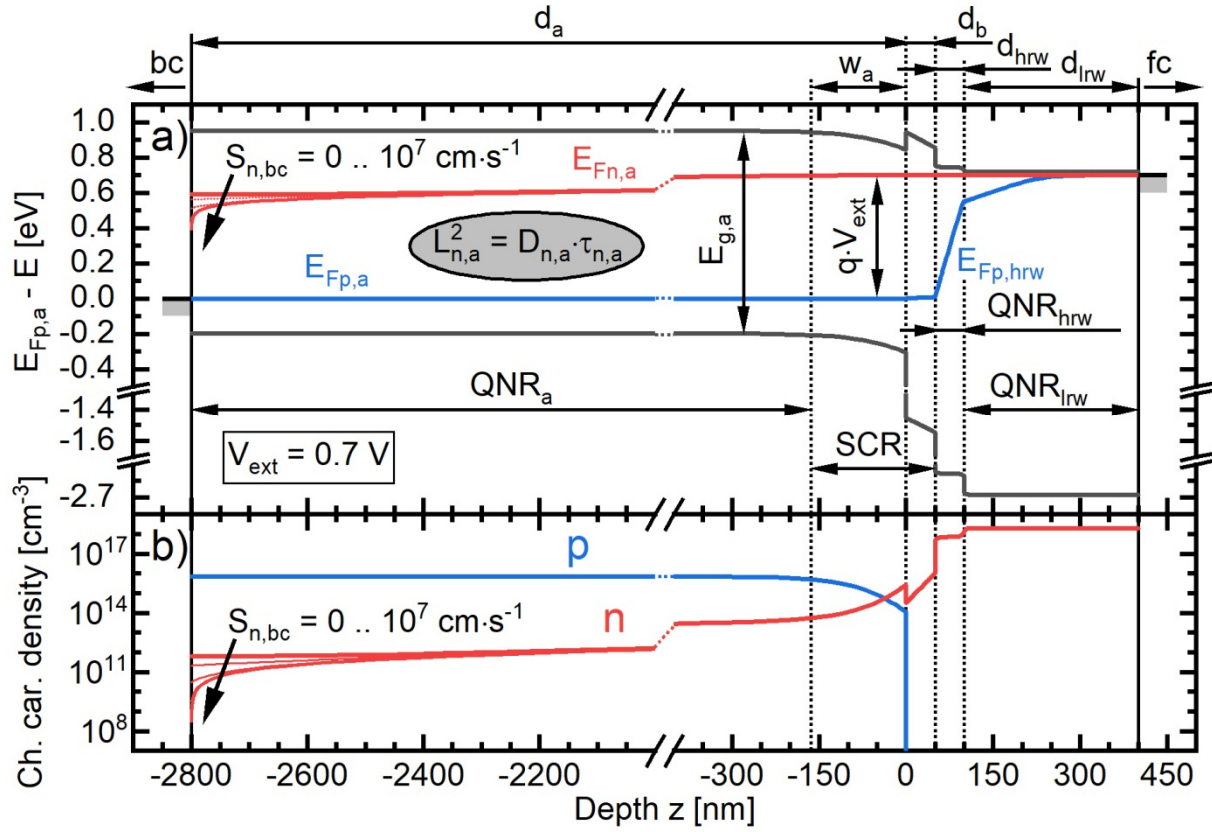


Figure 8 (a) Band diagram of a theoretical solar cell under an applied bias-voltage of $V_{\text{ext}} = 0.7$ eV in darkness. The physical parameters of the used solar cell model are given in Table A - 4. Recombination centres at the absorber/buffer interface are not included in the simulation of this band diagram. For a simplified illustration of the particular regions in the solar cell the spatial extension of space charge and charge accumulation layers within the window layers are neglected. (b) Spatial distributions of the electron and hole densities within the particular regions of the solar cell.

The electron density at the depletion edge $z = -w_a$ can be determined with the quasi-Fermi levels, giving following equation.

$$\Delta n_a(-w_a(V)) = \frac{n_{i,a}^2}{N_{A,a}} \left(\exp \left\{ \frac{E_{Fn,a} - E_{Fp,a}}{k_B T} \right\} - 1 \right) \stackrel{l.i.}{\approx} n_{a,0} \left(\exp \left\{ \frac{qV}{k_B T} \right\} - 1 \right) \quad 2.27$$

Using the result of equation 2.27 and $d\Delta n_a/dz|_{-d_a} = 0$ as boundary conditions the solution of equation 2.26 is given with

$$\Delta n_a(z, V) = n_{a,0} \left(\exp \left\{ \frac{qV}{k_B T} \right\} - 1 \right) \frac{\cosh \left(\frac{z + d_a}{L_{n,a}} \right)}{\cosh \left(\frac{d_a - w_a(V)}{L_{n,a}} \right)}, \quad z \leq -w_a(V) \quad 2.28$$

where $L_{n,a} = (D_{n,a} \cdot \tau_{n,a})^{1/2}$ denotes the diffusion length of electrons. Equation 2.28 gives the ability to obtain the depth and voltage dependent recombination rate $R_{n,a}(z, V) = \Delta n_a(z, V) / \tau_{n,a}$ of electrons within $\text{QNR}_{n,a}$. For a finite absorber thickness the electron current

$J_{n,a}$ becomes available in equation 2.29 by integrating $q \cdot R_{n,a}(z, V)$ over the complete QNR of the absorber.

$$J_{n,a}(V) = q \int_{-d_a}^{-w_a(V)} R_{n,a}(z, V) dz = \frac{qL_{n,a}n_{a,0}}{\tau_{n,a}} \left(\exp\left\{\frac{qV}{k_B T}\right\} - 1 \right) \tanh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right) \quad 2.29$$

The Shockley-equation for ideal diodes can be derived by combining the pre-factors on the right hand side of equations 2.29 to the saturation current density J_0 .

$$J_{diode}(V) = J_{n,a}(V) = J_0 \left(\exp\left\{\frac{qV}{k_B T}\right\} - 1 \right) \quad 2.30$$

$$J_0(V) = \frac{qL_{n,a}n_{a,0}}{\tau_{n,a}} \tanh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right) \approx \frac{qL_{n,a}n_{a,0}}{\tau_{n,a}} \quad \text{for } d_a \gg w_a(V), L_{n,a} \quad 2.31$$

The used model in Figure 8 has an absorber thickness of $d_a = 2.8 \mu\text{m}$, the diffusion length is $L_{n,a} \approx 500 \text{ nm}$ and the depletion width within the absorber is $w_a(0 \text{ V}) \approx 380 \text{ nm}$. With these values the argument of the hyperbolic tangent in equation 2.31 becomes > 3 , where the tanh-function converges to 1. That means, in the case of $d_a - w_a(V) \gtrsim 3L_{n,a}$ the narrowing on the right hand side of equation 2.31 is valid. This holds always for the default model, if the external voltage is applied in forward direction ($\geq 0 \text{ V}$), then $J_0(V) \rightarrow J_0$ becomes independent of the external voltage. By replacing $n_{a,0}$ with $n_{i,a}^2/N_{A,a}$ and $L_{n,a}$ with $(D_{n,a} \cdot \tau_{n,a})^{1/2}$ the saturation current density can be rewritten to:

$$J_0 \approx \frac{qn_{i,a}^2}{N_{A,a}} \sqrt{\frac{D_{n,a}}{\tau_{n,a}}} = \frac{qN_{C,a}N_{V,a}}{N_{A,a}} \sqrt{\frac{D_{n,a}}{\tau_{n,a}}} \exp\left\{-\frac{E_{g,a}}{k_B T}\right\}. \quad 2.32$$

It is evident from equation 2.32 that an Arrhenius plot of J_0 over T^{-1} delivers an activation energy of $E_A = E_{g,a}$ for the saturation current density. Thus, introducing the reference current density J_{00} [50] equation 2.32 can be recomposed to

$$J_0 = J_{00} \exp\left\{-\frac{E_A}{k_B T}\right\}. \quad 2.33$$

Back contact recombination current

In the former part of this section it could be shown that the finite absorber fulfilling $d_a - w_a(V) \gtrsim 3L_{n,a}$ gives a negligible modification of the diode current compared with an infinite

extended absorber. Hereafter, the impact of the electron back-contact recombination on the diode current is demonstrated. The recombination current density

$$J_{n,bc}(V) = qS_{n,bc}\Delta n_a(-d_a, V) = qD_{n,a} \frac{d\Delta n_a(-d_a, V)}{dz} \quad 2.34$$

of electrons at the back contact depends on the recombination velocity $S_{n,bc}$ and the present excess charge carrier density $\Delta n_a(-d_a, V)$. The right hand side of equation 2.34 represents the diffusion current out of the back side of the absorber. Transforming equation 2.34 to $d\Delta n_a/dz|_{-d_a, V} = (S_{n,bc}/D_{n,a}) \cdot \Delta n_a(-d_a, V)$ gives the back contact boundary condition for solving the continuity equation in 2.26. With the second boundary condition for the injected electron density $\Delta n_a(-w_a(V))$ in equation 2.27 the depth and voltage dependent electron density within QNR_a ($z \leq -w_a(V)$) results to

$$\Delta n_a(z, V) = \frac{n_{a,0} \left(\exp\left\{\frac{qV}{k_B T}\right\} - 1 \right) \left[\cosh\left(\frac{z + d_a}{L_{n,a}}\right) + \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \sinh\left(\frac{z + d_a}{L_{n,a}}\right) \right]}{\cosh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right) + \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \sinh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right)}. \quad 2.35$$

Obviously, in the case of $S_{n,bc} = 0$ the solution of $\Delta n_a(z, V)$ in equation 2.35 reduces to the solution without back-contact recombination in equation 2.28. The contribution of the additional hyperbolic sine terms with pre-factors on $\Delta n_a(z, V)$ is observable in Figure 8 b). Accordingly, up to a depth of $\frac{3}{4}$ of the absorber thickness ($z \approx -d_a + L_{n,a}$) $\Delta n_a(z, V)$ reveals no dependency to the back-contact recombination velocity. In a closer distance to the back-contact the hyperbolic sine function of the numerator in equation 2.35 converges to 0 and does not balance the additional contribution of the sinh-function in the denominator anymore. Thus, in conformity with Figure 8 b) an increasing recombination velocity $S_{n,bc}$ causes a decreasing electron density $\Delta n_a(-d_a, V)$ in the vicinity of the back-contact.

As mentioned above at $z = -d_a$ the sinh-function in the numerator of equation 2.35 converges to 0. On the other hand the cosh-function converges to 1 at $z = -d_a$. Consequently, the back-contact recombination current density can be deduced from equations 2.34 and 2.35 to

$$J_{n,bc}(V, S_{n,bc}) = \frac{qS_{n,bc}n_{a,0} \left(\exp\left\{\frac{qV}{k_B T}\right\} - 1 \right)}{\cosh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right) + \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \sinh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right)}. \quad 2.36$$

The diode current density $J_{\text{diode}}(V)$ can be obtained by the superposition principle of the back-

contact recombination and bulk recombination current density with $(J_{n,bc} + J_{n,a})|_{V, S_{n,bc}}$ in equation 2.37.

$$J_{diode}(V, S_{n,bc}) = J_{n,a}(V, S_{n,bc}) + J_{n,bc}(V, S_{n,bc}) = J_0 \left(\exp \left\{ \frac{qV}{k_B T} \right\} - 1 \right) \cdot \Xi(V, S_{n,bc}) \quad 2.37$$

$$\Xi(V, S_{n,bc}) = \frac{\sinh \left(\frac{d_a - w_a(V)}{L_{n,a}} \right) + \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \cosh \left(\frac{d_a - w_a(V)}{L_{n,a}} \right)}{\cosh \left(\frac{d_a - w_a(V)}{L_{n,a}} \right) + \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \sinh \left(\frac{d_a - w_a(V)}{L_{n,a}} \right)} \quad 2.38$$

Integration of equation 2.35 over QNR_a delivers $J_{n,a}$ in equation 2.37. After few transformations the right hand side of equation 2.37 becomes available, where J_0 corresponds to the approximated solution in equation 2.32 of an infinite absorber. The function $\Xi(V, S_{n,bc})$ given in equation 2.38 includes the modifications caused by a finite absorber and the electron recombination at the back-contact. For $d_a = 2.8 \mu\text{m}$, $L_{n,a} = 500 \text{ nm}$ and $\tau_{n,a} = 10 \text{ ns}$ this function results to ≈ 1 , independent from the external voltage $V_{\text{ext}} \geq 0 \text{ V}$ and the back-contact recombination velocity $S_{n,bc} \leq 10^7 \text{ cm/s}$. In consequence the diode current density of solar cells with identical physical quantities as given in Table A - 4 can be considered as immune to recombination at the back-contact.

Open circuit voltage

After investigating the diode current density in darkness, the diode current densities within the hetero-structure under illumination becomes the subject of interest. In this case the continuity equation in 2.26 for electrons $\Delta n_a(z)$ within the QNR of the absorber has to be supplemented by the generation rate $G_{n,a}(z)$ of excess charge carriers. For monochromatic illumination with a generation rate $G_{n,a}(z) = G_{n,a}(0) \exp\{\alpha z\}$ the continuity equation for electrons Δn_a and its solution can be given with the following 2 equations.

$$0 = G_{n,a}(z) - \frac{\Delta n_a(z)}{\tau_{n,a}} + D_{n,a} \frac{d^2 \Delta n_a(z)}{dz^2}, \quad z \leq -w_a \quad 2.39$$

$$\Delta n_a(z) = \frac{\tau_{n,a} \left(G_{n,a}(z) - G_{n,a}(-w_a - L_{n,a}) \cdot H(z, S_{n,bc}) - G_{n,a}(-d_a) \cdot \Lambda(z, S_{n,bc}) \right)}{(1 - \alpha^2 L_{n,a}^2)} \quad 2.40$$

In equations 2.39 and 2.40 it was assumed that $\tau_{n,a}$ is no function of the incident light intensity or applied voltage (weak excitation or injection). The solution in equation 2.40 has been derived by using the boundary conditions $d\Delta n_a/dz|_{-d_a} = (S_{n,bc}/D_{n,a}) \cdot \Delta n_a(-d_a)$ for the back

contact and $d\Delta n_a/dz|_{-w_a-L_{n,a}} = 0$ in the case of $L_{n,a} < d_a$ [151]. To achieve an improved clarity in equation 2.40 the dimensionless functions $H(z, S_{n,bc})$ and $\Lambda(z, S_{n,bc})$ have been introduced representatively for

$$H(z, S_{n,bc}) = \alpha \frac{L_{n,a} D_{n,a} \cosh\left(\frac{d_a + z}{L_{n,a}}\right) + L_{n,a}^2 S_{n,bc} \sinh\left(\frac{d_a + z}{L_{n,a}}\right)}{L_{n,a} S_{n,bc} \cosh\left(\frac{w_a + L_{n,a} - d_a}{L_{n,a}}\right) - D_{n,a} \sinh\left(\frac{w_a + L_{n,a} - d_a}{L_{n,a}}\right)} \quad 2.41$$

$$\Lambda(z, S_{n,bc}) = \frac{L_{n,a} (S_{n,bc} - \alpha D_{n,a}) \cosh\left(\frac{L_{n,a} + w_a + z}{L_{n,a}}\right)}{L_{n,a} S_{n,bc} \cosh\left(\frac{w_a + L_{n,a} - d_a}{L_{n,a}}\right) - D_{n,a} \sinh\left(\frac{w_a + L_{n,a} - d_a}{L_{n,a}}\right)}.$$

The contribution $J_{n,QNRa}$ to the photo-current density $J_{ph}(V)$ due to generated electrons within QNR_a becomes available with Δn_a in equation 2.40.

$$J_{n,QNRa}(V) = -q \int_{-d_a}^{-w_a(V)} G_{n,a}(z) - \frac{\Delta n_a(z)}{\tau_{n,a}} dz \quad 2.42$$

$$= -q \frac{\alpha^2 L_{n,a}^2 (G_{n,a}(-d_a) - G_{n,a}(z)) + G_{n,a}(z - L_{n,a}) \cdot H_0(z, S_{n,bc}) - G_{n,a}(-d_a) \cdot \Lambda_0(z, S_{n,bc})}{\alpha(1 - \alpha^2 L_{n,a}^2)} \Bigg|_{z=-w_a(V)}$$

$H_0(-w_a(V), S_{n,bc}) \rightarrow H_0(V, S_{n,bc})$ and $\Lambda_0(V, S_{n,bc})$ are the integrated functions of equations 2.41 extended with α to keep these functions dimensionless.

$$H_0(V, S_{n,bc}) = \frac{\alpha^2 L_{n,a}^2 D_{n,a} \sinh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right) + \alpha^2 L_{n,a}^3 S_{n,bc} \left(\cosh\left(\frac{d_a - w_a(V)}{L_{n,a}}\right) - 1\right)}{L_{n,a} S_{n,bc} \cosh\left(\frac{w_a(V) + L_{n,a} - d_a}{L_{n,a}}\right) - D_{n,a} \sinh\left(\frac{w_a(V) + L_{n,a} - d_a}{L_{n,a}}\right)} \quad 2.43$$

$$\Lambda_0(V, S_{n,bc}) = \frac{\alpha L_{n,a}^2 (S_{n,bc} - \alpha D_{n,a}) \left(\sinh(1) - \sinh\left(\frac{L_{n,a} + w_a(V) - d_a}{L_{n,a}}\right)\right)}{L_{n,a} S_{n,bc} \cosh\left(\frac{L_{n,a} + w_a(V) - d_a}{L_{n,a}}\right) - D_{n,a} \sinh\left(\frac{L_{n,a} + w_a(V) - d_a}{L_{n,a}}\right)}$$

By neglecting diffusion and recombination within the SCR the current density $J_{n,SCRa}$ due to light generation within SCR_a can be considered as constant. Integrating the generation rate from $z = -w_a(V)$ to $z = 0$ the contribution of the depletion region SCR_a within the absorber to the photo-current density results to

$$J_{n,SCRa}(V) = -q \frac{G_{n,a}(0) - G_{n,a}(w_a(V))}{\alpha}. \quad 2.44$$

Totalling equations 2.42 and 2.44 gives the collected photo-current density within the absorber. If the photon energy of the incident light is smaller than the band gap energy of the CdS buffer layer the light induced photo-current density of the absorber corresponds to $J_{ph}(V)$ of the complete solar cell. The diode current density J_{diode} of the ideal solar cell under illumination is accordingly determined by the sum of equations 2.30, 2.42, and 2.44.

$$J_{diode}(V) \approx J_0 \left(\exp \left\{ \frac{qV}{k_B T} \right\} - 1 \right) - J_{ph}(V) \quad 2.45$$

The open circuit voltage V_{OC} for the illuminated p-n⁻-n-n⁺-device can be obtained by setting the diode current density in equation 2.45 equal to zero. Assuming $J_{ph} \gg J_0$ conduces to an implicit equation for the temperature dependence of the open circuit voltage.

$$V_{OC}(T) \approx \frac{k_B T}{q} \ln \left(\frac{J_{ph}(V_{OC})}{J_0} \right) = \frac{E_A}{q} - \frac{k_B T}{q} \ln \left(\frac{J_{00}}{J_{ph}(V_{OC})} \right) \quad 2.46$$

Thus, the activation energy of the saturation current density for an ideal solar cell can be obtained by measuring V_{OC} as a function of temperature and extrapolating to $T = 0$ K (compare section 3.1.1).

Diffusion-capacitance

As shown in Figure 7 g), for bias-voltages exceeding 0.6 V an additional capacitance contribution $C_{diff,a}$ to the junction capacitance C_{SCR} emerges. The reason for this additional capacitance is the injection of electrons from the SCR into the QNR_a of the absorber giving additional negative charges within QNR_a. Figure 8 b) depicts the depth dependent electron and hole concentration under an applied forward bias of $V_{ext} = 0.7$ V. Within QNR_a the hole concentration can be considered as constant, whereas the electron concentration decreases towards the back contact. Following equation 2.19 this produces a capacitance indicated by $C_{diff,a}$. This diffusion capacitance can be derived from the oscillating excess electron density $\Delta n_a(z, V(t))$ within QNR_a. The external voltage $V(t)$ can be expressed with

$$V(t) = V_{DC} + \hat{V}_{AC} \exp\{i\omega t\} \quad 2.47$$

where V_{DC} represents the direct voltage and \hat{V}_{AC} the amplitude of the small test signal. Under the assumption that $\hat{V}_{AC} \ll V_{DC}$ the time dependent thickness variation of QNR_a becomes

negligible and it can be approximated $d_a - w_a(V(t)) \approx d_a - w_a(V_{DC})$. By courtesy of the previous assumption and by inserting equation 2.47 into 2.35 the time dependent excess electron density can be revealed to

$$\Delta n_a(z, V(t)) \approx n_{a,0} \Theta(z, V_{DC}, S_{n,bc}) \exp \left\{ \frac{q(V_{DC} + \hat{V}_{AC} \exp\{i\omega t\})}{k_B T} \right\}. \quad 2.48$$

In equation 2.48 the function $\Theta(z, V_{DC}, S_{n,bc})$ includes the hyperbolic functions of equation 2.35. Further, the -1 in equation 2.35 is neglected in equation 2.48 due to high forward voltages (compare Figure 7) giving $qV_{DC} \gg k_B T$ and $\exp\{q(V_{DC} + \hat{V}_{AC} \exp\{i\omega t\})/k_B T\} \gg 1$. For a small test signal equation 2.48 can be approximated with

$$\Delta n_a(z, V(t)) \approx n_{a,0} \Theta(z, V_{DC}, S_{n,bc}) \exp \left\{ \frac{qV_{DC}}{k_B T} \right\} \left(1 + \frac{q\hat{V}_{AC} \exp\{i\omega t\}}{k_B T} \right). \quad 2.49$$

From equation 2.49 it is visible that the complete time dependent excess electron density is the summation of the steady state solution in equation 2.35 and a time dependent excess electron density $\Delta \tilde{n}_a(t)$ due to the small test signal. In that case after Ref. [150] the time dependent excess electron density in equation 2.49 can be rewritten to

$$\Delta n_a(z, V(t)) = \Delta n_a(z, V_{DC}) + \Delta \tilde{n}_a(z, V_{DC}, t). \quad 2.50$$

Before, obtaining the ac current density \tilde{J} caused by the small test signal the time dependent continuity equation for $\Delta \tilde{n}_a(z, V_{DC}, t)$ in equation 2.51 has to be solved.

$$\frac{\partial}{\partial t} \Delta \tilde{n}_a = D_{n,a} \frac{\partial^2 \Delta \tilde{n}_a}{\partial z^2} - \frac{\Delta \tilde{n}_a}{\tau_{n,a}} \quad 2.51$$

With the boundary conditions

$$\Delta \tilde{n}_a(-w_a, V_{DC}, t) = n_{a,0} \exp \left\{ \frac{qV_{DC}}{k_B T} \right\} \frac{q\hat{V}_{AC}}{k_B T} \exp\{i\omega t\} \quad 2.52$$

$$\left. \frac{\partial}{\partial z} \Delta \tilde{n}_a \right|_{-d_a, V_{DC}} = \frac{S_{n,bc}}{D_{n,a}} \Delta \tilde{n}_a(-d_a, V_{DC}, t)$$

as well as $\partial \Delta \tilde{n}_a / \partial t = i\omega \cdot \Delta \tilde{n}_a$ and $\tau_{n,a}^* = \tau_{n,a} / (1 + i\omega \tau_{n,a})$ [150] the solution for $\Delta \tilde{n}_a(z, V_{DC}, t)$ results to

$$\Delta\tilde{n}_a(z, V_{DC}, t) = n_{a,0} \exp\left\{\frac{qV_{DC}}{k_B T}\right\} \frac{q\hat{V}_{AC}}{k_B T} \exp\{i\omega t\} \cdot \Theta^*(z, V_{DC}, S_{n,bc})$$

$$\Theta^*(z, V_{DC}, S_{n,bc}) = \frac{\cosh\left(\frac{z+d_a}{L_{n,a}^*}\right) + \frac{L_{n,a}^* S_{n,bc}}{D_{n,a}} \sinh\left(\frac{z+d_a}{L_{n,a}^*}\right)}{\cosh\left(\frac{d_a-w_a(V_{DC})}{L_{n,a}^*}\right) + \frac{L_{n,a}^* S_{n,bc}}{D_{n,a}} \sinh\left(\frac{d_a-w_a(V_{DC})}{L_{n,a}^*}\right)}$$
2.53

where $L_{n,a}^* = \sqrt{D_{n,a} \tau_{n,a}^*} = L_{n,a} (1+i\omega\tau_{n,a})^{-1/2}$ is the complex diffusion length. Equation 2.54 gives the solution of the ac component \tilde{J} of the complete current density, derived by integrating $q \cdot \Delta\tilde{n}_a / \tau_{n,a}$ over QNR_a plus the time dependent recombination current density at the back contact (compare equation 2.37).

$$\tilde{J}(V_{DC}, S_{n,bc}) = J_0 \exp\left\{\frac{qV_{DC}}{k_B T}\right\} \frac{q\hat{V}_{AC}}{k_B T} \exp\{i\omega t\} \cdot \Xi^*(V_{DC}, S_{n,bc})$$

$$\Xi^*(V_{DC}, S_{n,bc}) = \frac{1 + \frac{\cosh(\xi^*) - 1}{1 + i\omega\tau_{n,a}} + \frac{D_{n,a} \sinh(\xi^*)}{L_{n,a} S_{n,bc} \sqrt{1 + i\omega\tau_{n,a}}}}{\frac{D_{n,a} \cosh(\xi^*)}{L_{n,a} S_{n,bc}} + \frac{\sinh(\xi^*)}{\sqrt{1 + i\omega\tau_{n,a}}}}$$
2.54

In equation 2.54 ξ^* is the substitution of the complex ratio $(d_a - w_a(V_{DC})) / L_{n,a}^*$ and J_0 is the saturation current density from equation 2.32. Now, with the approximation $(1+i\omega\tau_{n,a})^{1/2} \approx 1 + 1/2 \cdot i\omega\tau_{n,a}$ [150] the diffusion capacitance $C_{diff,a} = \text{Im}(Y^*)/\omega$ can be obtained from the imaginary part of the complex admittance $Y^* = \tilde{J}/\hat{V}_{AC} \exp\{i\omega t\}$ tested by the small ac signal, giving a complicate expression for the frequency dependent diffusion capacitance. Therefore, equation 2.55 deals with the frequency independent solution of $C_{diff,a}$ obtained for low frequencies $\omega \ll 1/\tau_{n,a}$. On the over hand in the case of $\tau_{n,a} \approx 10$ ns equation 2.55 holds up to a frequency of $\approx 10^7$ s⁻¹, which is beyond or in the vicinity of the maximum frequency achieved by the most commercial LCR meter.

$$C_{diff,a}(V_{DC}, S_{n,bc}) = J_0 \frac{q \cdot \tau_{n,a}}{2k_B T} \exp\left\{\frac{qV_{DC}}{k_B T}\right\} \cdot \Gamma(V_{DC}, S_{n,bc})$$

$$\Gamma(V_{DC}, S_{n,bc}) = \frac{\xi \left(\frac{L_{n,a}^2 S_{n,bc}^2}{D_{n,a}^2} - 1 \right) + 2 \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \cosh \xi (\cosh \xi - 1) + \left[\left(1 + \frac{L_{n,a}^2 S_{n,bc}^2}{D_{n,a}^2} \right) \cosh \xi - 2 \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \right] \sinh \xi}{\left(\cosh \xi + \frac{L_{n,a} S_{n,bc}}{D_{n,a}} \sinh \xi \right)^2}$$
2.55

With J_0 from equation 2.32 it can be found in equation 2.55 that the diffusion capacitance is a

function of the minority charge carrier lifetime with $C_{\text{diff,a}} \propto \sqrt{\tau_{\text{n,a}}}$. The impacts of the geometrical dimensions and the back contact recombination on $C_{\text{diff,a}}$ are included in the dimensionless function $\Gamma(V_{\text{DC}}, S_{\text{n,bc}})$ of equation 2.55. For thick absorber layers with $\xi = (d_{\text{a}} - w_{\text{a}}(V_{\text{DC}}))/L_{\text{n,a}} \gg 1$ this function becomes $\Gamma(V_{\text{DC}}, S_{\text{n,bc}}) \approx 1$ and the impact of $S_{\text{n,bc}}$ on $C_{\text{diff,a}}$ is negligible. However for thin absorbers $\xi \approx 1$ an increasing $S_{\text{n,bc}}$ would reduce $C_{\text{diff,a}}$. In the case of Figure 7 g) it can be shown with equation 2.55 that for $V_{\text{DC}} = 0.6$ V the diffusion capacitance amounts to $C_{\text{diff,a}} \approx 0.13$ nF·cm⁻². Increasing V_{DC} to 0.7 V produces after equation 2.55 a capacitance contribution of $C_{\text{diff,a}} \approx 6.42$ nF·cm⁻², fitting perfectly the difference of ≈ 6.72 nF·cm⁻² between simulated and calculated data.

To avoid unknown capacitance contributions like $C_{\text{diff,a}}$ in the interpretation of voltage dependent admittance spectroscopy data, in section 4.4 of this work only bias-voltages below 0.5 V were considered for device modelling.

2.3. Regions of recombination

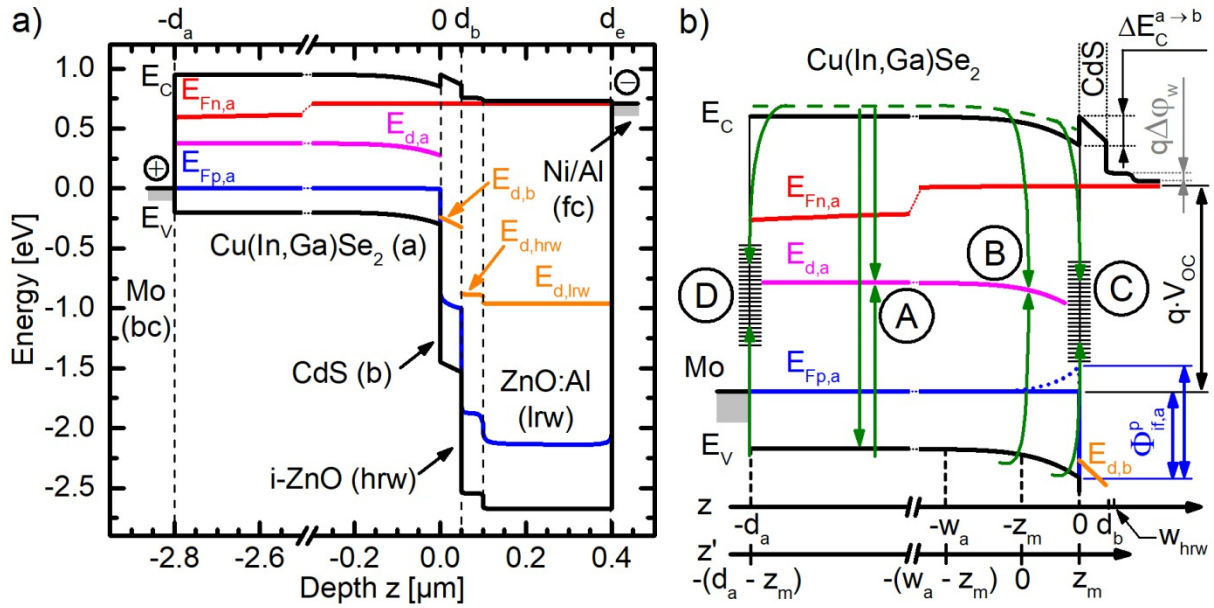


Figure 9 (a) Band structure of the default device for a CIGSe solar cell given in Table A - 4, the bracketed abbreviations are indicating the functional layers with bc = back contact, a = absorber, b = buffer, hrw = high-resistance window, lrw = low-resistance window, and fc = front contact. $E_{d,x}$ ($x = a, b, hrw, lrw$) are defect levels located on midgap of the corresponding layer. $E_{Fp,a}$ and $E_{Fn,a}$ are the quasi Fermi levels within the absorber. The state of the solar cell correspond to the open circuit condition with illumination from the right hand side and $T = 300$ K. (b) Magnification of the absorber region including the hetero junction for illustrating the critical recombination paths. Here (A) represents recombination within the quasi neutral region, (B) recombination within the absorber's depletion region, (C) recombination at the absorber/buffer interface, and (D) interface recombination at the Mo back contact. $\Delta E_C^{a \rightarrow b}$ is the electron affinity related conduction band offset between absorber and buffer layer, $\Delta \phi_w$ indicates the potential drop between the hr- and lr-window layer due to unequal doping densities. The hole barrier at the absorber/buffer interface is labelled by $\Phi_{if,a}^p$. The dotted $E_{Fp,a}$ in the vicinity of $z = 0$ indicates the upward bending of the hole quasi-Fermi level for high defect densities $N_{d,if} \gtrsim 10^{12} \text{ cm}^{-2}$ at the interface.

Thus far the idealized solar cell was considered by neglecting recombination losses at the front interface and within the depletion region of the absorber. Figure 9 b) depicts the common recombination sites by means of the simplified band diagram of a CIGSe solar cell with an absorber band gap of $E_{g,a} = 1.15$ eV ($GGI \approx 0.3$). The operation mode of the solar cell in Figure 9 is under open circuit condition. In that case the generated charge carriers cannot leave the cell and have to recombine within the device over the four recombination paths (A) – (D) located within and at the interfaces of the absorber. Obviously, the recombination processes (A) – (D) are connected in parallel, with (A) recombination in the quasi neutral region (QNR), (B) recombination in the space charge region (SCR), (C) recombination at the

absorber/buffer interface (IF) and (D) recombination at the back contact (BC). A key factor of solar cell development and improvement is the knowledge about the dominating recombination path limiting the solar cell's open circuit voltage and consequently the efficiency. In the following the impact of the particular recombination regions on the solar cell's operation principle are treated more in detail by considering the default device given in Table A - 4.

2.3.1. (A) QNR recombination

In principle, the probability of dominating QNR recombination under V_{OC} conditions enhances with increasing minority charge carrier lifetime. Provided that Auger recombination is negligible, then the highest possible lifetime is limited by radiative band to band recombination. Thus, a device limited by radiative recombination is sufficient to investigate the nature of QNR recombination within the absorber. For a device under V_{OC} condition an important boundary condition is the approximation $[d_a - w_a(V_{OC})]/d_a \approx 1$, indicating the strongly reduced depletion width $w_a(V)$ for $V = V_{OC}$ and the existence of a QNR per se. This means that this approximation holds also for very low absorber doping densities, despite the absorber is completely depleted under 0 V as indicated by the $w_a(0V) = d_a$ line in Figure 10.

Without recombination of minority charge carriers at the back contact the derivatives at the beginning of section 2.2.1 are valid in Figure 10. Due to $L_{n,a} > d_a$ for low absorber doping densities the saturation current density $J_0 \rightarrow J_0(V)$ is a function of the voltage and can be determined by equation 2.31. From equation 2.33 the activation energy of J_0 of the p-n⁻-n-n⁺-structure in section 2.2 was found to be the band gap energy of the absorber ($E_A = E_{g,a}$). The reason for this finding has been related to the much higher band gaps of the buffer and window layers, which can be observed in Figure 9 a). Additionally, from equation 2.46 it becomes apparent that the smaller the reference current density J_{00} the higher is V_{OC} , which is fulfilled for $N_{A,a}$, $\tau_{n,a}$, and $E_{g,a}$ ⁴ as high as possible. In the case of radiative recombination the minority charge carrier lifetime results to $\tau_{n,a}^{max} = \tau_{n,a}^{rad} \approx (B \cdot N_{A,a})^{-1}$. B is the radiative recombination constant and can be derived from the van Roosbroeck-Shockley relation [152].

⁴ The optimum band gap energy of solar cells – limited solely by radiative recombination – is defined by the Shockley-Queisser limit SQ2 in Figure 4 b) and is correspondingly given with $E_{g,a}^{opt} = 1.34$ eV.

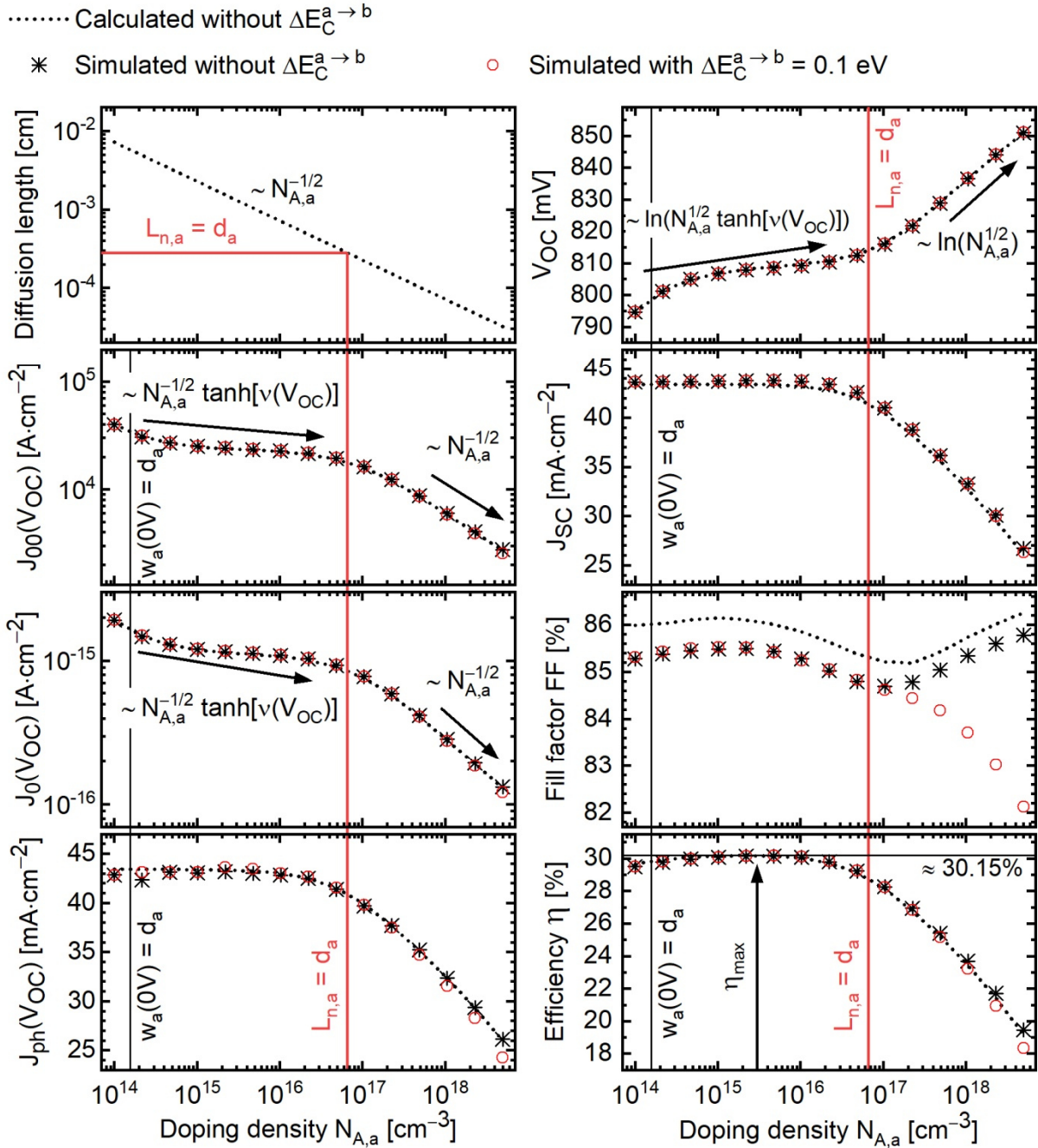


Figure 10 Simulated (scattered symbols) and calculated (dotted lines) diode parameter for the default device characteristics given in Table A - 4. The band structure is depicted in Figure 9. Simulated data were generated with *Scaps 1d*. The simulations were performed with and without a band offset $\Delta E_C^{a \rightarrow b}$ of the CdS buffer layer. To ensure dominating QNR-recombination due to radiative recombination within the absorber bulk other recombination channels of minority charge carriers related to defects within the absorber, to the metal contacts, and to internal interfaces are omitted in this plot. The function $v(V_{OC}) = [d_a - w_a(V_{OC})]/L_{n,a}$ takes into consideration the geometric extension of a finite absorber on the diode current density as derived in equation 2.29.

Consequently, the maximum absorber doping density of the idealized solar cell is balanced with the radiative lifetime for electrons, neglecting band gap narrowing or the occurrence of band-to-band Auger recombination. Correspondingly, the radiative recombination rate $U_{\text{rad},a}$ increases with increasing $N_{A,a}$, which also effects the collected photocurrent density $J_{\text{ph}}(V)$. $J_{\text{ph}}(V)$ can be obtained by integrating the continuity equation of the whole device under J_{SC} condition [50, 153]

$$J_{\text{ph}}(V) = -q\eta_C(V) \int_{-d_a}^{d_e} (G(z) - U(z, 0)) dz = \eta_C(V) \frac{J_{\text{SC}}}{\eta_C(0)}, \quad 2.56$$

where $-d_a$ denotes the back side of the absorber and d_e the front side of the emitter (see Figure 9). $U(z, 0)$ is the depth dependent net recombination rate at $V = 0$ V. The voltage dependent collection efficiency η_C of the absorber can be estimated to [154]

$$\eta_C(V) = \int_{E_{g,a}}^{\infty} 1 - \frac{\exp\{-\alpha(E)w_a(V)\}}{1 + \alpha(E)L_{n,a}} dE. \quad 2.57$$

With $w_a, L_{n,a} \propto N_{A,a}^{-1/2}$ it can be concluded from equations 2.56 and 2.57 that $N_{A,a}$ limits $J_{\text{ph}}(V_{\text{OC}})$ and $J_{\text{SC}} = J_{\text{ph}}(0)$. Especially when $L_{n,a}$ becomes smaller than the absorber thickness d_a (compare red solid lines in Figure 10) the impact of $N_{A,a}$ on J_{SC} and J_{ph} becomes visible. Taking equation 2.46 into consideration the increase of V_{OC} with higher $N_{A,a}$ is slightly reduced due to the decreasing $J_{\text{ph}}(V_{\text{OC}})$, compensating weakly the reduction of J_0 with increasing $N_{A,a}$.

On the bottom of the right hand side in Figure 10 it becomes apparent that increasing $N_{A,a}$ above 10^{17} cm^{-3} reduces eminently the device efficiency η . Reason is the strongly decreasing short circuit current density due to the reduction in collection efficiency $\eta_C(0)$ with decreasing w_a and $L_{n,a}$. This means that the increasing V_{OC} for $N_{A,a} \gtrsim 10^{17} \text{ cm}^{-3}$ in Figure 10 is not able to compensate the reduction in efficiency η due to the decreasing J_{SC} . The connection of η , V_{OC} , and J_{SC} is given in equation 2.58.

$$\eta = FF \cdot \frac{J_{\text{SC}}V_{\text{OC}}}{E_s} \quad 2.58$$

FF in equation 2.58 represents the fill factor and E_s stands for the energy flux density of irradiated sun light.

An impact on the J-V-characteristics in Figure 10 due to a band offset $\Delta E_C^{a \rightarrow b} = 0.1 \text{ eV}$ between the CIGSe absorber and CdS buffer layer (compare Figure 9 b)) becomes noticeable not until $N_{A,a} \gtrsim 10^{17} \text{ cm}^{-3}$, which is expressed by reduced $J_{\text{ph}}(V_{\text{OC}})$ and FF. In the case that the

band offset would exceed $\Delta E_C^{a \rightarrow b} \gtrsim 0.3$ eV the reflection of electrons at the CIGSe/CdS interface back into forward direction starts to reducing J_{SC} , FF, and the device efficiency independent from $N_{A,a}$. On the other hand for voltages close to V_{OC} , $\Delta E_C^{a \rightarrow b} \gtrsim 0.3$ eV effects a positive jump of E_{Fn} at the absorber/buffer interface, increasing V_{OC} . However, J_{SC} and V_{OC} are not influenced in Figure 10 over the whole $N_{A,a}$ range for such a small-sized band offset of $\Delta E_C^{a \rightarrow b} = 0.1$ eV as depicted in Figure 9 b). Equally, no noticeable impact of $\Delta E_C^{a \rightarrow b} = 0.1$ eV on the saturation current density is observed in Figure 10.

In Figure 9 a) the absorber is spatially extended to $-d_a = 2.8 \mu\text{m}$. The finite absorber causes a characteristic point with $L_{n,a} = d_a$ for the diode parameter $J_0(V_{OC})$, $J_{00}(V_{OC})$, and V_{OC} in Figure 10. This point indicates that if the diffusion length minority charge carriers is significantly smaller than the thickness of the absorber $L_{n,a} \ll d_a$ the hyperbolic tangent in equation 2.31 becomes ≈ 1 . Thus, the approximation on the right hand side of equation 2.31 is still valid and the proportionalities of the characteristic parameter to $N_{A,a}$ follow from equations 2.32 and 2.46 to $J_0 \propto N_{A,a}^{-1/2}$ and $V_{OC} \propto \ln(N_{A,a}^{1/2})$. However, in the vicinity and on the left hand side of the demarcation line $L_{n,a} = d_a$ the impact of $\tanh([d_a - w_a(V_{OC})]/L_{n,a}) = \tanh[v(V_{OC})]$ on J_0 in equation 2.31 is not negligible anymore. With the effect that the increasing $\tanh[v(V_{OC})]$ with decreasing $L_{n,a} \propto N_{A,a}^{-1/2}$ nearly compensates the reduction of J_0 and the concomitant enhancement of V_{OC} for increasing doping densities.

2.3.2. (B) SCR recombination

If only radiative recombination is active, optimum diode parameter for the default device, depicted in Figure 9 with the physical quantities in Table A - 4, were found for $N_{A,a}$ in the range of $10^{15} - 10^{16} \text{ cm}^{-3}$ (see the arrow η_{\max} in Figure 10). In the latter case the equations of section 2.2.1 are still applicable. However, if recombination via deep defects becomes active equations 2.45 and 2.46 have to be supplemented by the diode ideality factor A.

$$J_{diode}(V) = J_0 \left(\exp \left\{ \frac{qV}{Ak_B T} \right\} - 1 \right) - J_{ph}(V) \quad 2.59$$

$$V_{OC}(T) = \frac{E_A}{q} - \frac{Ak_B T}{q} \ln \left(\frac{J_{00}}{J_{ph}(V_{OC})} \right) \quad 2.60$$

For a device without shunt paths or tunnelling enhanced recombination the diode ideality factor lies in the range between 1 and 2 [155], where $A = 1$ represents solely dominating recombination within the QNR (or in exceptional cases at the CIGSe/CdS interface see

below) and $A > 1$ partial or dominating recombination within the SCR. However, the diode ideality factor is not a constant quantity either due to the decreasing SCR width with increasing forward bias or due to saturation of recombination levels with rising charge carrier injection aroused by high forward currents. Thus, Figure 11 depicts the A-factor and J_0 under V_{OC} condition as a function of the absorber doping $N_{A,a}$ in column a), the ratio of defect density and doping concentration $N_d/N_{A,a}$ with $N_{A,a}$ fixed to $7 \cdot 10^{15} \text{ cm}^{-3}$ in column b). Further shows Figure 11 in column c) the impact of the defect level $E_d - E_V$ and in column d) the ratio of the capture cross sections σ_n/σ_p , where σ_p was varied and $\sigma_n = 10^{-12} \text{ cm}^2$ was retained constant. To keep the donor type character of the defect level $\sigma_p > \sigma_n$ was dispensed. If not stated otherwise for simulations in Figure 11 defect and device properties were utilized from Table A - 4. The arrows and solid lines in Figure 11 are indicating the specified default values of the CIGSe absorber in Table A - 4. Further, for simplification recombination of minority charge carriers at the metal contacts and internal interfaces was omitted, but not radiative recombination within the absorber.

As shown in Figure 11 the condition of $A(V_{OC}) = 2$ under V_{OC} condition is hard to achieve with a device involving a hetero junction as depicted in Figure 9, even if the recombination centres are located at midgap of the absorber. With $A(V_{OC}) > 1.33$ (resulting from equation 2.62) represented by the horizontal dotted line in the first row of Figure 11, there are 2 conditions in Figure 11 where recombination within the SCR becomes dominant. In the first case for high defect densities $N_d > 10^{14} \text{ cm}^{-3}$ ($N_d/N_{A,a} > 1.4 \cdot 10^{-2}$) in column b) and in the second case for high capture cross sections $\sigma_p/\sigma_n \approx 1$ in column c). Following the solid lines in Figure 11 the default model (without interface states) can be considered as dominated by QNR recombination with $A(V_{OC}) \approx 1$.

The depicted cardinal parameters (V_{OC} , J_{SC} , FF, η) in Figure 11 derived from illuminated J-V-curves exhibit a distinct correlation between V_{OC} and $J_0(V_{OC})$. In turn $J_0(V_{OC})$ and $A(V_{OC})$ are weakly correlated to each other, and are following equal trends in every column of Figure 11. However, it appears that $A(V_{OC})$ shows a lower sensitivity to the change of defect parameters than $J_0(V_{OC})$. A-factors and saturation current densities in Figure 11 have been extracted from simulated spatially resolved recombination rates under V_{OC} . The diode current density $J_{diode}(V)$ was estimated with the following 2 diode model described by equation 2.61.

$$J_{diode}(V) = J_{01}(V) \left(\exp \left\{ \frac{qV}{k_B T} \right\} - 1 \right) + J_{02}(V) \left(\exp \left\{ \frac{qV}{2k_B T} \right\} - 1 \right) - J_{ph}(V) \quad 2.61$$

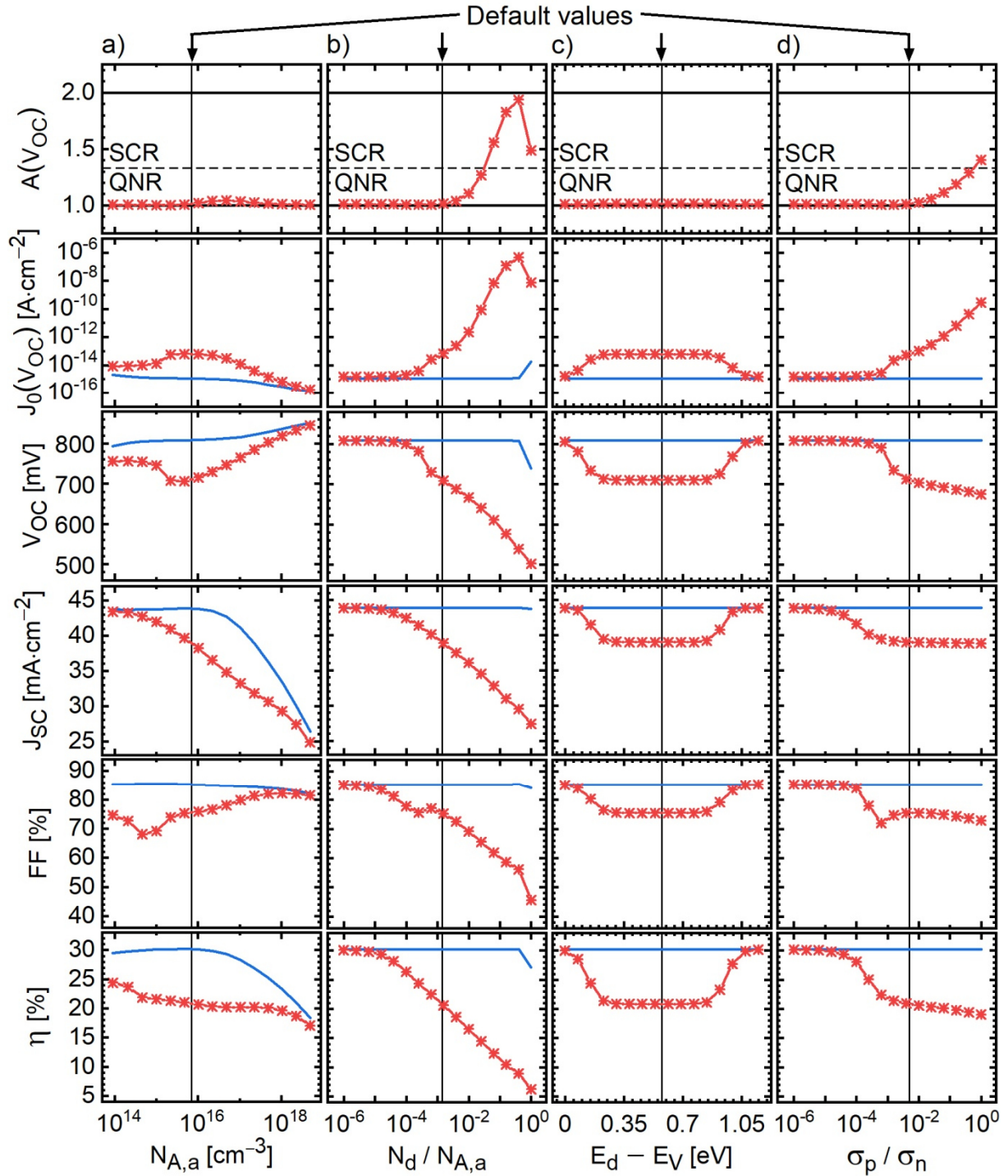


Figure 11 Simulated J-V-parameter to investigate the impact on the device characteristics of a donor type bulk defect placed within the band gap of the absorber. Simulations were performed on the default device given in Table A - 4 without recombination of charge carriers at internal interfaces or of minority charge carriers at the metal contacts. Column a) depicts the J-V-characteristics as a function of the shallow acceptor density $N_{A,a}$ of the absorber, the trap parameter were fixed to the values in Table A - 4. The impact of the defect properties are shown in column b) with varying density N_d of the trap states normalized to $N_{A,a} = 7 \cdot 10^{15} \text{ cm}^{-3}$, in column c) with a variable trap level $E_d - E_V$ and in column d) with a versatile hole capture cross section σ_p normalized to $\sigma_n = 10^{-12} \text{ cm}^2$. If not stated otherwise all physical parameter for simulating a) - d) are corresponding to the given values in Table A - 4. The dotted lines are obtained on a device in the radiative limit, to emphasize the impact of the particular defect parameter.

On the right hand side of equation 2.61 the first term correspond to the recombination current density within the QNR and the second term to the recombination current density within the depletion region of the absorber. Both saturation current densities J_{01} and J_{02} become available by integrating the recombination rate over the particular thickness of QNR and SCR under V_{OC} . From the saturation current densities J_{01} and J_{02} of the 2 diode-model in equation 2.61 it is hard to discriminate between dominating QNR or SCR recombination. Further, direct relations between J-V-parameters like V_{OC} and J_{01} as well as J_{02} are not unambiguous. Thus in Figure 11 $A(V_{OC})$ and $J_0(V_{OC})$ of the 1 diode model derived from the 2 diode model parameter were utilized to disclose interrelations of the J-V-parameters and the diode equation. By linearization of equations 2.59 and 2.61 with a Taylor expansion in the vicinity of V_{OC} and equating them the diode quality factor $A(V_{OC})$ becomes available after following equation.

$$A(V_{OC}) = \frac{J_{01} \exp\left\{\frac{qV_{OC}}{2k_B T}\right\} + J_{02}}{J_{01} \exp\left\{\frac{qV_{OC}}{2k_B T}\right\} + \frac{1}{2}J_{02}}. \quad 2.62$$

After obtaining $A(V_{OC})$ with equation 2.62, the saturation current density $J_0(V_{OC})$ of the 1 diode-model becomes determinable with equation 2.59. The knowledge of $A(V_{OC})$ gives the possibility to discriminate between dominating recombination within the QNR ($A < 1.33$) and dominating recombination within SCR ($A > 1.33$) under V_{OC} condition.

The increased J_0 and decreased J-V-parameter in column b) of Figure 11 for radiative limited recombination (blue solid line) – acting as the reference – is ascribed to the compensation effect in the case of $N_d \approx N_{A,a}$, resulting from the definition of donor type defect states. Further reveals $A(V_{OC})$ and $J_0(V_{OC})$ in column b) an unexpected reduction for the highest defect concentration $N_d/N_{A,a} = 10^0$. This is in turn a consequence of the compensated absorber doping due to donor type defect states. The lower hole concentration effects that the recombination rate of electrons reduces within the SCR and an higher concentration of electrons is injected into the QNR of the absorber, reducing $A(V_{OC})$. On the other hand the reduction of J_0 indicates that the diode current density becomes limited by the lower hole concentration of the absorber. However, this reduction of J_0 is not translated into an improvement of V_{OC} . The reason is the strongly reduced photocurrent density $J_{ph}(V_{OC})$ as indicated by the accelerated decrease in FF.

In column a) of Figure 11 the decreasing V_{OC} with increasing doping density in the range of $10^{14} \dots 5 \cdot 10^{15} \text{ cm}^{-3}$ originates from the asymmetric capture cross sections $\sigma_n = 10^{-12} \text{ cm}^2$ for electrons and $\sigma_p = 5 \cdot 10^{-15} \text{ cm}^2$ for holes. As a result, the recombination current density over the defect level is limited by holes for low $N_{A,a}$. Appropriate, with increasing doping density

the saturation current density $J_0(V_{OC})$ increases and V_{OC} decreases. In the case that $N_{A,a}$ exceeds $5 \cdot 10^{15} \text{ cm}^{-3}$ the recombination process becomes solely limited by electrons and J_0 starts to decreasing, effecting an increasing V_{OC} . Reaching very high doping densities, all quantities in column a) of Figure 11 are converging to the values of the radiative limited device. The declining and increasing trend of V_{OC} as a function of $N_{A,a}$ in column a) of Figure 11 should be taken into account by the interpretation of $V_{OC}(t)$ -measurements (see section 3.1.2).

Analytically, the diode current can be derived from the product of the charge carrier densities $n \cdot p \rightarrow (n \cdot p)^{1/A}$ within the particular bands [50]. This approach follows from the high injection condition within the depletion region. Under the assumption of constant quasi-Fermi levels within the SCR the charge carrier product can be rewritten to

$$(n \cdot p)^{\frac{1}{A}} = n_i^{\frac{2}{A}} \exp\left\{\frac{E_{Fn} - E_{Fp}}{Ak_B T}\right\} = (N_{C,a} N_{V,a})^{\frac{1}{A}} \exp\left\{-\frac{E_{g,a}}{Ak_B T}\right\} \exp\left\{\frac{qV}{Ak_B T}\right\}. \quad 2.63$$

Now, the charge carrier densities at the point $-z_m$ of maximum recombination U_m (Figure 9 b)) can be determined with equation 2.63 by using the relation $\tau_{p0} \cdot n(-z_m) = \tau_{n0} \cdot p(-z_m)$. By approximation, in the vicinity of $-z_m$ the recombination rate decays to each side of the pn-junction exponentially with a characteristic length of $(k \cdot T)/(q \cdot E_{z,m})$, where $E_{z,m}$ denotes the electric field at $-z_m$ [156]. Integration of the recombination rate over the depletion region of the absorber delivers the recombination current:

$$J_{SCR} = q \int_{-w_a}^0 U(z) dz = q \int_{-(w_a - z_m)}^{z_m} U(z') dz'. \quad 2.64$$

An exact solution of the integral in equation 2.64 requires the knowledge of the position dependent energetic distance of the quasi Fermi-levels to the respective band edges as a function of the applied voltage within the SCR [156]. In that case a system of non-linear differential equations has to be solved, wherefore device simulation is usually indispensable. However, with the simplification that U_m decays exponentially in $+z$ - and $-z$ -direction and inserting equation 2.63 into the Shockley-Read-Hall (SRH) [112] equation an analytical expression for J_{SCR} can be derived to

$$\begin{aligned}
J_{SCR}(V) &\approx \frac{\pi}{2} \cdot \frac{k_B T}{E_{z,m}} \cdot \left(\frac{N_{C,a} N_{V,a}}{\tau_{n0} \tau_{p0}} \right)^{\frac{1}{A}} \exp \left\{ -\frac{E_{g,a}}{A k_B T} \right\} \left(\exp \left\{ \frac{qV}{A k_B T} \right\} - 1 \right) \\
&= J_{00} \exp \left\{ -\frac{E_{g,a}}{A k_B T} \right\} \left(\exp \left\{ \frac{qV}{A k_B T} \right\} - 1 \right) = J_0 \left(\exp \left\{ \frac{qV}{A k_B T} \right\} - 1 \right).
\end{aligned} \tag{2.65}$$

In correspondence to dominating recombination within the QNR, from equation 2.65 an activation energy of $E_A = E_{g,a}$ for J_0 can be obtained as well. Thus, if recombination dominates in the SCR a $V_{OC}(T)$ -measurement should reveal the band gap energy of the absorber (see section 3.1.1).

2.3.3. (C) Interface recombination

The recombination rate of charge carriers over interface states is described by the model of Pauwels and Vanhoutte [157]. In contrast to the usual Shockley-Read-Hall recombination, where the occupation density of the investigated defect level depends on two carrier concentrations p and n , the occupation density of interface states can depend on 4 different carrier concentrations in accordance to Figure 9 given with $p_{if,a}$, $p_{if,b}$, $n_{if,a}$ and $n_{if,b}$ [158]. Then, with the SRH-equation [112] the net recombination rate $U_{SRH,if}$ of charge carriers over a discrete defect level ($E_{d,if}$, $N_{d,if}$) at the CIGSe/CdS interface (see Figure 9) under an applied bias voltage and/or illumination can be given as

$$U_{SRH,if}(V) = \frac{n_{if} p_{if,a} - n_{i,a}^2}{\frac{1}{\sigma_p v_p N_{d,if}} (n_{if} - n_1) + \frac{1}{\sigma_n v_n N_{d,if}} (p_{if,a} - p_1)}, \tag{2.66}$$

where n_{if} denotes the higher non-equilibrium electron concentration either $n_{if,a}$ at $z = z \rightarrow 0^-$ within the absorber or $n_{if,b}$ at $z = z \rightarrow 0^+$ within the buffer layer [159]. Due to the positive band offset $\Delta E_C^{a \rightarrow b} > 0$ (see Figure 9 b)) it is highly probable under forward biasing that the higher electron concentration is located within the absorber with $n_{if,a}$ at $z = z \rightarrow 0^-$. On the other hand the higher intrinsic $n_{i,a}$ and the higher non-equilibrium hole concentration $p_{if,a}$ are located invariably within the absorber. By virtue of interface defects $[N_{d,if}] = \text{cm}^{-2}$ the pre-factors of the denominator correspond to recombination velocities $S_{n,if}$, $S_{p,if}$ for electrons and holes, respectively.

$$S_{n,if} = \sigma_n v_n N_{d,if} \quad 2.67$$

$$S_{p,if} = \sigma_p v_p N_{d,if}$$

Usually, the variables $p_1 = N_{V,a} \exp\{-(E_{d,if} - E_{V,a})/k_B T\}$, $n_1 = N_{C,a} \exp\{-(E_{C,a} - E_{d,if})/k_B T\}$, and $n_{i,a}^2$ in equation 2.66 are negligible in comparison to the non-equilibrium charge carrier densities $n_{if,a}$ and $p_{if,a}$. This is true, if the trap level is located at midgap $E_{g,a}/2$ of the absorber and if a high positive Fermi-level splitting is existent as it is the case under V_{oc} .

To evaluate the impact of recombination centres at the interface on the J-V-characteristics of a solar cell one has to distinguish between donor and acceptor type defects and additionally has to regard the Fermi-level position at the interface. According to Figure 9, this requires to solving the Poisson equation for a p-n⁻-n-n⁺-junction with a complete depleted buffer as well as a partial depleted high resistance window (hrw) layer as conducted in section 2.2, but now with additional charge states at the absorber/buffer interface. In that case the charge neutrality condition in the depletion approximation of the hetero-junction reads

$$qN_{A,a}w_a + qn_{A,if}^- = qN_{D,hrw}w_{hrw} + qN_{D,b}d_b + qn_{D,if}^+ \quad 2.68$$

In equation 2.68 $n_{A,if}^-$ and $n_{D,if}^+$ denote the ionized acceptor, respectively donor type trap states at the interface. The density $n_{d,if}$ of occupied interface defects is governed by the following rate equation

$$\begin{aligned} \frac{dn_{d,if}}{dt} = & \frac{1}{N_{d,if}} [S_{n0,if} n_{if,a} (N_{d,if} - n_{d,if}) - S_{p0,if} p_{if,a} n_{d,if}]_{capture} \\ & + \frac{1}{N_{d,if}} [S_{p0,if} (N_{d,if} - n_{d,if}) p_1 - S_{n0,if} n_{d,if} n_1]_{emission} \end{aligned} \quad 2.69$$

where the first cornered bracket term indicates the capture rates and the second one the emission rates (in line with [106]). In steady state $dn_{d,if}/dt = 0$ and by inserting equation 2.66 into 2.69, further with the relation $n_{i,a}^2 = p_1 n_1$ the ionized acceptor or donor trap density at the interface in equation 2.68 can be determined to

$$\begin{aligned} n_{A,if}^- = & \frac{S_{n,if} n_{if,a} + S_{p,if} p_1}{S_{n,if} (n_{if,a} - n_1) + S_{p,if} (p_{if,a} - p_1)} N_{d,if} = \gamma_{A,if} N_{d,if} \\ n_{D,if}^+ = & (1 - \gamma_{A,if}) N_{d,if} = \gamma_{D,if} N_{d,if}. \end{aligned} \quad 2.70$$

The quantities $\gamma_{A,if}$ and $\gamma_{D,if}$ are voltage dependent, since n_{if} and $p_{if,a}$ are functions of the voltage. Regarding the default model in Figure 9 the depletion approximation in equation 2.68 holds merely for bias voltages close to V_{OC} and produces slight deviations ($< 3\%$) between analytical and simulated potentials, respectively barrier heights $\Phi_{if,a}^p(V_{OC})$ in Figure 12 b) for bulk limitation. (The deviations between calculations and simulations of the strong IF-limited devices are of other nature and discussed later in this section.) However, at lower voltages, especially $V \leq 0$, the assumption of i. e. a partially depleted hrw-layer is not fulfilled anymore for a high concentration of acceptor states at the interface and the error of the analytical solution increases.

Donor type interface states:

In the case of a discrete donor level with $E_{d,if} \approx E_{g,a}/2$ and a type inversion of the absorber with $N_{A,a} \ll N_{D,hrw}$ at the interface, it can be assumed that $S_{n,if}n_{if,a} \gg S_{p,if}p_{if,a}$. Accordingly, equation 2.66 can be simplified to

$$U_{SRH,if}(V) \approx S_{p,if}p_{if,a} = S_{p,if}N_{V,a} \exp\left\{-\frac{\Phi_{if,a}^p(V)}{k_B T}\right\} \quad 2.71$$

and the voltage dependent recombination current density J_{if} follows with

$$J_{if}(V) = qS_{p,if}N_{V,a} \exp\left\{-\frac{\Phi_{if,a}^p(V)}{k_B T}\right\} = J_0 \left(\exp\left\{\frac{qV}{Ak_B T}\right\} - 1\right). \quad 2.72$$

Under the condition of a constant hole quasi Fermi-level $E_{Fp,a}$ within the depletion region of the absorber (see Figure 9) the hole barrier $\Phi_{if,a}^p$ is described by

$$\Phi_{if,a}^p(V) = \left(E_{Fp,a}(V) - E_{V,a}(V)\right)_{z=0} = (E_{Fp,a} - E_{V,a})_{QNR} + q\varphi_{if,a}(V). \quad 2.73$$

Hence, for further examinations the voltage dependent potential $\varphi_{if,a}(V)$ at the interface ($z = 0$) of the absorber has to be determined via solving the Poisson equation for the structure depicted in Figure 9. Following the assumption that the donor trap level at the interface is discrete and located on $E_{g,a}/2$ an additional contribution to the SCR by these chargeable defects becomes negligible, because of $\exp\{- (E_F - E_{d,if})/k_B T\} \approx 0$, if the type inversion of the absorber at the interface is strong enough in equilibrium. This holds even under illumination or voltage biasing, since $\gamma_{D,if} \approx 0$ for $E_{d,if} \approx E_{g,a}/2$ and $S_{n,if}n_{if} \gg S_{p,if}p_{if,a}$. On the other hand an additional downward band bending within the absorber is induced by the different electron

affinities of the CIGSe and CdS layers with $\chi_{\text{CIGSe}} - \chi_{\text{CdS}} = 0.1$ eV. As well, the positive band offset represents an electron barrier at the CIGSe/CdS interface and enhances further the downward band bending of the absorber due to an increased electron concentration at the absorber surface. This situation requires to solve the Poisson-Boltzmann equation, which considers also the mobile charge carriers for the position and voltage dependent potential. However, an analytical solution of this non-linear problem is hard to achieve even with appropriate simplifications [160, 161]. Therefore, hereinafter the analytical problem is treated without a band offset between absorber and buffer layer. This does not changes the previous assumption of the recombination rates at the interface, since $p_{\text{if,a}} \gg p_{\text{if,b}}$.

By inserting equation 2.16 into 2.11 the potential $\varphi_{\text{if,a}}(V)$ at the absorber/buffer interface results to

$$\varphi_{\text{if,a}}(V) = \vartheta \cdot \Delta\varphi_{\text{SCR}}(V) + \varphi^* \left(1 + \frac{\beta}{2} - \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{\text{SCR}}(V)}{\varphi^*}} \right). \quad 2.74$$

Hence, one will find that the square root voltage term in equation 2.74 impedes the direct comparison of the left hand and right hand side in equation 2.72. This problem can be overcome in accordance to Ref. [159] by linearization of $\varphi_{\text{if,a}}$ with a Taylor expansion at V_{OC} . Thus, in the vicinity of V_{OC} , equation 2.74 can be rewritten to

$$\begin{aligned} \varphi_{\text{if,a}}(V) \approx & \vartheta(V_{\text{bi}} + \Delta\varphi_w) + \varphi^* \left(1 + \frac{\beta}{2} - \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{\text{SCR}}(V_{\text{OC}})}{\varphi^*}} \right) \\ & - \vartheta V_{\text{OC}} / \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{\text{SCR}}(V_{\text{OC}})}{\varphi^*}} + \left(\vartheta / \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{\text{SCR}}(V_{\text{OC}})}{\varphi^*}} - \vartheta \right) V. \end{aligned} \quad 2.75$$

As specified in section 2.2 for calculating potentials, the correction term V_{corr} does not enter into $\Delta\varphi_{\text{SCR}}(V_{\text{OC}})$ in equation 2.17. Inserting the linearized potential into equation 2.73 gives the hole barrier for the recombination current density J_{if} over IF-states on the left hand side in equation 2.72. By a comparison of coefficients the sought quantities J_0 and A of J_{if} on the right hand side of equation 2.72 can be directly determined and follow with

$$A = \left(\vartheta - \vartheta / \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{\text{SCR}}(V_{\text{OC}})}{\varphi^*}} \right)^{-1} \quad 2.76$$

$$J_0 = qS_{p,if}N_{A,a} \left(\frac{N_{V,a}N_{C,lrw}}{N_{A,a}N_{D,hrw}} \right)^\vartheta \exp \left\{ -(k_B T)^{-1} \left[\vartheta E_{g,a} + q\varphi^* \left(1 + \frac{\beta}{2} - \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*}} \right) - qV_{OC}\vartheta / \sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*}} \right] \right\}. \quad 2.77$$

The activation energy E_A of the saturation current density can be obtained by the ansatz $J_0 = J_{00}\exp[-E_A/(Ak_B T)]$ and comparison of coefficients. However, the square roots and the unknown function $\Delta\varphi_{SCR}(V_{OC})$ in equation 2.77 inhibit the direct extraction of E_A with

$$\frac{E_A}{Ak_B T} = \frac{1}{k_B T} \cdot \left(\vartheta E_{g,a} + q\varphi^* \left(1 + \frac{\beta}{2} \right) - \frac{q\varphi^* \left(1 + \beta + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*} \right) + qV_{OC}\vartheta}{\sqrt{1 + \beta + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*}}} \right). \quad 2.78$$

The right hand side of equation 2.78 is the transformed argument of the exponential function in equation 2.77. E_A becomes available from equation 2.78 by generating the limits of $qV_{OC}(T)$ and $q\Delta\varphi_{SCR}(V_{OC}, T)$ for $T \rightarrow 0$ K.

$$\lim_{T \rightarrow 0} qV_{OC}(T) = E_A \quad ! \quad 2.79$$

$$\lim_{T \rightarrow 0} q\Delta\varphi_{SCR}(V_{OC}, T) = E_{g,a} - E_A \quad 2.80$$

With the assumption that the net doping densities and material constants in equations 2.14, 2.17, and 2.18 are temperature independent, the activation energy is found to be

$$E_A = E_{g,a} + \frac{\beta}{2\vartheta} q\varphi^* = E_{g,a} + \frac{q^2 d_b^2 N_{D,b}^2}{2} \left(\frac{1}{\varepsilon_b N_{D,b}} - \frac{1}{\varepsilon_{hrw} N_{D,hrw}} \right). \quad 2.81$$

From equation 2.81 it becomes apparent that in the case of dominating interface recombination the activation energy of J_0 exceeds $E_{g,a}$ by an expression depending on the thickness of the buffer layer as well as the doping densities of buffer and high resistance window layer. However, the additional contribution to E_A by this expression is marginal i.e. for the default model given in Table A - 4, where $d_b = 50$ nm, $N_{D,b} = 10^{15}$ cm⁻³ and $N_{D,hrw} = 7.1 \cdot 10^{17}$ cm⁻³, the activation energy increases by a small amount of 2.3 meV.

To evaluate the analytical model, Figure 12 a) shows calculated and simulated V_{OC} values as a function of the donor defect density at the absorber/buffer interface of the default model in

Table A - 4. Simulations were performed with and without a band offset of 0.1 eV. For simplification the bulk defect of the absorber was removed. Thus, the problem reduces to a bulk recombination limited device (in the radiative limit) for low $N_{d,if}$ values and an IF-recombination limited device for high $N_{d,if}$ values. This leads to a 2 diode equation for the current density at V_{OC}

$$J(V_{OC}) = J_{0,if} \left(\exp \left\{ \frac{qV_{OC}}{A_{if}k_B T} \right\} - 1 \right) + J_{0,bulk} \left(\exp \left\{ \frac{qV_{OC}}{A_{bulk}k_B T} \right\} - 1 \right) - J_{ph}(V_{OC}) = 0 \quad 2.82$$

with $A_{bulk} = 1$. The quantities A_{if} , $J_{0,if}$, and $J_{0,bulk}$ are calculated with equations 2.76, 2.77, and 2.32, respectively.

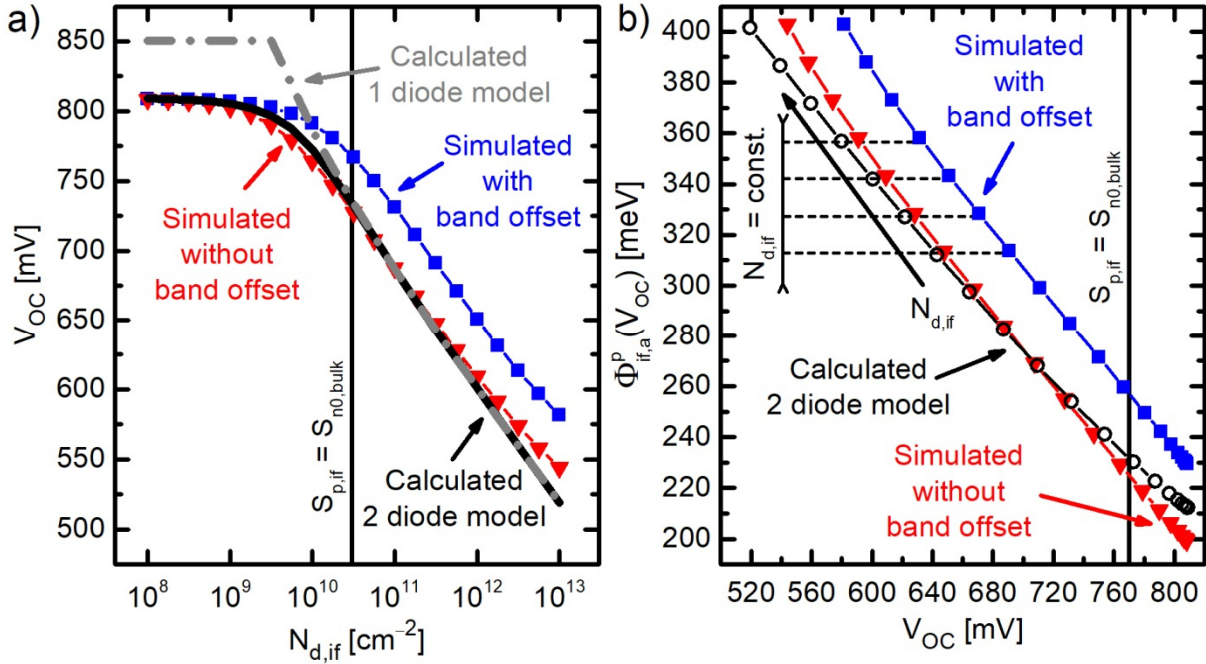


Figure 12 (a) Simulated and calculated V_{OC} as a function of the donor defect density at the absorber/buffer interface. The data were obtained using the default model in Table A - 4 without bulk defects within the absorber. (b) Hole barrier $\Phi_{if,a}^p$ at the interface calculated with equation 2.73 and plotted against V_{OC} as a function $N_{d,if}$ from (a).

The impact of the band offset between absorber and buffer layer on V_{OC} is demonstrated in Figure 12 a). When $\Delta E_C^{a \rightarrow b}$ changes from 0 to 0.1 eV, V_{OC} increases almost constantly by ≈ 40 mV in the case of dominating IF-recombination. The origin of this phenomenon can be understood from Figure 12 b). Because of the additional downward band bending induced by the different electron affinities of absorber and buffer layer a higher bias voltage (V_{OC})

becomes necessary to reduce the hole barrier $\Phi_{if,a}^p$ at the interface. Indicated by the constant $N_{d,if}$ levels in Figure 12 b), $\Phi_{if,a}^p(V_{OC})$ is identical for the 3 models. This supports the approach in equations 2.71 and 2.72 that the diode current is solely limited by holes at the interface, if the type inversion of the absorber is strong enough.

At high defect concentrations $N_{d,if} > 10^{12} \text{ cm}^{-2}$ in Figure 12 the deviation between simulated and calculated V_{OC} values begins to increase. The reason is an upward bending of $E_{Fp,a}$ due to high recombination velocities $S_{p,if} \gtrsim 10^4 \text{ cm}\cdot\text{s}^{-1}$, enhancing the depletion of holes at the interface. Thus, the recombination current over IF-states with high recombination velocities is also triggered by the transport of holes to the surface, which is neglected by assuming flat quasi-Fermi levels within the SCR. Hence, at given forward bias $\Phi_{if,a}^p$ in the simulation is higher than its calculated counterpart with equations 2.73 and 2.74, explaining higher V_{OC} values with higher $N_{d,if}$ in simulations.

In Figure 13 $J_{0,if}(V_{OC})$ and $A_{if}(V_{OC})$ of the recombination current density over IF-states and characteristic J-V-parameter of the default device have been simulated for varying acceptor and donor type defect properties at the interface. The device parameters are given in Table A - 4. Consistent with equation 2.76 for donor type interface states the values of A_{if} are nearly constant over the complete range of defect densities in column a) and hole capture cross-sections (due to $p_{if,a} \ll n_{if,a}$) in column c) of Figure 13. At higher defect densities and capture cross-sections the A-factor increases slightly due to the upward bending of $E_{Fp,a}$ arising at $N_{d,if} \approx 10^{11} \text{ cm}^{-2}$ or $\sigma_p/\sigma_n \approx 10^{-3}$.

For a straightforward interpretation of simulated results in Figure 13 the absorber bulk defect was omitted to exclude recombination within the depletion region of the absorber. Also recombination of minority charge carriers at the metal contacts has been suppressed. Accordingly, dominating interface recombination (under V_{OC}) can be assumed for donor type interface states when $S_{p,if} \gg D_{n,a}/L_{n,a} = (D_{n,a}/\tau_{n,rad})^{1/2}$ is fulfilled. In Figure 12 a) ($S_{n0,bulk} = D_{n,a}/L_{n,a}$) and Figure 13 column a) the condition $S_{p,if} = D_{n,a}/L_{n,a}$ is reached for $N_{d,if} \approx 3 \cdot 10^{10} \text{ cm}^{-2}$. With $N_{d,if} = 10^{11} \text{ cm}^{-2}$ in column c) of Figure 13 $S_{p,if} = D_{n,a}/L_{n,a}$ is reached for an hole capture cross-section of $\sigma_p \approx 3 \cdot 10^{-16} \text{ cm}^2$ or $\sigma_p/\sigma_n \approx 3 \cdot 10^{-4}$. On the left of $S_{p,if} = D_{n,a}/L_{n,a}$ dominating bulk recombination can be considered, on the right dominating interface recombination.

In contrast to a constant $A_{if}(V_{OC})$ in column a) and c) of Figure 13 the other J-V parameters are strongly affected by the defect density $N_{d,if}$ and hole capture cross-section σ_p of interface donor states. The saturation current density $J_{0,if}(V_{OC})$ plotted on a double logarithmic scale in column a) and c) reveals a power law. Fitting $J_{0,if}$ over the complete $N_{d,if}$ range as well as for

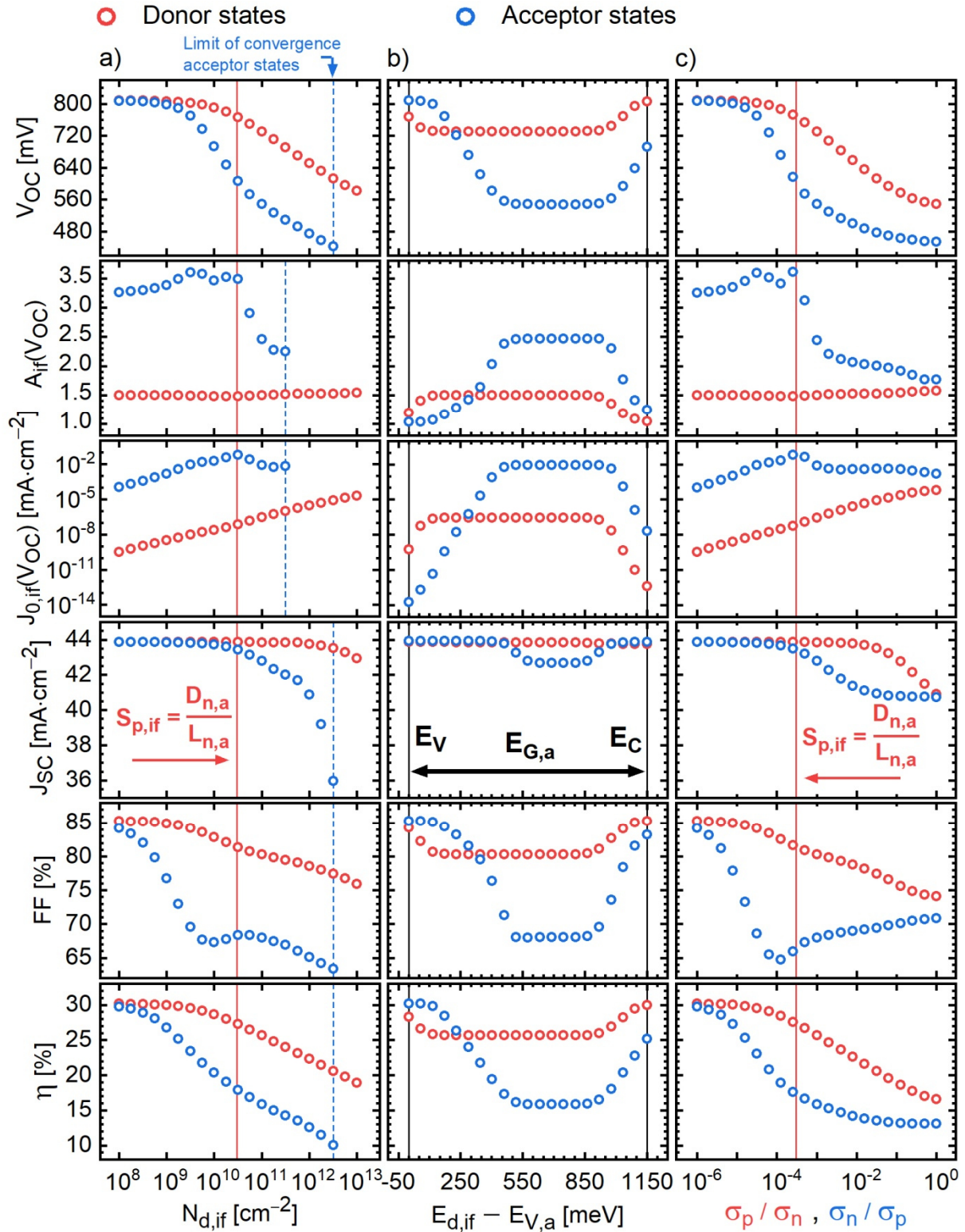


Figure 13 Simulated J-V-parameter to investigate the impact of donor and acceptor type defects located at the absorber/buffer interface on the device performance of the default model given in Table A - 4. To keep the model simple the recombination level within the absorber bulk was removed, as well recombination of minority charge carriers at the metal contacts was eliminated. Column a) depicts the J-V-characteristics as a function of the acceptor/donor density $N_{d,if}$ at the absorber/buffer interface, the other trap parameter were fixed to the values in Table A - 4. The impact of the energy level is shown in column b). Column c) illustrates the effect of the hole capture cross section $\sigma_{p,if}$ (normalized to $\sigma_n = 10^{-12} \text{ cm}^2$) in the case of donor type defects and vice versa the electron capture cross section in the case of acceptor states.

$\sigma_p/\sigma_n < 0.1$ in both cases an exponent of 0.97 can be obtained. This confirms equation 2.77 where $J_{0,if} \propto S_{p,if} \propto \sigma_p \cdot N_{d,if}$. However, for large σ_p the exponent reduces, explained by a less limitation of the interface recombination current density via holes $S_{n,if} n_{if,a} \gg S_{p,if} p_{if,a} \rightarrow S_{n,if} n_{if,a} \approx S_{p,if} p_{if,a}$.

For high $N_{d,if}$ even J_{SC} is declining in column a) in spite of a large hole barrier $\Phi_{if,a}^p(0)$ at the inverted interface under $V = 0$ V. The same effect can be observed for large hole capture cross-sections in column (c). J_{SC} starts to decline for the ratio $\sigma_p/\sigma_n \approx 10^{-2}$ with σ_n fixed to 10^{-12} cm². For $\sigma_p/\sigma_n = 1$ the approximation of completely occupied trap states with $\gamma_{D,if}(V_{OC}) \approx 0.002$ is still valid. This is not fulfilled anymore when the trap level moves closer to the conduction band like in column (b) of Figure 13. A defect level of $E_{d,if} - E_{v,a} = 0.8$ eV gives $\gamma_{D,if}(V_{OC}) \approx 0.002$ too, at $E_{d,if} - E_{v,a} = 1$ eV the occupation density under V_{OC} reduces to $\approx 50\%$, giving $\gamma_{D,if}(V_{OC}) \approx 0.5$, affecting the potential curve within the SCR. Hence, compared to the demarcation level at the valence band V_{OC} , FF, and η are increased after passing the demarcation level at the conduction band.

Acceptor type interface states:

As emerging from Figure 13 the circumstances of dominating interface recombination change dramatically if the IF-states become acceptors. In that case the proportionalities found in equations 2.76 and 2.77 are not applicable anymore over the complete ranges of $N_{d,if}$ and σ_n/σ_p in column a), respectively c). Since, for acceptor like IF-states in a p-n⁻-n-n⁺-structure with a type inversion of the absorber at the interface it is highly probable that additional negative charged interface states alter the potential curve of the SCR, reducing the strength of type inversion at the interface. Hence, the depletion width of the absorber, as derived in equation 2.16, is modified by an additional length w_{if}^* arising from charged interface states.

$$w_a = (\vartheta w_{if}^* + \delta d_b) \left(\sqrt{1 + \frac{1}{\vartheta - 1} + \frac{\delta^2 d_b^2}{(\vartheta w_{if}^* + \delta d_b)^2} \left(\beta - \frac{1}{\vartheta - 1} + 2\vartheta \frac{\Delta\varphi_{SCR}(V)}{\varphi^*} \right)} - 1 \right) \quad 2.83$$

The Greek symbols in equation 2.83 are equivalent to equations 2.17. The extension or reduction of w_a by charged interface states with w_{if}^* depends on the inverse doping density of the hr-window (i-ZnO) and results to

$$w_{if}^* = +\gamma_{A,if} \frac{\varepsilon_a N_{d,if}}{\varepsilon_{hrw} N_{D,hrw}} \quad \left(= -\gamma_{D,if} \frac{\varepsilon_a N_{d,if}}{\varepsilon_{hrw} N_{D,hrw}} \right). \quad 2.84$$

A negative w_{if}^* indicates an addition (Donors) and a positive w_{if}^* indicates a subtraction (Acceptors) to the depletion width w_a of the absorber. In the case of very small $N_{d,if}$ or σ_n giving $\gamma_{A,if} \approx 0$ it follows $w_{if}^* \approx 0$, thus equation 2.83 can be transferred into the solution without charged IF-states given with equation 2.16. For donor IF-states equations 2.83 and 2.84 hold as long as the buffer layer can be assumed to be completely depleted.

Another important consideration is the severe dependence of w_{if}^* on illumination and voltage biasing. Resulting from equation 2.70 it is $\gamma_{A,if}(V) \approx (S_{n,if} n_{if,a}) / (S_{n,if} n_{if,a} + S_{p,if} p_{if,a})$ in the case of $E_{d,if} \approx E_{g,a}/2$. Since $S_{n,if} \ll S_{p,if}$ for acceptor states the condition $S_{n,if} n_{if,a} \gg S_{p,if} p_{if,a}$ for donor states, giving $\gamma_{D,if}(V) \approx 1$ for $V = V_{OC}$, is not valid anymore in spite of an inverted interface $n_{if,a} \gg p_{if,a}$. Thus, the ionization of acceptor-like IF-states is defined by both $n_{if,a}$ and $p_{if,a}$. In this case the formula of the potential $\phi_{if,a}(V)$ at the interface becomes an implicit equation. In the same way the recombination rate $U_{SRH,if}(V)$ given in equation 2.66 can not be reduced to one charge carrier concentration. Accordingly, for a defect level located on midgap equation 2.66 can be modified to

$$U_{SRH,if}(V) \approx \frac{S_{n,if} n_{if,a} S_{p,if} p_{if,a}}{S_{n,if} n_{if,a} + S_{p,if} p_{if,a}}, \quad 2.85$$

which impedes the comparison of coefficients as performed in equations 2.72 – 2.78 to estimate i.e. the diode quality factor.

Nevertheless, in order to evaluate the impact of charged IF-states on the recombination current and henceforward on the activation energy a case differentiation can be applied by assuming 3 different scenarios with (1) $S_{n,if} n_{if,a} \ll S_{p,if} p_{if,a}$ for either less inversion or possibly realized by $\sigma_n \ll \sigma_p$; (2) $S_{n,if} n_{if,a} \gg S_{p,if} p_{if,a}$ for strong inversion and/or large electron capture cross sections $\sigma_n \approx \sigma_p$; as well as (3) $S_{n,if} n_{if,a} \approx S_{p,if} p_{if,a}$ for less inversion and/or $\sigma_n \lesssim \sigma_p$.

$$(1) S_{n,if} n_{if,a} \ll S_{p,if} p_{if,a}$$

In this limit the occupation (= degree of ionization) of the interface states can be approximated to $\gamma_{A,if}(V) \approx 0 = \text{const.}$ for $V \leq V_{OC}$. This condition corresponds to the previously investigated case of completely occupied donor states, with the difference that

henceforward electrons $n_{if,a}$ are limiting the recombination current. Following the procedure as applied to donor type interface states the parameters A , J_0 and E_A are derived as follows

$$A = \left(1 - \vartheta + \vartheta / \sqrt{1 + \beta + \frac{2\vartheta \cdot \Delta\varphi_{SCR}(V_{OC})}{\varphi^*}} \right)^{-1} \quad 2.86$$

$$J_0 = qS_{n,if}N_{C,b} \left(\frac{N_{A,a}}{N_{V,a}} \right)^{\vartheta-1} \left(\frac{N_{D,hrw}}{N_{C,lrw}} \right)^{\vartheta} \exp\{-2\vartheta\} \exp \left\{ -(k_B T)^{-1} \left((1 - \vartheta)E_{g,a} \right. \right. \\ \left. \left. - q\varphi^* \left(1 + \frac{\beta}{2} - \sqrt{1 + \beta + \frac{2\vartheta \cdot \Delta\varphi_{SCR}(V_{OC})}{\varphi^*}} \right) + qV_{OC}\vartheta / \sqrt{1 + \beta + \frac{2\vartheta \cdot \Delta\varphi_{SCR}(V_{OC})}{\varphi^*}} \right) \right\} \quad 2.87$$

$$E_A = E_{g,a} - \frac{\frac{q^2 d_b^2 N_{D,b}^2}{2} (\varepsilon_{hrw} N_{D,hrw} - \varepsilon_b N_{D,b})}{\varepsilon_a N_{A,a} \left(2\varepsilon_{hrw} N_{D,hrw} - \varepsilon_b N_{D,b} + 2\sqrt{\varepsilon_{hrw} N_{D,hrw} \cdot (\varepsilon_{hrw} N_{D,hrw} - \varepsilon_b N_{D,b})} \right)} \quad 2.88$$

In turn all quantities of the recombination current density are not being functions of the IF-defect properties, except $S_{n,if} \propto \sigma_n N_{d,if}$. This is approximately confirmed for A_{if} and $J_{0,if}$ in column c) of Figure 13 for $\sigma_n/\sigma_p \leq 3 \cdot 10^{-4}$. In this range the degree of ionization is found to be $\gamma_{A,if}(V_{OC}) \approx 0$. However due to the positive off-set in the conduction band between absorber and buffer layer instead to be constant A_{if} increases slightly from ≈ 3.3 to ≈ 3.6 and instead of $J_{0,if} \propto \sigma_n$ a power law with $J_{0,if} \propto \sigma_n^{1.17}$ is found. If σ_n/σ_p exceeds $3 \cdot 10^{-4}$ the parameters A_{if} and $J_{0,if}$ start to decrease due to the increasing $\gamma_{A,if}(V_{OC})$, which is not reflected by the other J-V-parameters like V_{OC} , since $J_{0,if}$ and A_{if} are functions of V_{OC} itself. However $\gamma_{A,if}(V_{OC}) > 0$ is not in accordance with case (1). A similarity appears by comparing the progressions of A_{if} and $J_{0,if}$ in column a) and column c) of Figure 13. For small $N_{d,if}$ it was considered from equation 2.84 that $w_{if}^* \approx 0$. Hence, due to $\sigma_n/\sigma_p = 10^{-3}$, giving $S_{n,if} n_{if,a} < S_{p,if} p_{if,a}$ under V_{OC} equations 2.86 and 2.87 are also applicable to $N_{d,if} \leq 3 \cdot 10^{10} \text{ cm}^{-2}$. In column a) the deviations of $J_{0,if}$ and A_{if} to the theory are in the same order as in column c), which is again a result of the conduction band off-set, impacting the potential curve within the SCR.

The activation energy in equation 2.88 corresponds to the band gap energy of the absorber modified by a reduction term. This expression amounts to $\approx 6 \cdot 10^{-5} \text{ eV}$, using the values of the default model provided in Table A - 4. Therefore, it is quite fair to estimate $E_A \approx E_{g,a}$ in the case of completely unoccupied acceptor states at the interface.

$$(2) S_{n,if}n_{if,a} \gg S_{p,if}p_{if,a}$$

Situation (2) with $S_{n,if}n_{if,a} \gg S_{p,if}p_{if,a}$ at V_{OC} will give $\gamma_{A,if}(V_{OC}) \approx 1 = \text{const.}$ and results in the other extremum of completely charged IF-states.

$$A = \left(\vartheta - \vartheta / \sqrt{1 + \frac{1}{\vartheta - 1} + \frac{1}{(\nu + 1)^2} \left(\beta - \frac{1}{\vartheta - 1} + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*} \right)} \right)^{-1} \quad 2.89$$

$$J_0 = qS_{p,if}N_{A,a} \left(\frac{N_{V,a}N_{C,lrw}}{N_{A,a}N_{D,iw}} \right)^\vartheta \exp\{2\vartheta\} \exp \left\{ -(k_B T)^{-1} \left[\vartheta E_{g,a} \right. \right. \\ \left. \left. + q\varphi^* \left((\nu + 1)^2 + \frac{\beta}{2} + \frac{(\nu + 1)^2 - 1}{2(\vartheta - 1)} \right) \right. \right. \quad 2.90$$

$$\left. - q\varphi^*(\nu + 1)^2 \sqrt{1 + \frac{1}{\vartheta - 1} + \frac{1}{(\nu + 1)^2} \left(\beta - \frac{1}{\vartheta - 1} + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*} \right)} \right.$$

$$\left. - qV_{OC} \vartheta / \sqrt{1 + \frac{1}{\vartheta - 1} + \frac{1}{(\nu + 1)^2} \left(\beta - \frac{1}{\vartheta - 1} + 2\vartheta \frac{\Delta\varphi_{SCR}(V_{OC})}{\varphi^*} \right)} \right] \left. \right\}$$

$$E_A = E_{g,a} + \frac{q^2 d_b^2 N_{D,b}^2}{2} \left(\frac{1}{\varepsilon_b N_{D,b}} \left(1 - \frac{2N_{d,if}}{N_{D,b} d_b} \right) - \frac{1}{\varepsilon_{hrw} N_{D,hrw}} \left(1 - \frac{N_{d,if}}{N_{D,b} d_b} \right)^2 \right). \quad 2.91$$

In equations 2.89, 2.90 the variable $\nu = \vartheta w_{if}^* / \delta d_b$ was introduced for the sake of a better overview. In equation 2.91 the activation energy E_A is a function of the density $N_{d,if}$ of IF-states. For low defect densities $N_{d,if} \ll N_{D,b} d_b = 5 \cdot 10^9 \text{ cm}^{-2}$ the activation energy correspond to the found E_A in equation 2.81 for donor IF-states. Reaching those low defect densities the J-V characteristics of the device will no longer dominated by IF-recombination (see Figure 13). However, there is a critical defect density $N_{d,if}^{\text{crit}}$ at the interface, from where on the second term in equation 2.91 reduces E_A to lower values than the band gap energy.

$$N_{d,if}^{\text{crit}} = N_{D,b} d_b - \frac{\varepsilon_{hrw}}{\varepsilon_b} N_{D,hrw} d_b + d_b \sqrt{\frac{\varepsilon_{hrw}^2}{\varepsilon_b^2} N_{D,hrw}^2 - \frac{\varepsilon_{hrw}}{\varepsilon_b} N_{D,b} N_{D,hrw}} \quad 2.92$$

In the case of the default model in Table A - 4 the critical density of IF-states amounts to $N_{d,if}^{\text{crit}} \approx 2.5 \cdot 10^9 \text{ cm}^{-2}$.

Provided that $E_{d,if} - E_V = E_{g,a}/2 = 0.575 \text{ eV}$ and $N_{d,if} = 10^{11} \text{ cm}^{-2}$, to arrive at scenario (2) with $\gamma_{A,if}(V_{OC}) \approx 1$ the capture cross sections of $N_{d,if}$ have to be set equal to each other. With $\sigma_n = \sigma_p = 10^{-12} \text{ cm}^2$ following equation 2.91 the activation energy results to $E_A \approx E_{g,a} - 0.09 \text{ eV} = 1.06 \text{ eV}$.

$$(3) S_{n,if}n_{if,a} \approx S_{p,if}p_{if,a}$$

By replacing $S_{n,if}n_{if,a}$ with $S_{p,if}p_{if,a}$ in equations 2.70 and 2.85 it is straight forward that the degree of ionization becomes $\gamma_{A,if}(V_{OC}) \approx 0.5$ and the recombination current equivalent to equation 2.72 is divided by a factor of 2. Thus, with some simple deliberations the saturation current density itself as well as the variable v in equations 2.89 and 2.90 are multiplied by a factor of 0.5. Consequently $\frac{1}{2} N_{d,if}$ can be directly inserted into equation 2.91 giving an activation energy reduced by 43 meV compared to the band gap energy $E_{g,a}$ of the absorber.

3. Measurement techniques

On the basis of previous section 2.3, in the following a more profound view is given on the V_{OC} methods for identifying the dominant region of recombination in solar cells. For device simulation in chapter 4.4 defect spectroscopy of solar cells is treated in more in detail.

To monitor the impact of ALE on the dynamics of minority charge carries within the absorber layer, time-resolved photoluminescence measurements (TRPL) were performed on bare CIGSe layers. A simple correlation between minority carrier lifetime and TRPL decay time is often not possible. Maiberg et al. give a comprehensive experimental and theoretical background to this method [29, 121, 162, 163],[Höl17],[Höl19]. Important for the TRPL measurement is the time correlated single photon counting (TCSPC) technique. Fundamentals about TCSPC can be found in references [164-168].

The effect of ALE on the surface morphology of bare CIGSe absorbers was investigated with X-ray photoelectron spectroscopy (XPS). Basics of this method are well explained in the literature [169], measurement details of this work are explained within the publication [Höl11] (see section 4.1). To obtain the CIGSe/CdS interface morphology of complete solar cells glow discharge optical emission spectroscopy (GDOES) was employed. An elaborate explanation of this technique is given in references [170-172].

3.1. Open circuit voltage (V_{OC}) measurements

3.1.1. V_{OC} as a function of temperature

Plotting $V_{OC}(T)$ against temperature and extrapolating of $V_{OC}(T)$ to $V_{OC}(0\text{ K}) = E_A$ by a linear fit (see Ref. [Höl11]) is an accredited method to obtain E_A of J_0 [173-176]. As found in section 2.3 partially or completely dominating interface recombination can be concluded, if $V_{OC}(T)$ yields $E_A < E_{g,a}$. On the other hand if the $V_{OC}(T)$ measurement exhibits $E_A \cong E_{g,a}$ all recombination paths (QNR, SCR, IF) are possibly limiting the device performance. However, all of the measured activation energies in section 4 [Höl11],[Höl13] are increased by ≥ 30 meV compared to $E_{g,a} = 1.15$ eV. From GDOES measurement and the deduced band diagram in Figure 5 it becomes obvious that $E_{g,a}$ at the interface can differ from process to process. This deviation amounts to a statistical error of ± 10 meV and is not responsible for the systematic shift of the activation energy with $E_A > E_{g,a}$. Another origin of this systematic shift is due to

the temperature dependence of the material parameters N_V and N_C . But also the physical quantities such as v_{th} and defect parameters such as $\sigma_{n,p}$ are temperature dependent. Thus, in contrast to the ideal activation energies derived in section 2.3, this section shows that $E_A(T)$ becomes a function of temperature too. Figure 14 a) shows linear fitted and extrapolated $V_{oc}(T)$ -curves for different temperature ranges of interest. The data were obtained on the default device in Table A - 4, limited by radiative recombination. In that case J_0 is given with equations 2.32 and 2.33, reformulation with respect to the temperature dependencies yields

$$J_0(T) = J_{00} \exp\left\{-\frac{E_A}{k_B T}\right\} = \frac{q N_{C,a}(T) N_{V,a}(T)}{N_{A,a}} \sqrt{\frac{D_{n,a}(T)}{\tau_{n,a}(T)}} \exp\left\{-\frac{E_{g,a}}{k_B T}\right\}, \quad 3.1$$

disregarding the weak temperature dependency of the band gap energy [177, 178]. Further the dopants $N_{A,a}$ are assumed to be hydrogen like, fulfilling impurity exhaustion over the complete temperature range of interest.

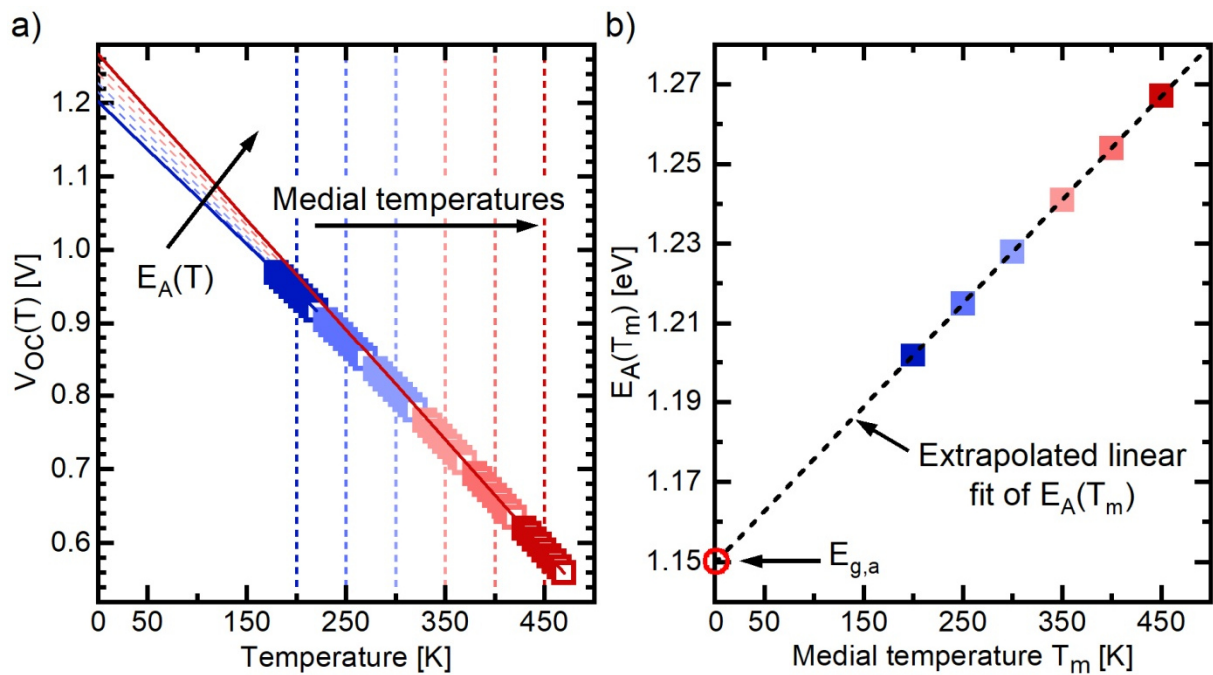


Figure 14 (a) Simulated $V_{oc}(T)$ values by means of the radiative limited default model in Table A - 4. To generate the case of diffusion limited QNR recombination the temperature dependency of $\tau_{n,a}$ was adjusted to $T^{-1/2}$. Solid and dashed lines in (a) illustrate the extrapolated linear fit of $V_{oc}(T)$ for different medial temperatures specified by the colour code. (b) Derived activation energies E_A from (a) plotted against the medial temperatures of the underlying temperature ranges, indicated by the colour code of the particular points.

Inserting equation 3.1 into 2.46 and extrapolating to 0 K yields in accordance to Figure 14 b) an activation energy as a linear function of temperature.

$$E_A(T_m) = E_{g,a} + k_B T_m \sum_i c_i \cdot \alpha_i \quad 3.2$$

Here T_m corresponds to the medial temperature (see Figure 14) and $c_i \cdot \alpha_i$ to the temperature exponent of the particular physical quantity in equation 3.1. As shown in the previous sections the temperature exponents are related to $N_C \cdot N_V \propto T^3 \rightarrow c \cdot \alpha = 3$, $D_{n,a} \propto T^{-1/2} \rightarrow c \cdot \alpha = -1/2 \cdot 1/2$ and for the radiative lifetime $\tau_{n,a} \propto B^{-1} \propto T^{3/2} \rightarrow c \cdot \alpha = -1/2 \cdot 3/2$ [152]. Thus, at each medial temperature the activation energy is increased by $+2k_B T_m$, if radiative recombination is dominant. However for a polycrystalline solar cell, as it is de facto the case for CIGSe, QNR recombination possibly takes place by non-radiative recombination at grain boundaries. An important role during this process plays the transport of minority charge carriers via diffusion to the grain boundaries. In this regard, the temperature dependency of $\tau_{n,a}$ equals to the temperature dependency of $D_{n,a} \propto T^{-1/2}$ and they will cancel out each other in equation 3.2. In that case, $E_A(T_m)$ is increased by $+3k_B T_m$ compared to $E_{g,a}$, merely because of the contribution by the effective density of states. However, this scenario cannot be simulated in 1 dimension. That's why, in order to derive the results in Figure 14 the simulation model for dominating QNR recombination is still limited by radiative recombination, but the temperature dependency of $\tau_{n,a}$ is set to $T^{-1/2}$.

An overview of $E_A(T_m)$ for the several regions of dominant recombination is depicted in Figure 15 a). The utilized model was again the default model in Table A - 4. To ensure that only one region of recombination is dominating the device all other recombination channels are suppressed during simulation i.e. by removing IF-states while simulating dominant SCR-recombination. Analogous to prevailing QNR-recombination, if the device is limited by SCR- or IF-recombination due to donors, $E_A(T_m)$ follows equally to equation 3.2 a linear trend with an extrapolated $E_A(0K) \approx E_{g,a}$. However, in both cases a higher $\sum c_i \cdot \alpha_i$ is obtained because of the additional contributions from the temperature dependency of the recombination rate over defects. Temperature relevant rate parameters are the capture cross sections and thermal velocities. For SCR-recombination it follows from $J_{SCR}(V)$ in equation 2.65 that $\sum c_i \cdot \alpha_i \approx 4.2$ ($A_{300K} \approx 1.4$, $E_{z,m} \propto V_{bi} \propto -k_B T$) and for IF-Donor recombination $\sum c_i \cdot \alpha_i \approx 4.5$ ($\vartheta \approx 1$) taking J_0 from equation 2.77.

If temperature dependent charges and defect related occupation probabilities are involved in $V_{OC}(T)$ measurements it becomes evident from Figure 15 a) that the extracted activation

energies do not follow the previous found rules anymore. A pronounced deviation of $E_A(T_m)$ can be observed for IF-Acceptor recombination. But especially at high temperatures ($T \gtrsim 360$ K) also $E_A(T_m)$ of SCR recombination begins to deviate from the linear solution in equation 3.2. Reasonable for this non-conformance is the temperature dependency of the diode ideality factor, changing continuously from $A \approx 1.4$ at 300 K to $A \approx 2$ at 460 K with the result that $\sum c_i \cdot \alpha_i$ becomes a function of temperature too.

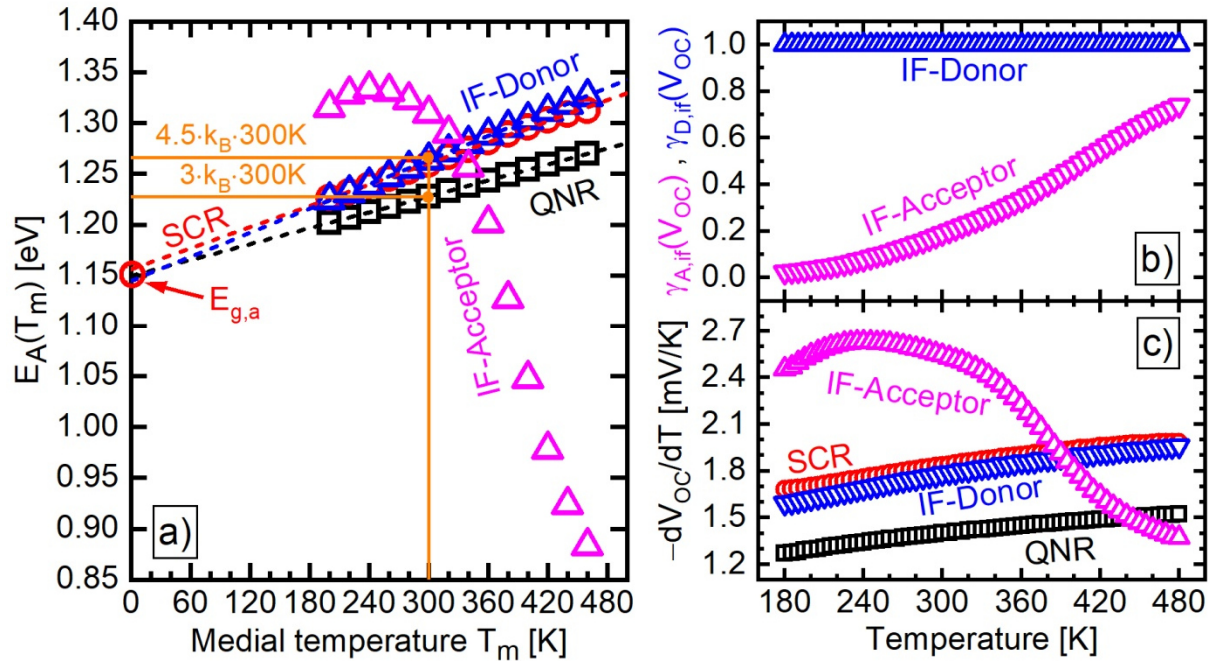


Figure 15 (a) Activation energies as a function of medial temperatures for different dominating recombination paths, obtained on the default model in Table A - 4 by simulating $V_{OC}(T)$ and extrapolating the linear fit to 0K. (b) Electron occupation probabilities $\gamma_{A,if}(V_{OC})$ and $\gamma_{D,if}(V_{OC})$ dependent on temperature for acceptor, respectively donor type defect states at the interface. (c) Differential change of V_{OC} with temperature subjected to several regions of recombination controlling the device characteristics.

In the case of IF-acceptor states the A-factor alone is no satisfying explanation for the non-conformance of $E_A(T_m)$ to the linear model in equation 3.2. It is furthermore the temperature dependent occupation probability $\gamma_{A,if}(V_{OC})$ shown in Figure 15 b) impacting the variation of V_{OC} with temperature depicted by $-dV_{OC}/dT$ in Figure 15 c). Thus, comparing the curvature of $E_A(T_m)$ in Figure 15 a) and $-dV_{OC}/dT$ in Figure 15 c) it is visible that both following an equal trend. Two interwoven mechanisms are responsible for disturbing the estimation of E_A from $V_{OC}(T)$ measurements for IF-acceptor states in Figure 15. The first mechanism is the change of charge carrier trap rates $S_{n,if}n_{if,a}$ and $S_{p,if}p_{if,a}$ illustrated by the temperature dependent occupation probability $\gamma_{A,if}(V_{OC})$ in Figure 15 b). With respect to section 2.3.3

($S_{n,if}n_{if,a} \ll S_{p,if}p_{if,a}$) at low temperatures ($T \lesssim 240$ K) the IF-recombination rate is due to $S_{n,if} \ll S_{p,if}$ practically restricted to electrons, giving $\gamma_{A,if}(V_{OC}) \approx 0$ despite $n_{if,a} > p_{if,a}$ (inversion at IF) under V_{OC} . Because of the limitation by majority charge carriers in the case of dominating recombination over IF-acceptor states the reduction of V_{OC} with temperature is pronounced higher than of the other dominating recombination sites as shown by $-dV_{OC}/dT$ in Figure 15 c). A maximum of $-dV_{OC}/dT$ is found at $T \approx 240$ K, afterwards with increasing temperatures $-dV_{OC}/dT$ decreases initially slowly and after surpassing $T \approx 340$ K accelerated. This can be explained with the increasing trap occupation $\gamma_{A,if}(V_{OC})$ with higher temperatures. Increasing $\gamma_{A,if}(V_{OC})$ means that the recombination rate $S_{p,if}p_{if,a}$ under V_{OC} decreases, reducing $-dV_{OC}/dT$. At $T \approx 410$ K, where $\gamma_{A,if}(V_{OC}) \gtrsim 0.5$ the recombination rate over IF-acceptor-states is limited by holes ($S_{n,if}n_{if,a} > S_{p,if}p_{if,a}$) and the reduction in $-dV_{OC}/dT$ decelerates. The second mechanism is the simultaneously scaling up of negative charges at the absorber surface due to the increasing $\gamma_{A,if}(V_{OC})$ with temperature, forcing E_{Fn} closer to mid-gap. As a result, the electron barrier at the interface increases with temperature and counteracts to the thermal activated recombination process. Accordingly, the slope of the straight $V_{OC}(T)$ plots reduces as indicated by a reduction of $-dV_{OC}/dT$ in Figure 15 c) and equally $E_A(T_m)$ declines after reaching its maximum at $T_m \approx 240$ K. Beyond $T_m = 360$ K the linear extrapolation of $V_{OC}(T)$ to 0 K culminates to activation energies much lower than $E_{g,a}$. If the defect density increases with $N_{d,if} > 10^{11} \text{ cm}^{-2}$ or the trap level moves closer to the valence band with $E_{d,if} - E_{V,a} < 0.575 \text{ eV}$ the distribution of $E_A(T_m)$ in Figure 15 a) shifts to lower temperatures and $E_A < E_{g,a}$ becomes likewise possible at $T_m = 300$ K.

3.1.2. V_{OC} as a function of time

The $V_{OC}(t)$ -method utilizes the illumination triggered increase of $N_{A,a}$ due to the metastable behaviour of CIGSe absorbers as described in chapter 2.1.5. To avoid additional light enhanced modifications of the window layers the solar cells are illuminated with red light ($E_{h\nu} < E_{g,CdS}$). During the measurement the samples are active cooled from the backside and kept on 25°C (STC = standard testing conditions). The temperature and V_{OC} are measured continuously in 1.5 second steps for 3 hours. An additional temperature correction is performed by measuring $\Delta V_{OC}/\Delta T$ in the vicinity of 25°C and recalculating each measurement point to 25°C .

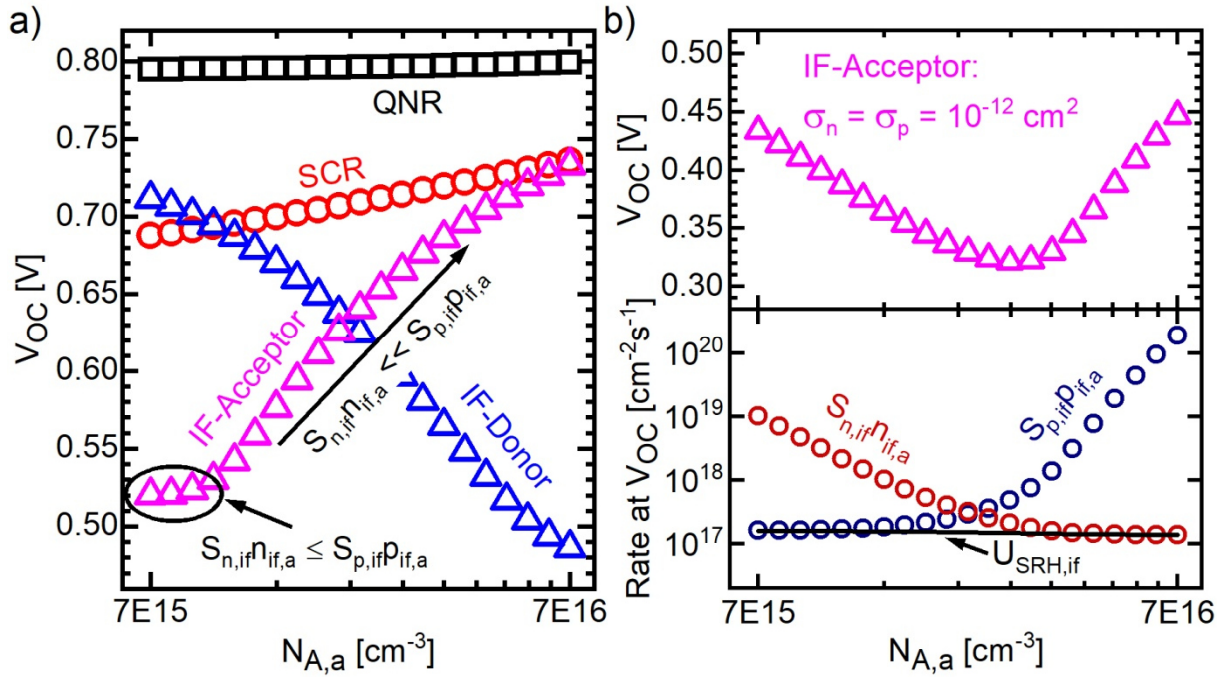


Figure 16 a) Simulated open circuit voltage V_{OC} as a function of the absorber doping density $N_{A,a}$ and the dominating region of recombination by modifying the default model in Table A - 4. Dominating SCR recombination was achieved by equal capture cross-sections of the bulk defect, analogous to the situation $\sigma_n/\sigma_p = 10^0$ in column d) of Figure 11. In the case of dominating recombination over IF-donor or acceptor states the capture cross-sections were asymmetric, resulting in $S_{n,if} = 10^3 \cdot S_{p,if}$ for donors and $S_{p,if} = 10^3 \cdot S_{n,if}$ for acceptors. b) V_{OC} (top) and the recombination rate at V_{OC} (bottom) as a function of the absorber doping for an acceptor type interface defect with equal capture cross sections.

Decisive for the determination of the dominant region of recombination is the slope trend of the $V_{OC}(t)$ -transient. If recombination within the QNR of the absorber limits the device it can be deduced from equation 2.32 that with increasing $N_{A,a}$ the saturation current density J_0 declines. Thus, for dominating QNR recombination the $V_{OC}(t)$ -transient should reveal an increasing trend with progressing illumination time. The identical behaviour exists for SCR recombination. With increasing $N_{A,a}$ the electric field $E_{z,m}$ in equation 2.65 scales up, causing a declining J_0 under the assumption that the A-factor remains nearly constant as illustrated in column a) of Figure 11. Hence, an ascending $V_{OC}(t)$ -transient ($V_{OC}(t) \equiv V_{OC}(N_{A,a})$) as shown in Figure 16 a) is a strong indicator for dominating QNR as well as SCR recombination.

On the other hand, if the $V_{OC}(t)$ -transient reveals a declining trend the existence of dominating interface recombination is highly probable. In the case of IF-donor states the recombination current density J_{if} in equation 2.72 increases with $N_{A,a}$ due to a decreasing hole barrier $\Phi_{if,a}^p$ at the interface. This case is true as long as $S_{n,if}\eta_{if,a} \gg S_{p,if}p_{if,a}$ with $\gamma_{D,if}(V_{OC}) \approx 1$ is valid. However, for IF-acceptor states the slope of the $V_{OC}(t)$ -transient depends strongly on the

capture cross-sections of electrons and holes as well as the defect energy level, defining the dominating recombination rate $S_{n,if}n_{if,a}$ or $S_{p,if}p_{if,a}$ and with this the occupation probability. In Figure 16 a) compared to IF-donor states an opposed increasing trend for the $V_{OC}(t)$ -transient under dominating IF-recombination with acceptor states is found. The reason for this opposite slope trend lies in the 3 orders of magnitude higher $S_{p,if}$ than $S_{n,if}$. As a result, despite $n_{if,a} > p_{if,a}$ (inversion), the recombination rate over IF-acceptor states is limited by $n_{if,a}$. With higher doping density $N_{A,a}$ the electron barrier $\Phi_{if,a}^n$ at the interface increases, enhancing V_{OC} . Accordingly, to obtain a decending $V_{OC}(t)$ -transient the condition $S_{n,if}n_{if,a} \gg S_{p,if}p_{if,a}$ has to become true, which would be the case for lower doping densities than the minimum $N_{A,a} = 7 \cdot 10^{15} \text{ cm}^{-3}$ in Figure 16 a). This is alternatively confirmed in Figure 16 b) by simulating $V_{OC}(N_{A,a}) \equiv V_{OC}(t)$ with equal capture cross-sections for electrons and holes ($\sigma_n = \sigma_p = 10^{-12} \text{ cm}^2$) of the IF-acceptor states (the remaining quantities of the simulation model have been kept constant). In this case the condition $S_{n,if}n_{if,a} \gg S_{p,if}p_{if,a}$ is reached for $N_{A,a} \approx 7 \cdot 10^{15} \text{ cm}^{-3}$ and a decending trend of $V_{OC}(N_{A,a}) \equiv V_{OC}(t)$ is obtained. After surpassing $N_{A,a} \approx 10^{16} \text{ cm}^{-3}$ the recombination rate becomes limited by electrons with $S_{n,if}n_{if,a} < S_{p,if}p_{if,a}$ as depicted in the bottom graph of Figure 16 b). The minimum in V_{OC} is reached until the interface recombination current density is solely limited by electrons ($U_{SRH,if} \approx S_{n,if}n_{if,a}$) and $V_{OC}(N_{A,a}) \equiv V_{OC}(t)$ begins to increase.

To summarize this section, for $V_{OC}(t)$ -measurements it can be concluded that an increasing slope trend of $V_{OC}(t)$ -transients allows no unambiguous determination or exclusion of dominant recombination sites within the solar cell. In this case additional methods like $V_{OC}(T)$ -measurements or voltage dependend admittance spectroscopy have to be utilized. However, measuring a $V_{OC}(t)$ -transient with a decreasing slope trend is a strong indicator for dominating recombination at the CIGSe/CdS interface.

3.2. Admittance spectroscopy

The response of a solar cell to a small AC test-signal delivers essential information about its electronic properties like doping densities or defect states within the band gap. Figure 17 sketches the simplified measurement circuit to determine the admittance or impedance of a solar cell from AC probing. Due to an auto balance bridge the n-side of the solar cell is set to zero potential (Virtual ground) with the high input resistance of the operational amplifier it follows $I_{ref} \cong I_x$.

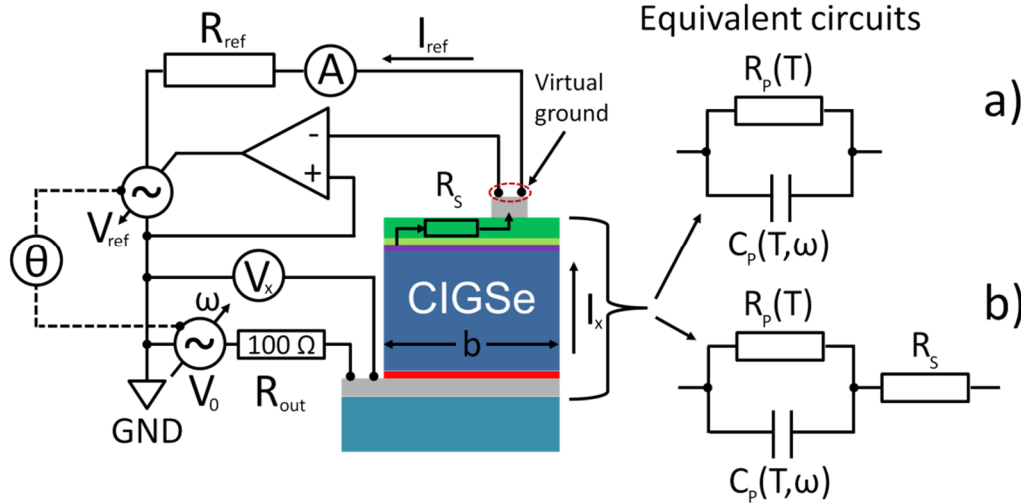


Figure 17 Simplified measurement configuration of a solar cell during admittance spectroscopy. The equivalent circuits on the right hand side correspond to an ideal solar cell (a) without and (b) with a series resistance R_s induced by the covered distance of the electrical current to the grid finger through the ZnO:Al layer. All other variables are explained within the text.

Because of R_{ref} , current I_{ref} is in phase with V_{ref} and the phase shift θ between V_x and I_x can be obtained by phase comparison of V_0 and V_{ref} . In this work an *Agilent E4980A* LCR-meter with an output resistance of $R_{out} = 100 \Omega$ was used to test the samples. This setup employs equivalent circuit a) on the right hand side of Figure 17 to extract the test unit's (solar cell) capacitance C_p and resistance R_p analogous to equation 3.3 and 3.4.

$$\omega \cdot C_p = \frac{\frac{V_0}{V_x} - 1}{R_{out}} \cdot \sin \theta \quad 3.3$$

$$R_p = \frac{R_{out}}{\left(\frac{V_0}{V_x} - 1\right) \cdot \cos \theta} \quad 3.4$$

In equation 3.3 as well as 3.4, V_0 is the root mean square voltage of the test-signal and V_x the voltage drop over the device, R_{out} the output resistance of the LCR-meter and ω represents the angular frequency. By comparing the left and right side of equation 3.3 the high-pass property ($V_x \rightarrow 0$ for $\omega \rightarrow \infty$) of circuit a) in Figure 17 becomes visible.

The most considerable source of error of capacitance measurements is a resistance R_s connected in series with the parallel circuit as shown by equivalent circuit b) in Figure 17. Reasons for an additional series resistance are manifold and of intrinsic or extrinsic character. Intrinsic, the predominantly resisting contribution acting as a series resistance is the sheet resistance of the AZO layer, denoted by R_s in Figure 17. Extrinsic, the wire length and

electrical contacts may provide further series resistances. In particular electrical contacts can hold further capacitances in series, distorting the measured capacitance.

Firstly the role of a series resistance on the measured capacitance C_{meas} is investigated. This is the case that equivalent circuit b) is the actually measured system state, but the measured data are analysed with equivalent circuit a). Via the complex admittances \underline{Y}_p of the $R_p \parallel C_p$ -element and $1/R_s$ for the series resistance, the complete complex admittance \underline{Y} of circuit b) can be written as:

$$\begin{aligned} \underline{Y} &= \left(\frac{1}{\underline{Y}_p} + R_s \right)^{-1} = \left(\frac{1}{\frac{1}{R_p} + j\omega C_p} + R_s \right)^{-1} \\ &= \frac{R_p + R_s + (\omega C_p)^2 R_s R_p^2}{(R_p + R_s)^2 + (\omega C_p)^2 R_s^2 R_p^2} + \frac{j\omega C_p}{\left(1 + \frac{R_s}{R_p}\right)^2 + (\omega C_p R_s)^2}. \end{aligned} \quad 3.5$$

Thus the measured values C_{meas} and R_{meas} after circuit a) in presence of a series resistance can be deduced by equations 3.6 - 3.8 with the result that both parameters become frequency dependent. For a sufficient small frequency ($\omega \ll 1/C_p R_s$) and series resistance ($R_s \ll R_p$), the measured capacitance can be determined to $C_{meas} \approx C_p$, however in the case of $\omega \rightarrow \infty$, $C_{meas} = 0$ is valid and independent from R_s .

$$\underline{Y}_{meas} = \frac{1}{R_{meas}} + j\omega C_{meas} \quad 3.6$$

$$C_{meas} = \frac{Im(\underline{Y}_{meas})}{\omega} = \frac{C_p}{\left(1 + \frac{R_s}{R_p}\right)^2 + (\omega C_p R_s)^2} \quad 3.7$$

$$R_{meas} = \frac{1}{Re(\underline{Y}_{meas})} = R_p \cdot \frac{\left(1 + \frac{R_s}{R_p}\right)^2 + (\omega C_p)^2 R_s^2}{1 + \frac{R_s}{R_p} + (\omega C_p)^2 R_s R_p} \quad 3.8$$

The series resistance due to the lateral charge carrier transport through the window layer to the grid finger can be minimized by reducing the cell dimension b in Figure 17.

3.2.1. Equivalent circuit and Schottky barrier at the back contact

The bottom graph of Figure 18 depicts the band diagram of the default model from Table A - 4 equipped with a Schottky barrier formed at the back contact (BC). To keep the model

simple deep defects within the absorber are not regarded in this section and will be discussed in the next section 3.2.2. The barrier for majority charge carriers at the back contact can be treated analogous to the junction barrier at the front interface. Thus the equivalent circuit of a Schottky barrier can be described by a parallel connection of a resistor R_{BC} and a capacitance C_{BC} . Further all other regions of the solar cell can be modelled likewise, resulting in the equivalent circuit shown in the upper part of Figure 18.

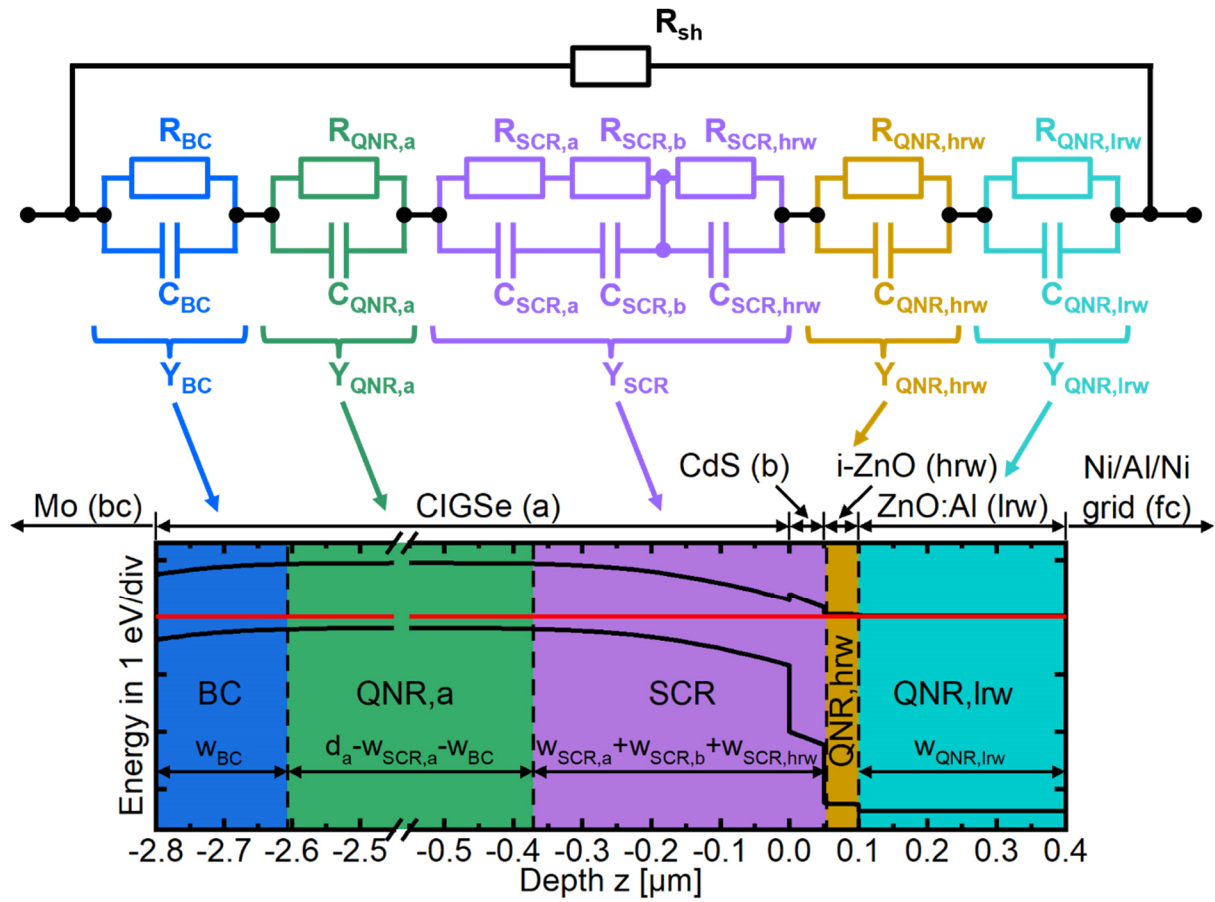


Figure 18 Equilibrium band diagram ($T = 300$ K) and corresponding equivalent circuit regarding the majority charge carriers of the default device equipped with a Schottky barrier ($\Phi_{BC} = 0.4$ eV) at the back contact (BC).

The resistors of the QNR regions i.e. $R_{QNR,a}$ are restricted to the majority charge carriers with

$$R_{QNR,a} = \frac{d_a - w_{SCR,a} - w_{BC}}{q\mu_{p,a}p_a} \quad 3.9$$

and the QNR capacitance $C_{QNR,a}$ follows analogous to the approach in equation 2.23 with

$$C_{QNR,a} = \frac{\varepsilon_a}{d_a - w_{SCR,a} - w_{BC}}. \quad 3.10$$

Both quantities $[R] = \Omega \cdot \text{cm}^2$ and $[C] = \text{nF} \cdot \text{cm}^{-2}$ are related to the device area. In experiment the area is measured with a software tool by taking a picture of the cell and drawing a closed polygon along the cell edges. With the pixel number within the polygon and the pixel size the area becomes measurable. However there are several sources of error mainly (1) the fringed edges of the cell due to mechanical scribing, (2) the definition of the pixel size by means of an element with a known distance within the picture and (3) the aberration of the camera optics. An estimation of the area error revealed $\approx 5\%$, which can be taken directly as the error of the capacitance. Since the measurement of a reference circuit consisting of a 10 nF capacitor and 10 k Ω resistor connected in parallel exhibited an error of $\approx 0.1\%$ in the frequency range from 10^2 to 10^6 Hz for the measured values by the LCR-meter.

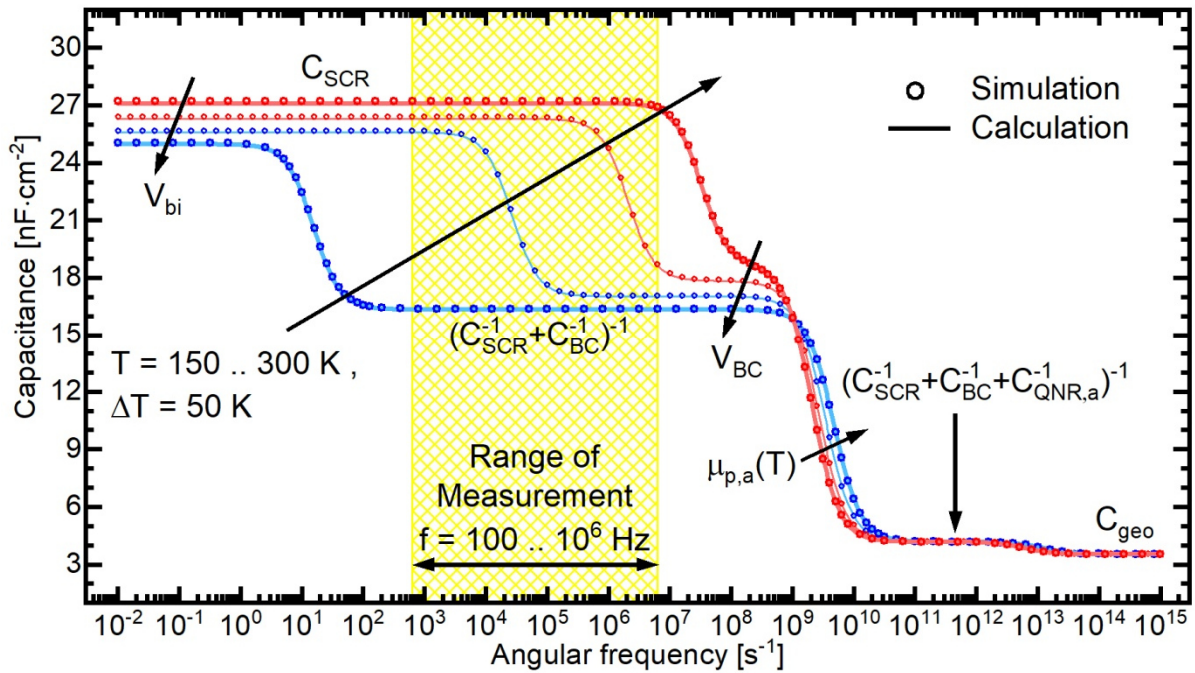


Figure 19 Calculated (solid lines) and simulated (open circles) admittance spectra of the default model given in Table A - 4 as a function of temperature. For calculation the equivalent circuit in Figure 18 was utilized. To illustrate only the impact of a back contact barrier with $\Phi_{BC} = 0.4$ eV defect levels within the absorber and at the interfaces were excluded.

Based on Figure 19, in the following it will be shown that for the interpretation of admittance measurements it is sufficient to utilize the imaginary part of $\underline{Y}_{\text{meas}}$ in the form of the capacitance. Plots of the capacitance over the logarithm of the angular frequency

(subsequently designated with C-f) and as a function of temperature are shown in Figure 19. C-f curves represented by solid lines in Figure 19 are calculated with the equivalent circuit depicted in Figure 18. The open circles in Figure 19 are obtained by numerical simulations. For both, simulations and calculations the input data were the physical quantities of the default model in Table A - 4. In addition the model is equipped with a transport barrier with $\Phi_{BC} = 0.4$ eV for holes at the back contact as depicted in Figure 18. Figure 19 discloses a good match between simulated data by solving numerically the semiconductor equations and analytical data by calculating the equivalent circuit in Figure 18. The determination of the capacitance from calculations is conducted equally to the measurement case. Firstly, the complex admittance \underline{Y} of the complete device can be calculated with

$$\underline{Y} = \frac{1}{R_{sh}} + \left(\frac{1}{\underline{Y}_{BC}} + \frac{1}{\underline{Y}_{QNR,a}} + \frac{1}{\underline{Y}_{SCR}} + \frac{1}{\underline{Y}_{QNR,hrw}} + \frac{1}{\underline{Y}_{QNR,trw}} \right)^{-1}. \quad 3.11$$

Due to the negligible modification of the device admittance by the depletion or accumulation regions within the window layers, these admittances are not regarded in equation 3.11 and Figure 18. Subsequently, by applying equivalent circuit a) of Figure 17 on \underline{Y} the capacitance can be obtained analogous to equation 3.7 with $C = \text{Im}(\underline{Y})/\omega$. The capacitance curves in Figure 19 reveal 3 explicit steps in their progression. For the lowest temperature $T = 150$ K one will find 4 distinct plateaus indicated by C_{SCR} , $(C_{SCR}^{-1} + C_{BC}^{-1})^{-1}$, $(C_{SCR}^{-1} + C_{BC}^{-1} + C_{QNR,a}^{-1})^{-1}$, and C_{geo} . Because of R_{SCR} representing the highest resistance within the device the capacitance converges to C_{SCR} for low frequencies. C_{SCR} was calculated with equation 2.22 and R_{SCR} analogous to equation 2.25 by integrating the inverse conductance $1/\sigma(z)$ over the SCR. A weak temperature dependency can be found for C_{SCR} due to the temperature dependency of V_{bi} in accordance with equation 2.14. The 2nd capacitance plateau results from the hole barrier at the back contact. A strong temperature dependency is visible for the step from C_{SCR} to $(C_{SCR}^{-1} + C_{BC}^{-1})^{-1}$. This strong temperature dependency of the characteristic frequency ω_{BC} follows from the temperature activated resistance $\omega_{BC} \propto R_{BC}^{-1} \propto \exp\{-\Phi_{BC}/k_B T\}$. Accordingly, Φ_{BC} becomes experimentally available by an Arrhenius plot of $\ln(\omega_{BC} \cdot T)$ [Höll13]. For the calculated C-f curves in Figure 19 R_{BC} was obtained by integrating $1/\sigma(z)$ from $z = -d_a$ to $z = -d_a + w_{BC}$. The capacitance of the depletion region at the back contact has been estimated with $C_{BC} = \epsilon_a/w_{BC}$. Due to the weak temperature dependency of the built in voltages V_{bi} and V_{BC} the 2nd capacitance plateau reveals likewise a weak temperature dependency. In contrast, no temperature dependency can be observed for the 3rd and 4th capacitance plateau. Moreover, the 2nd and 3rd capacitance steps are a weak

function of temperature too. This weak temperature dependency originates from the weak temperature activated dielectric relaxation of the quasi-neutral regions with QNR_a causing the 2nd capacitance step as well as QNR_{lrw} and QNR_{lrv} causing the 3rd capacitance step. From Figure 18 the capacitance of QNR_a can be deduced to

$$C_{QNRa} = \frac{\varepsilon_a}{d_a - w_{SCR,a} - w_{BC}} \quad 3.12$$

and the resistance of QNR_a is under the assumption of solely present hydrogen like acceptor states N_{A,a} determined by

$$R_{QNRa} = \frac{d_a - w_{SCR,a} - w_{BC}}{q\mu_{p,a}N_{A,a}}. \quad 3.13$$

The characteristic frequency ω_{QNRa} of the dielectric relaxation of the absorber follows to

$$\omega_{QNRa} = \frac{1}{R_{QNRa}C_{QNRa}} = \frac{q\mu_{p,a}N_{A,a}}{\varepsilon_a}, \quad 3.14$$

giving the temperature dependency $\omega_{QNRa} \propto \mu_{p,a} \propto T^{-3/2}$. In the case that the doping density of the absorber is defined by less shallow acceptors with E_{A,a} the temperature dependency of the characteristic frequency increases to $\omega_{QNRa} \propto \mu_{p,a} / (\exp\{(E_{A,a} - E_F)/k_B T\} + 1)$.

For thick absorber layers with d_a >> d_b it can be shown that the 3rd capacitance plateau corresponds approximately to the geometrical capacitance C_{geo,a} of the absorber.

$$C_{geo,a} \approx (C_{SCR}^{-1} + C_{BC}^{-1} + C_{QNR,a}^{-1})^{-1} = \frac{\varepsilon_a \varepsilon_b}{\varepsilon_a d_b + \varepsilon_b d_a} \approx \frac{\varepsilon_a}{d_a} \quad 3.15$$

In equation 3.15 C_{SCR} has been taken from equation 2.22 and C_{QNR,a} from equation 3.12 the capacitance of the back contact barrier is C_{BC} = ε_a/w_{BC}.

The 4th capacitance plateau indicated with C_{geo} in Figure 19 arises from the dielectric relaxation of the complete device. Due to the high doping density of the window layers the frequency range of C_{geo} is close to the visible range of the electro-magnetic (EM) spectrum. For device modelling a doping density of N_{D,lrw} ≈ 2 · 10¹⁸ cm⁻³ has been chosen to keep the low-resistive window layer non-degenerated. However, in the case of realistic devices the lrw-layer is usually degenerated and it can be assumed that C_{geo} will be obtained in the visible range of the EM spectrum. Thus, C_{geo} is experimentally not observable even with LCR-meter operating with frequencies in the THz range. The frequency range of 100 Hz to 1 MHz used in this work for admittance spectroscopy is indicated by the yellow shaded box in Figure 19.

By varying the temperature the capacitance step of the back contact barrier passes through this frequency range and can be analyzed. Usually, signals in admittance spectroscopy originating from deep defects or transport barriers for the photo-current, which are crucial for solar cell operation possess high activation energies. Hence, these features are not observed in admittance spectroscopy due to low characteristic frequencies $f_0 < 100$ Hz even for high temperatures $T > 300$ K.

3.2.2. Volume and interface defects

In view of the capacitance contribution of a volume defect within the absorber, energetically located within the band gap, this case was comprehensive analysed by Walter et al. [106]. With the result that, if the defect level intersects or grazes the Fermi-level, usually within the depletion region of the absorber (see Figure 3 in Paper 4, section 4.4), and is able to be thermally emptied or occupied by electrons, then a contribution by the defect to the junction capacitance is observable. The origin of this capacitance contribution is a phase shift of the alternating current density induced by the defect related capture and emission process of charge carriers within the bands evoked by the alternating voltage. If the frequency of the alternating voltage reaches and exceeds the characteristic frequency ω_d of the changeability of defect occupation, the capacitance contribution by the defect to the junction capacitance becomes negligible. This condition is characterized by a step in the measured capacitance. As shown by virtue of an interface defect level in Figure 20 a), usually at the low frequency side of the capacitance step the measured capacitance corresponds to the sum $C_{SCR} + C_d$, with C_d the capacitance contribution by the defect, then the high frequency side is determined by the junction capacitance C_{SCR} . This is true, if there are no other admittance modifications by further defects or transport barriers are existent. In the case of an acceptor like defect state centred at $E_d - E_V > E_F - E_V$ (QNR) with asymmetric capture cross-sections $\sigma_p \gg \sigma_n$ and/or an intersection point with the Fermi-level at $z = -z_i > -w_a$ where $p_a(-z_i) \gg n_a(-z_i)$, the characteristic frequency can be deduced from equation 2.69 as shown in Ref. [106] to

$$\omega_d = 2\sigma_p v_p p_0(-z_i) = 2\sigma_p v_p N_{V,a} \exp\left\{-\frac{E_a}{k_B T}\right\}. \quad 3.16$$

At $z = -z_i$ the activation energy corresponds with $E_a = E_d - E_V (= E_F - E_V)$ to the defect energy level. The characteristic frequency ω_d in equation 3.16 represents the inflection point of the capacitance step. Hence, ω_d can be found straightforward by determining the local maximum

in the derivative $-\omega dC/d\omega$ of the measured capacitance frequency curves. The activation energy becomes determinable by an Arrhenius-plot of $\ln(\omega_d T^{-2})$ [179]. The multiplication with T^{-2} within the logarithm is due to the temperature dependency of $v_p \propto T^{1/2}$ and $N_{V,a} \propto T^{3/2}$, the capture cross-section σ_p is assumed to be temperature independent.

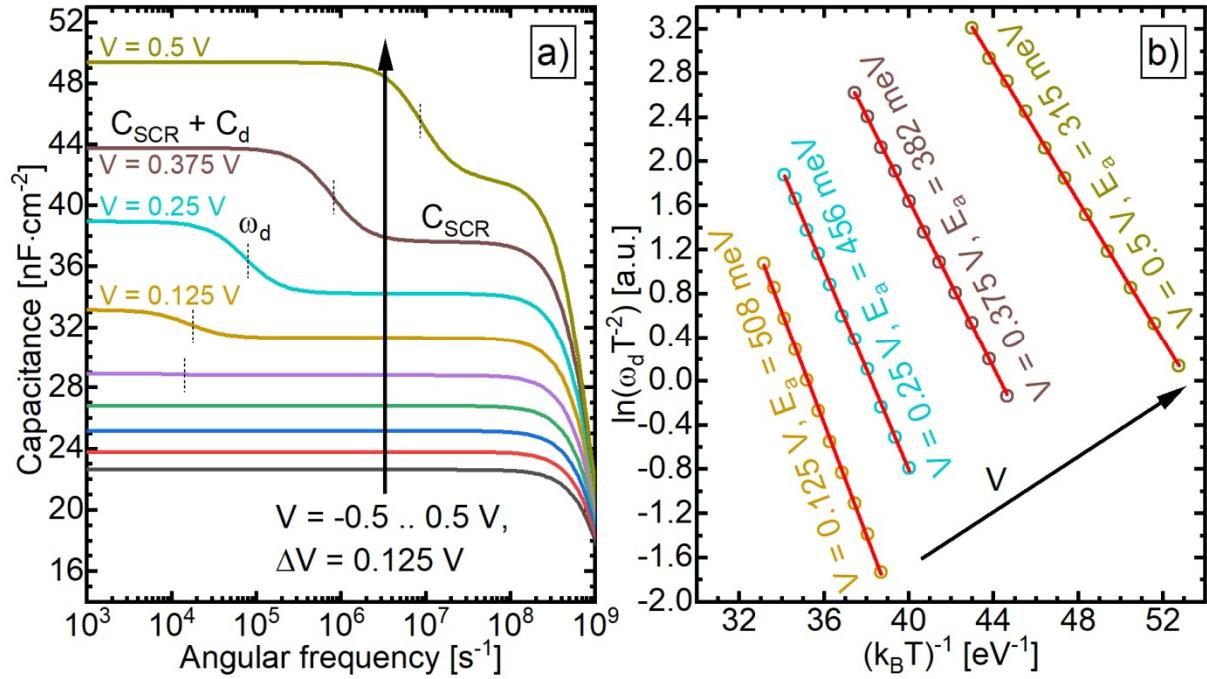


Figure 20 (a) Capacitance frequency curves as a function of the applied bias voltage simulated by means of the default model in Table A - 4 with acceptor states at the CIGSe/CdS interface settled at a discrete level of $E_d - E_V = E_g/2$. Simulations were performed under a constant temperature of $T = 300$ K. The dashed vertical lines are indicating the characteristic frequency ω_d . (b) Arrhenius plots of the temperature corrected logarithm of the characteristic frequency $\ln(\omega_d T^{-2})$ for determining the activation energy E_a as a function of the DC bias of the capacitance step shown at 300 K in (a).

As mentioned above, the intersection of defect and Fermi level is a prerequisite for determining the defect energy level from admittance spectroscopy. Further, at the intersection point the change of occupied defect states becomes maximally, giving the maximum possible capacitance contribution by the considered defect level [106]. With regard to spatially narrow defects, as it is the case for interface defects, the response of IF-states by AC-probing depends strongly on the position of the Fermi-level at the interface. This means in the case of an inverted absorber/buffer interface deep defects would not be observed in equilibrium admittance spectroscopy (completely occupied). This is visible in Figure 20 a) where for bias voltages in reverse direction up to $V = 0$ V no or a negligible capacitance step is observed. However, by applying a bias voltage in forward direction, a condition is created where the occupation of the interface defect level located on midgap of the absorber can be significantly

modified by the AC test signal. Then a contribution by this defect to the junction capacitance becomes available and with increasing forward bias the height of the capacitance step and concomitant the amplitude of the alternating occupation probability of the defect enhances.

In Figure 20 an energetically discrete distributed acceptor like ($\sigma_p = 10^3 \cdot \sigma_n$) defect state was utilized for simulating the voltage dependent capacitance contribution. After equation 3.16 for a bulk defect the obtained characteristic frequencies ω_d and the activation energy E_a of the capacitance steps of this kind of defect are independent from the DC bias voltage. However, as shown in Figure 20 a) and b) for interface states both ω_d and E_a are a function of the DC bias voltage. While ω_d increases, E_a reduces with increasing forward bias. To obtain from measured voltage dependent admittance spectra the characteristic parameters of interface defects like energy level or capture-cross sections the modulated recombination current density $J_{if} = J_{if}(V_{DC}) + \tilde{J}_{if}$ over IF-states has to be derived. With equation 2.66 and $J_{if} = q \cdot (U_{SRH,if}(V_{DC}) + \tilde{U}_{SRH,if})$ the capacitance contribution by IF-states $C_d = \text{Im}(\tilde{J}_{if})/\omega$ can be related to the defect parameters [106, 180, 181]. However, this requires the knowledge about the positions of the quasi-Fermi levels at the interface. Experimentally, these quantities are difficult to access and the modelling of voltage dependent admittance results by device simulations becomes mandatory for quantifying the defect properties of IF-states.

4. Experimental results and device simulation

The subject of this thesis is the understanding of optoelectronic effects in CIGSe semiconductors which occur under different environmental conditions, in particular exposure to air-light combinations. On the one hand it deals with the strategy to experimentally uncover the effects of air-light-exposure (ALE) on bare CIGSe absorber layers and complete solar cells. On the other hand, an electronic simulation model is proposed which describes the impact of ALE on the solar cell physics. The presentation of these studies takes place in the form of peer-reviewed publications [Höl1],[Höl2],[Höl3],[Höl4] in the following referred to by Paper 1, 2, 3, 4. Interpretations of the results in the stated articles are founded on the fundamentals in chapter 2 and the examinations of the measurement methods in chapter 3. Supporting information and considerations for the comprehensive understanding of the presented studies are given in the subsections of sections 4.1 - 4.4.

4.1. ALE induced surface modification

The first indications for ALE surface modification were obtained after long-term TRPL measurements on bare CIGSe layers in ambient air. The TRPL decay time at the end of a particular experiment performed at a particular location of the sample was significantly reduced with respect to the decay time measured at the beginning of the experiment. However by changing the location of excitation on the sample surface, the initial decay time was observed, in spite of identical air exposure. This underlined the role of light for the observed degradation process and culminated in the first publication identifying the ALE effect given in this section with Paper 1. The ALE effect in Paper 1 is named as WLS (white light soak) since at the time of publication the abbreviation ALE was not established. Accordingly, WLS (= ALE) denotes the exposure of bare CIGSe layers to the ambient atmosphere under illumination with 1 sun equivalent white light.

TRPL-measurements in Paper 1 show that the formerly known degradation of the minority charge carrier lifetime of CIGSe due to air-exposure accelerates under illumination. This adds on the one hand to the previous results of Metzger et al. [25, 40]. On the other hand, by applying for the first time XPS-measurements in connection with TRPL-measurements, Paper 1 combines this TRPL-lifetime degradation directly with a modification of the CIGSe surface chemistry. The important results from XPS-measurements are that (1) only the bonding

characteristics of Na, O, and Se are affected by ALE and (2) an accumulation of O and Na on the surface is caused by ALE.

Both methods, TRPL and (even more so) XPS, are sensitive to the surface. Thus, if ALE also affects the bulk region of the CIGSe layer is not determinable with these two methods. Therefore, in order to solve this problem, in Paper 1 complete solar cells were manufactured from CIGSe absorbers with different ALE times. Concomitant to the reducing TRPL-decay time of the bare CIGSe layers, V_{OC} of the related solar cells monotonously decreases with increasing ALE time. That means the detrimental modification of the CIGSe absorber due to ALE persists throughout processing the buffer and window layers. This indicates that the dominant recombination region of the solar cell is the same as the dominant recombination region of the initial bare CIGSe layer. By determining the activation energy of the saturation current density from $V_{OC}(T)$ measurements in Paper 1, the dominant recombination mechanism of solar cells from ALE-treated absorber takes place at the interface. Hence, the reduction of TRPL-decay time due to ALE of bare CIGSe layer is referred to an increased recombination rate of minority charge carriers at the surface.

In conclusion the presented results in Paper 1 are firstly important for manufactures. But also for researchers who are investigating CIGSe absorber layers with charge carrier generating methods either directly in ambient air or after air exposure.

Light induced degradation of Cu(In,Ga)Se₂ thin film surfaces

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We investigate light-induced degradation of Cu(In,Ga)Se₂ (CIGSe) layers by means of time-resolved photoluminescence (TRPL) measurements. Illumination in the range of minutes with 1 sun white light equivalent leads to a strong reduction of the carrier lifetime as determined by TRPL. Ambient storage in the dark, however, does not cause degradation. X-ray photoelectron spectroscopy of the CIGSe surface reveals a light induced enhancement of Na 1s and O 1s core-level emission. The position of the O 1s peak at 531.6 eV is related to a Na-O-CIGSe bonding complex. The light-induced degradation of the CIGSe layer finally translates into inferior open circuit voltages due to the dominance of interface recombination in completed solar cell devices. This study has implications for laboratory research and may need to be regarded in CIGSe module production.

Link to original publication: <http://dx.doi.org/10.1063/1.4992116>

4.1.1. Supporting information and considerations of Paper 1

Correction TRPL decay times

In Paper 1 it was shown that illumination of bare CIGSe layers in ambient (humid) air causes a strong reduction of the decay time in TRPL-measurements. This leads to the assumption that a degradation of the minority charge carrier lifetime takes place during the application of the TRPL-method itself. Typical parameters for the laser-excitation in TRPL measurements are given in Table II of Paper 1 in this section. Therewith, the sample is exposed to an average laser light intensity of $\approx 10^{-3} \text{ Wcm}^{-2}$ (0.01 suns) for a measurement time of $\approx 30 \text{ s}$. With respect to Figure 1 of Paper 2 in the next section 4.2 this corresponds to an ALE light dose of 0.03 Jcm^{-2} and implicates a reduction of the average decay time by 5 - 10% during the measurements in the as fabricated or 18 h storage state. That means it could be expected that the first two sets of decay constants in the inset of Figure 2 in Paper 1 deviate systematically to lower values compared to the “true” decay constants without illumination. After 1 min illumination with 1 sun equivalent white light, called white light soak (WLS), the reduction of decay time caused by the TRPL measurement itself becomes negligible, since the absolute light dose amounts to $\approx 6 \text{ Jcm}^{-2}$, which is located in the region where the reduction of decay time levels off for an intensity of $\approx 10^{-3} \text{ Wcm}^{-2}$ (see Figure 1 in Paper 2).

Na-passivation in dry air

Figure 2 of Paper 1 depicts elongated TRPL-transients of the investigated CIGSe layers after a storage period in dry air (+ N₂) and darkness. This observation is a general characteristic of CIGSe layers with Sodium doping. Usually, the maximum of the time constants is reached after ca. 10 h and stabilizes for 1 - 2 days, if the samples are remaining in darkness and dry air. In comparison with Figure 1 in Paper 1 the latter sample state serves as the starting point of the ALE experiments. In contrast, CIGSe layers without Na reveal no increase of decay times after similar or longer storage periods in dry air. This gives reasons that Sodium is involved in the process of passivation leading to increased decay constants after the exposure to dry air in darkness. The mechanism behind the passivation process may be related to a Na-catalyzed oxygenation of selenium vacancies as explained in section 2.1.3 and assumed in Paper 1.

Experimental and method related ALE

As shown in Figure 3 of Paper 1, keeping CIGSe layers in dry air or even high-vacuum without illumination is no guarantee against the reduction of TRPL decay times. Provided that the layers were exposed to ambient (humid) air, this gives reasons that a participation of adsorbed or already reacted air components, preferably H_2O , are involved in the degradation process.

Further illumination in high-vacuum for 1 h reveals again a strong reduction of the TRPL decay time indicating a photo-catalyzed surface modification. However, the measured TRPL decay is definitively less fast than the decay measured after 10 min illumination in ambient air (compare Figure 2 and 3 in Paper 1). Thus, it is imaginable that the surface reaction is limited by the amount of physically or chemically adsorbed H_2O on the surface. In contrast, the ambient atmosphere constitutes an infinite source of H_2O and the surface reaction proceeds uninhibited, resulting in a stronger reduction of TRPL decay time after a shorter illumination period. Further, exposure to X-rays in ultra high-vacuum causes a similar strong decrease in TRPL time constants, which indicates the involvement of excited charge carriers, presumably electrons, in the detrimental surface reaction. In XPS-measurements this may produce an error due to the method itself especially in the case of non-ALE layers exposed to ambient (humid) air in darkness, serving as the reference.

By comparing the TRPL decay time reduction under high-vacuum in Figure 3 of Paper 1 the participation of excited electrons during ALE reaction becomes equally evident. Thus, after 3 days storage in darkness (thermal excitation) the time constants decrease much less than after 1 h illumination (photon excitation).

Chemistry of AE and ALE

Three distinct differences in the surface chemistry of ALE compared to non-ALE CIGSe layers can be observed in Figure 4 of Paper 1 with (1) a segregation of Na and O at the very surface, (2) a shift of the O 1s and Na 1s XPS peaks to lower binding energies, and (3) an increasing signal of the Se - O bonding. Observation (1) in combination with (3) implies that a bonding complex consisting of O, Na (as found by Heske et al. [46]), and maybe of Se is formed. In spite of this the role of Na during ALE and AE is not straightforward. It is shown by Heske et al. [46] that the adsorption of H_2O takes place at Na bonding sites. Thus, in the case of accumulated Na at the CIGSe surface the Na 1s peak is centred at a binding energy of $E_b \approx 1073.0$ eV. After adsorption of H_2O a shift of the Na 1s peak to a lower binding energy of $E_b \approx 1072.3$ eV is observed in [46]. An identical binding energy of $E_b \approx 1072.2$ eV is found

for the non-illuminated AE sample in Figure 4 of Paper 1, leading to the assumption that Na at the surface of the AE sample is mostly involved in the H₂O adsorption. Further, it can be shown in [46] after desorption of H₂O the Na 1s peak shifts back to the former higher binding energy of $E_b \approx 1073.0$ eV of the clean surface. A reduced intensity of the Na 1s peak after H₂O desorption indicates a Na desorption as well [46].

It is suggested by Heske et al. [45] that the binding type of accumulated Na on the free surface is of enhanced metallic character. In Figure 21 it can be shown that upon H₂O adsorption, the Na 1s binding energy and the kinetic energy of the Na KL₂₃L₂₃ Auger signal are shifted to lower values – indicating a Na bonding state of enhanced ionic character [45, 46]. Further, Figure 21 demonstrates identical Auger parameter of Na for surfaces exposed to ambient air without illumination (AE no light) from Paper 1 and surfaces with adsorbed H₂O (ads. H₂O) from [46]. However, the bonding character of Oxygen for these 2 surface states is different, as discussed below.

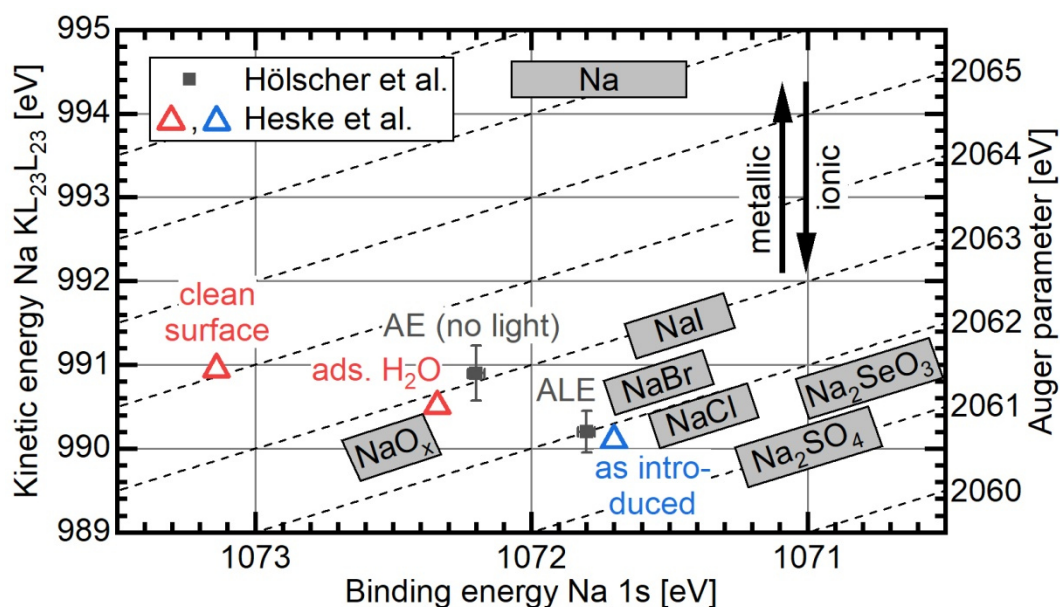


Figure 21 Characteristics of the Auger Na KL₂₃L₂₃ kinetic energy as a function of the Na 1s binding energy for different surface conditions obtained by Heske et al. (red triangles = [46], blue triangles = [45]), respectively paper 1 (squares). The scattered lines represent constant Auger parameter level with a distance of 1 eV, scaled on the right hand side. Determined Auger parameter regions of common Na compounds are indicated by grey squares taken from Ref. [182].

The Auger parameters with ≈ 2063 eV of the latter 2 Na species are in quantitative proximity to the one of NaO_x compounds. In contrast, with an Auger parameter of ≈ 2064 eV the Na compound of the clean surface from Heske et al. [46] matches well that of NaSe_x [139].

For the ALE treated sample, a stronger ionic binding character of Na can be concluded from Figure 21. Thus, the Auger parameter with ≈ 2062 eV corresponds fairly well to the Sodium salts, preferable Na_2SeO_3 or other Na-Se-O compounds. Further, the appearance of a Se-O signal for the ALE treated sample in Figure 4 of Paper 1 supports the thesis of a Na-O-Se complex formed due to ALE.

In accordance with the Na 1s peak, likewise the O 1s peak of the ALE sample reveals a lower binding energy with $E_b \approx 531.6$ eV compared to the AE sample with $E_b \approx 532.5$ eV in Figure 4 of Paper 1. In Ref. [46] it is shown that the O 1s peak for adsorbed H_2O on the CIGSe surface is centred at a binding energy of $E_b \approx 534.0$ eV. Here raises the question if the O 1s peak of the AE sample stands for a third, may be passivating species. Or, is this peak the result of an overlap of the adsorbed O species located at 534.0 eV and the detrimental O species located at 531.6 eV. The answer can be obtained from Figure 22. By a multiple-peak fit consisting of 2 peaks centred at 531.6 eV and 534.0 eV, the O 1s peak from the AE sample cannot reconstructed in Figure 22 a). Only by adding a third peak with a variable peak centre produces a satisfactory fitting result. In Figure 22 b) a binding energy of $E_b \approx 532.3$ eV is found for the third O species. This third O species is a conceivable explanation for increased TRPL decay times observed on CIGSe layers after storage in dry air and darkness. If this oxygen species originates from additional adsorbents such as NO_x , SO_x , and CO_x or from a reaction product of Na and O cannot completely solved in this work. No peak shifts of N, S, and C signals in XPS-measurements are observable between the ALE and the AE sample in Paper 1. Hence, a Na-O bonding complex seems to be most probable.

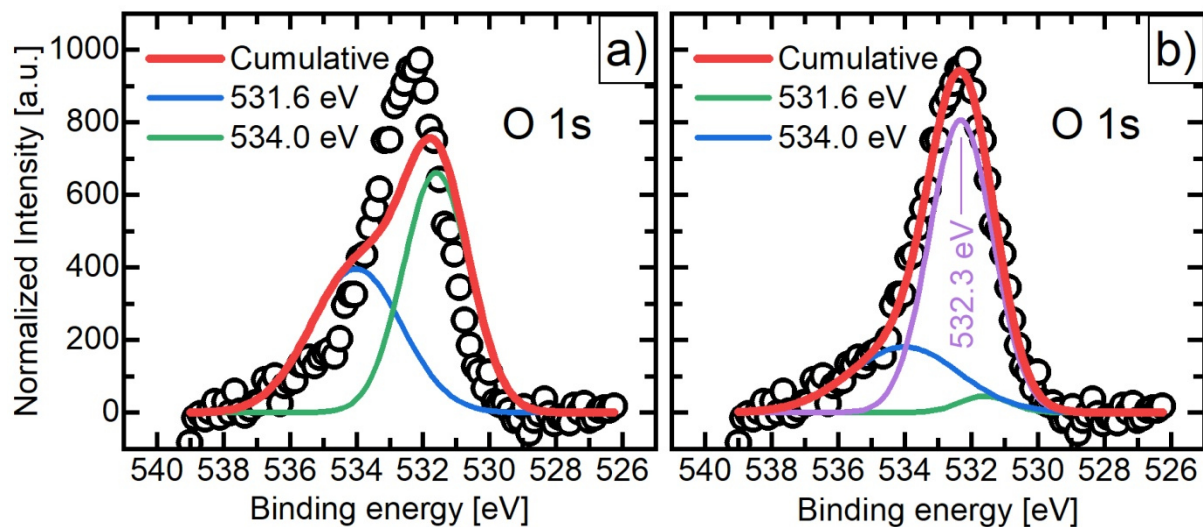


Figure 22 Peak fits of the O 1s core-level of the non-illuminated AE sample shown in Figure 4 of paper 1. With (a) two overlapping Voigt profiles centred invariable at 531.6 eV and 534.0 eV as well as (b) supplemented by a third Voigt profile with a fitted peak centre at 532.3 eV.

A further consistency between Paper 1 and Ref. [46] is the detrimental O species located at a binding energy of $E_b \approx 531.6$ eV. Thus, with a stepwise annealing from 100 K to room temperature a shift of the O 1s peak from 534.0 eV for adsorbed H₂O to 531.6 eV observed in Ref. [46]. Giving reasons that the O state after annealing is identical to the one observed for the ALE sample in Paper 1. The question that remains is, if the O 1s peak shift in [46] is triggered by increasing temperature or by X-ray exposure. Nevertheless, from the finding of [46] a formation of Na₂CO₃ responsible for the detrimental ALE-effect can be excluded. Because the CIGSe surfaces were exposed to H₂O after a sputter cleaning step and subsequently annealed in ultra-high vacuum.

Indications for ALE modifications localized on the surface

A first indication that ALE solely affects the surface can be traced back to the observed Se-O and Na 2s signals in Figure 4 of Paper 1. XPS investigations by Heske et al. [45] revealed that these 2 signals vanish after cleaning the surface by sputtering. The investigated sample in [45] was exposed to ambient air, may be in combination with light. Indications that the “as introduced” status of this sample is equivalent to the ALE treated status in Paper 1 have been obtained from the similar Auger parameters in Figure 21. Niles et al. [139] observed via depth dependent XPS that the concentration of Se bonded to O decreases rapidly by 2 orders of magnitude within the first 4 nm. Whereas, the Oxygen concentration decreases only by 1 order of magnitude at a distance of 12 nm referred to the surface [139].

At the end of Paper 1 it can be shown by $V_{OC}(T)$ -measurements that solar cells with ALE absorbers are dominated by recombination at the CIGSe/CdS interface. This emphasizes the previous argumentation that the lifetime reduction in TRPL-measurements due to ALE can be ascribed to a detrimental modification of the CIGSe surface. Details about the verification of interface recombination are discussed in section 4.3.

4.2. Disclosure of ALE kinetics and self-healing by HLS

The effects of ALE on bare CIGSe layers in Paper 1 of the previous section are obtained with an illumination intensity corresponding to 1 sun (0.1 W cm^{-2}). Exposure of CIGSe layers to such high light intensities is not usual in the processes of manufacturing or handling with contact to ambient air. Therefore, Paper 2 studies ALE as a function of light intensity and light dose. It is shown that reducing the light intensity far below 1 sun is no guarantee against degradation of the TRPL lifetime. The applied light intensities during ALE in Paper 2 are related to a well illuminated laboratory, estimated with 0.003 suns ($3 \cdot 10^{-4} \text{ W} \cdot \text{cm}^{-2}$). Hence, an important observation in Paper 2 is that a retention time for 10 min of the bare CIGSe layer under laboratory conditions reduces the averaged TRPL decay constant down to 30% of its initial value.

In advancement to Paper 1, Paper 2 tracks the impairing effect of ALE on one and the same sample. It is shown by use of TRPL-measurements on CIGSe/CdS devices that the increased recombination of ALE-absorbers is still present after CBD of the CdS buffer layer. A kinetic inhibition of the ALE effect is concluded in Paper 2 from the comparison of TRPL-lifetime reductions of samples with different ALE times but identical light dose. A stronger lifetime reduction of an absorber results into a higher performance deterioration of the completed solar cell.

A fundamental discovery of Paper 2 is the (self-) recovery of ALE devices after HLS under open circuit condition (HLS_{OC}). Thus, all J-V-parameters (except J_{SC}) are levelling up to the values of the non-ALE sample. However this reparation process is metastable and can be revised by applying voltages $\leq 0 \text{ V}$ independent from illumination (DA , HLS_{CC}). The reparation process is accelerated by increased temperatures (here: 85°C), indicating diffusion and/or chemical reactions during the metastable changes of solar cells. Further accompaniments of HLS and the problem of reduced J_{SC} after HLS are discussed in section 4.3.

Critical role of air-light exposure on co-evaporated Cu(In,Ga)Se₂ solar cells

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We present a comprehensive study concerning the light exposure of bare Cu(In,Ga)Se₂ (CIGSe) layers in ambient air and its impact on the electrical properties of the solar cells. With time-resolved photoluminescence (TRPL) a degradation of the minority charge carrier lifetime after air-light exposure of CIGSe layers is observed. This degradation is related to a light induced modification of the CIGSe surface and persists upon completion of the solar cells. A strong reduction in solar cell performance from ~16% down to ~13% reflects the degradation effect of the solar cell's absorber. The deteriorated solar cell performance can be recovered by light soaking of the complete solar cell at increased temperatures of 85 °C.

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4.2.1. Supporting information and considerations of Paper 2

Participation of excited charge carriers during ALE reaction

In Figure 1 (b) of Paper 2 a severe TRPL-lifetime reduction of up to $\approx 15\%$ is obtained after 12 h AE in darkness for sample CIGSe D. As a reminder, while storing bare CIGSe layers for the identical time period in dry air (+N₂) no degradation of the lifetime is observable. This points towards a similar degradation process as effected by ALE, but with thermal excitation of charge carriers instead of light excitation.

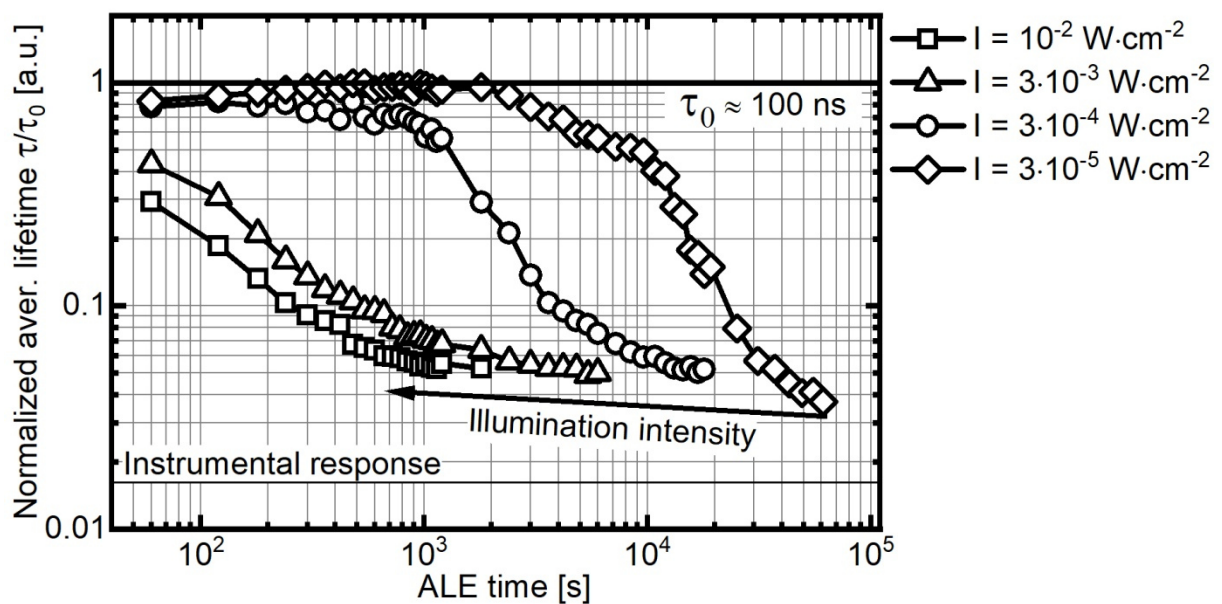


Figure 23 Normalized average decay times as a function of ALE duration for 4 different illumination intensities obtained on bare CIGSe layer of one and the same batch. The initial lifetime of $\tau_0 \approx 100$ ns is used for normalisation.

A further indication that excited charge carriers are involved in the ALE surface modification can be obtained from Figure 23. The shapes of the curves in Figure 23 remind of the kinetics of chemical equilibrium reactions. The reaction velocity depends on the light intensity during ALE, equally to the injection level of excited charge carriers. The 2 lowest intensities in Figure 23 are kinetically inhibited in the first 700 s for $I = 3 \cdot 10^{-4} \text{ Wcm}^{-2}$, and in the first 2000 s for $I = 3 \cdot 10^{-5} \text{ Wcm}^{-2}$. The sample illuminated with the lowest ALE intensity, however, first exhibits an increasing trend (after the initial decay of the lifetime from the reference level τ_0). A possible explanation is that the deteriorating ALE reaction is overcompensated by a passivation reaction. The lifetime enhancement under very low ALE intensities in Figure 23 is

may be subjected to the identical passivation effect observed in Figure 2 of Paper 1 after storage in dry air and darkness.

Band bending at the bare absorber surface

In the former section a competing passivation reaction was considered for the temporarily increasing trend of the normalized decay times under very low ALE intensities. An alternative explanation of this effect can be given with the band bending situation at the surface. It is shown by Heske et al. in Ref. [46] that accumulation of Na at the surface, as equally observed for ALE, effects a downward bending of the bands at the surface. On the other hand in Ref. [46] a reduction of the downward band bending is found after H₂O adsorption, which is referred by the authors to the passivation of Na at the surface. No further band bending in [46] is induced by the detrimental surface reaction of Na + H₂O(ads.) + CIGSe.

With regard to TRPL measurements a severe downward band bending due to Na accumulation at the surface is able to reduce the recombination rate over surface states. The reason is the transport of excited holes away from the surface into the bulk causing a reduction of the hole density at the surface. This translates into a local separation of holes within the bulk from electrons at the surface, reducing the recombination rate over surface states. As a consequence, the TRPL decay should be dominated by transport mechanisms of electrons and holes to recombine with each other. This apparent passivation mechanism (via band bending) depends on the position of the Fermi-level as well as on the density and type of defects at the surface. In order to prove this hypothesis further experiments such as ultra-violet photoelectron spectroscopy (UPS) are necessary.

By further elapse of ALE time, it is assumed that at the point where the decay times in Figure 23 start to fall the downward band bending reduces and surface recombination becomes dominant due to a reduced local separation of charge carriers. However, to describe the strong reduction of the decay time down to 0.05 (5 ns) at the end of ALE in Figure 23 a supporting downward band bending at the surface is mandatory. This can be shown by assuming no surface band bending. In that case, following Maiberg and Scheer [162], the TRPL lifetime $\tau_{n,S}$ is limited by diffusion of minority charge carriers to the surface and can be approximated by

$$\tau_{n,S} = \frac{d_a}{S_n} + \frac{2}{5} \cdot \frac{q}{k_B T} \cdot \frac{d_a^2}{\mu_n} \quad 4.1$$

Using the maximum recombination velocity of $S_n = 10^7$ cm/s for $T = 300$ K and an absorber thickness of $d_a = 2.8$ μm the electron mobility has to be $\mu_n \gtrsim 250$ $\text{cm}^2\text{V}^{-1}\text{s}^{-1}$ to achieve the

final lifetimes of $\lesssim 5$ ns in Figure 23. But, simulations of TRPL experiments reveal electron mobilities with $\mu_n \lesssim 10 \text{ cm}^2\text{V}^{-1}\text{s}^{-1}$ [Höl17], which would corroborate the existence of a downward band bending in the case of dominating surface recombination due to ALE.

Metastable TRPL-transients of CIGSe/CdS devices

In section 3.4 of Paper 2 a metastable character is found for solar cells with ALE absorbers. First it should be mentioned that the depicted progress of J-V-characteristics in Figure 5 of Paper 2 is also observed on devices with non-ALE absorbers, but with smaller amplitude.

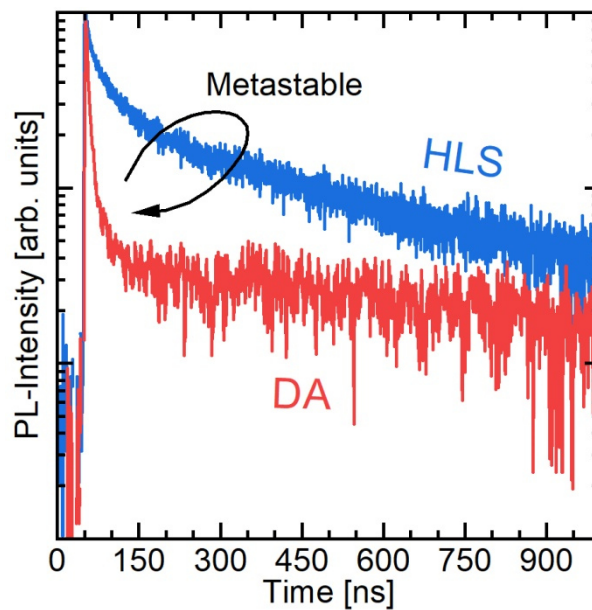


Figure 24 Metastable changes of TRPL-transients examined on CdS covered non-ALE CIGSe layers.

With respect to Figure 24 a metastable character is observable in TRPL-measurements of non-ALE CIGSe + CdS hetero structures too. The shapes of the 2 transients in Figure 24 indicate an enhanced separation of charge carriers in the HLS state. Charge carrier separation translates into a fast initial decay (separation) and a slow second decay (reinjection). The time constant of charge carrier separation is direct proportional to the depletion width of the absorber w_a [163]. This means the steeper the initial decay the smaller is w_a . For a completely depleted buffer layer the depletion width of the absorber as a function of the doping density can be determined from the charge neutrality condition $N_{A,a}w_a = N_{D,b}d_b$. With this in mind, the shapes of the TRPL transients in Figure 24 can be interpreted as follows. In the case of the DA state the separation process is slowly enough (large w_a) that a distinct initial decay appears in TRPL measurements. After HLS the initial time constant decreases (small w_a) and

cannot resolved by the TRPL setup (time resolution ≈ 1.5 ns) anymore. Further, after passing through the initial decay in Figure 24 the PL-Intensity of the HLS transient is ≈ 1 order of magnitude higher, compared to the DA transient. In combination with a faster second decay after HLS this observation can be explained with (1) a smaller depletion width w_a , reducing the spatial distance of separated charge carriers and (2) a lower barrier for reinjection of excited electrons into the absorber bulk (or holes into the depletion region), enhancing the possibility of recombination. The former conclusions point towards an increased p-type doping of the absorber after HLS and may be explains the metastable character of solar cells with non-ALE absorbers. However, as shown in the next section, the recovery of solar cell with ALE absorbers can be referred to a different mechanism evoked by HLS.

4.3. Existence and elimination of dominant interface-recombination

After disclosing the phenomenology of ALE and HLS in the previous sections with Paper 1 and Paper 2, this section concentrates with Paper 3 on the microscopic description of solar cell modifications due to ALE and HLS. In Paper 1 it could be shown with XPS-measurements that ALE modifies the CIGSe surface chemistry. By means of $V_{OC}(T)$ -measurements it was concluded in Paper 1 that this surface modification drives the completed solar cells into dominant interface recombination, reducing V_{OC} and device efficiency. Recent $V_{OC}(T)$ -measurements in Paper 3 are confirming the $V_{OC}(T)$ -results of Paper 1. Investigations by 2 further independent methods, namely $V_{OC}(t)$ -measurements and voltage dependent admittance spectroscopy, Paper 3 gives the unique evidence that interface recombination plays a dominant role in solar cells made of ALE absorbers. In this context, voltage dependent admittance spectroscopy in Paper 3 gives the ability to concatenate interface recombination with the occurrence of a spatially narrow defect response, usually caused by interface states. In the case of non-ALE samples $V_{OC}(T)$ - and $V_{OC}(t)$ -measurements indicates no limitation by interface recombination and hence the occurrence of the spatially narrow defect response is absent, emphasizing the relationship of interface recombination and this admittance signature. As shown in Paper 2 HLS under open circuit condition increases the J-V-parameter (except for J_{SC}) of ALE devices to an identical level observed on non-ALE devices. In Paper 3 this improvement can be correlated with $V_{OC}(t)$ - and $V_{OC}(T)$ -measurements to a relocation of the dominant recombination region from the interface into the absorber bulk (SCR or QNR). This finding is accompanied by a suppression of the spatially narrow defect signal in voltage dependent admittance spectroscopy. With GDOES-measurements before and after applying HLS it can be demonstrated in Paper 3 that the latter results come along with a segregation of Na at the CIGSe/CdS interface.

From the known accumulation of Na found with XPS-measurements in Paper 1 for ALE absorbers, an ambivalent role for Na is concluded in Paper 3. Hence, during ALE the availability of Na acts detrimental to the electronic quality of the absorber surface. Conversely, after HLS a passivation of interface defects by Na becomes evident for devices with ALE absorbers. If this observed passivation effect can be extended to other defect states is still under debate.

Impact of air-light exposure on the electrical properties of Cu(In,Ga)Se₂ solar cells

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The impact of air-light exposure of bare Cu(In,Ga)Se₂ layers is investigated by measuring the performance of completed solar cells. Solar cells formed from air-light exposed absorbers reveal inferior cell parameters by about 10% regarding open circuit voltage, fill factor, and efficiency compared to cells from non-illuminated absorbers. Time-dependent and temperature-dependent open circuit voltage measurements give reasons that the solar cell impairment by air-light exposure of the bare absorbers is due to interface recombination. Interface states are detected by admittance spectroscopy. Heat-light soaking of complete solar cells – having formerly degraded interfaces – recovers the solar cell parameters up to the non-degraded levels. Paradoxically, both the air-light induced degradation of bare absorbers and the revision of cell parameters after light annealing go along with a light induced segregation of sodium at the Cu(In,Ga)Se₂ surface and Cu(In,Ga)Se₂/CdS interface, respectively.

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4.3.1. Supporting information and considerations of Paper 3

Closer inspection of $V_{OC}(t)$ -transients

The study in Paper 3 uses the methods $V_{OC}(T)$, $V_{OC}(t)$, and voltage dependent admittance spectroscopy as introduced in sections 3.1 and 3.2. For simplification, in Paper 3 the results of $V_{OC}(T)$ and $V_{OC}(t)$ are discussed on the basis of a pn^+ structure, giving a type inversion at the interface of the lower doped p-type material. Further the capture cross sections for electrons and holes of interface states are assumed to be equal in Paper 3, resulting in a common reference current density given with equation 3. In spite of this, the conclusions in Paper 3 are not in conflict with the predictions in section 3.1. Moreover, the analysis of the $V_{OC}(t)$ method examined on a $p-n^-n-n^+$ structure in 3.1.2 allows an alternative interpretation of the $V_{OC}(t)$ transients shown in Figure 3 B) of Paper 3. The subject of interest is the change in slope trend after $t \approx 3000$ s of the $V_{OC}(t)$ transients obtained on the 10 and 60 min ALE cells. A possible explanation for this occurrence is given in Paper 3 with passivation of interface state due to long time illumination analogous to the HLS effect. Another explanation can be deduced from Figure 16 on page 68. In the case of acceptor like interface states (as found in Paper 4) for the declining part of the $V_{OC}(t)$ -transient it holds $S_{n,if}n_{if,a} > S_{p,if}p_{if,a}$ and the recombination current density over inface states is limited by the voltage dependent hole density at the surface. After passing through the minimum of the $V_{oc}(t)$ transient at $t \approx 3000$ s the recombination current density becomes limited by electrons ($S_{n,if}n_{if,a} < S_{p,if}p_{if,a}$) causing an increasing trend of $V_{OC}(t)$. As shown in Figure 16 on page 68 the change of a decreasing to an increasing slop can be directly correlated to an increasing doping density $N_{A,a}$ of the absorber, resulting in an increased electron and decreased hole barrier at the CIGSe/CdS interface.

Indication for dominating SCR recombination after HLS

In Paper 3, Figure 6 A) it remarkable that for both, ALE and non-ALE-samples, the activation energy E_A of the saturation current density increases to 1.28 eV after HLS. In section 3.1.1 (see Figure 15) it was figured out that $E_A = E_{g,a} + 3 \cdot kT$ should be obtained for a device limited by QNR recombination. With the narrowing of a uniform band gap energy corresponding to $E_{g,a} = 1.15$ eV, in Paper 3 the non-ALE device before HLS can be verified with $E_A = 1.24$ eV $\approx E_{g,a} + 3 \cdot kT$ to be dominated by QNR recombination. After HLS the activation energy is increased by additional 0.04 eV ≈ 1.5 kT giving $E_A = 1.28$ eV $\approx E_{g,a} + 4.5 \cdot kT$. The relation $E_A = E_{g,a} + 4.5 \cdot kT$ was found in section 3.1.1 for (1) a device limited by recombination over donor states at the interface or (2) a device dominated by recombination within the SCR.

Under the made assumption that $V_{OC}(t)$ under red light illumination is a function of the doping density $V_{OC}(t) \rightarrow V_{OC}(N_{A,a})$ as well, dominating recombination over donor states at the interface after HLS can be ruled out. Because in section 3.1.2 (Figure 16, page 68) a decreasing trend of V_{OC} for increasing $N_{A,a}$ is found in the case of dominant recombination over IF-donor states. Hence, with the observation of $E_A = 1.28 \text{ eV} \approx E_{g,a} + 4.5 \cdot kT$ in Figure 6 A) and increasing trends for all $V_{OC}(t)$ -transients in Figure 6 B) of Paper 3, dominating SCR recombination should be taken into account after HLS, which seems to be independent from the ALE status of the absorber. With this background it can be concluded that HLS drives the solar cell into dominating SCR recombination.

Reduced depletion width of the absorber after HLS

A systematic by-product of HLS is the reduction of J_{SC} by $\approx 1 \text{ mA} \cdot \text{cm}^{-2}$. From Figure 5 in Paper 3 it is apparent that this effect is independent from the ALE status of the absorber layer. For solar cells with non-ALE absorbers this produces a loss in device efficiency after HLS. With the external quantum efficiency (EQE), measured on a non-ALE device, in Figure 25 the loss in J_{SC} after HLS can be referred to range of the light spectrum. A reduced collection-efficiency for long wavelengths is a typical sign of a shorter depletion width w_a usually caused by an increased doping density $N_{A,a}$ of the absorber. This finding supports the postulated change in depletion width, describing the metastability of TRPL transients obtained on CIGSe + CdS hetero-structures in section 4.2.1.

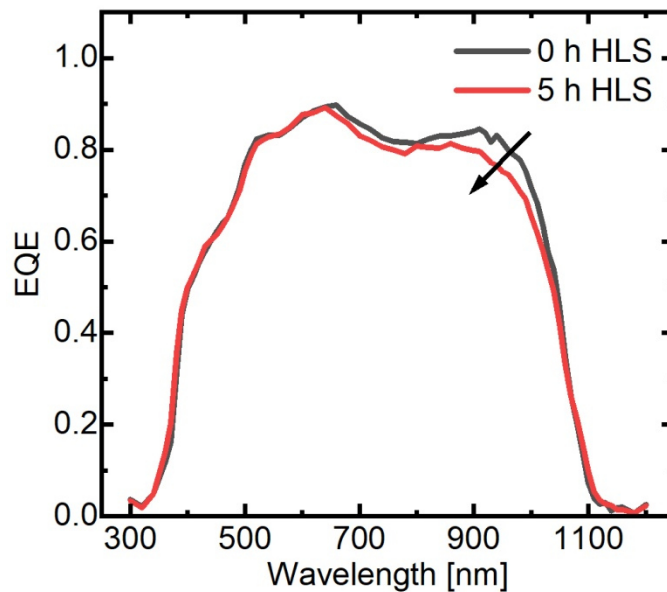


Figure 25 External quantum efficiency as function of HLS duration measured on the non-ALE device of the study in paper 3.

4.4. Quantification of interface defects and device modelling

An important result from Paper 3 of the previous section was the identification of an interface defect level responsible for dominating interface recombination in solar cells made of ALE absorbers. In order to elucidate the physical properties of these defect states, in Paper 4 one-dimensional numerical device simulations with SCAPS 1d is performed.

From a detailed analysis of voltage dependent admittance spectra, 3 distinct signals are found for ALE devices in Paper 4. These signals can be ascribed to the common N1-effect, a deep bulk defect (B), and the ALE induced interface defect (IF). By comparing simulated admittance- and J-V-data with the experimental curves the parameter room of the 3 signatures could be narrowed down to the following solutions.

- N1 This signal is best modelled in Paper 4 with a transport barrier for majority carriers at the back contact as proposed by Eisenbarth et al. [77]. However, Paper 4 regards for the first time the weak temperature dependence of the characteristic frequency of the N1-feature in admittance spectroscopy. Thus the transport barrier has to be supplemented by an interfacial layer (IL) in between the absorber and the metallic back contact. This layer is specified by an unusual low effective density of states of the valence band ($N_V \approx 10^{16} \text{ cm}^{-3}$) to allow the weak temperature dependence of the N1 characteristic frequency.
- (B) In Paper 4 a deep donor trap located energetically close to midgap well describes this signature. (B) here is referred to the 2nd ionization-level $D2(+/+)$ of the shallow minority charge carrier trap $D2(0/+)$ found in earlier studies by simulations of TRPL-experiments [Höl7],[Höl8],[Höl9]. This assumption is based on (1) the strong asymmetrical capture cross sections for electrons ($\sigma_n = 10^{-11} \text{ cm}^2$) and holes ($\sigma_p = 10^{-19} \text{ cm}^2$) as well as (2) the identical defect density of (B) and $D2(0/+)$.
- (IF) Finally, in Paper 4 the interface states caused by ALE are found to be of acceptor type. Hence, the capture cross sections amount to $\sigma_p = 3 \cdot 10^{-11} \text{ cm}^2$ for holes and $\sigma_n = 4 \cdot 10^{-16} \text{ cm}^2$ for electrons. Energetically, the IF-defect is Gaussian distributed with a standard deviation of $\sigma(E_d) = 0.15 \text{ eV}$ located at $E_d = 0.3 \text{ eV}$ above the valence band. The integrated 2 dimensional defect density resulted in $N_d = 3.5 \cdot 10^{11} \text{ cm}^{-2}$.

The main achievements of Paper 4 are the establishment of a physical model for the ALE affected CIGSe/CdS interface as well as an alternative interpretation of the N1-response in admittance spectroscopy.

Device simulation of Cu(In,Ga)Se₂ solar cells by means of voltage dependent admittance spectroscopy

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The simulation of solar cell devices is important for the understanding of defect physics and loss mechanisms in real solar cells. On the other hand, voltage dependent admittance spectroscopy delivers essential information for establishing a baseline simulation model of Cu(In,Ga)Se₂ (CIGSe) solar cells. Here we give an explanation for the weak temperature dependence of the N1-signal, the latter being not compatible with a bulk defect or with a simple hole barrier at the Mo back contact. Furthermore, we find a $E_{d,IF} - E_V \approx 0.3$ eV deep recombination-active acceptor state at the absorber/buffer interface made of air-light exposed CIGSe absorbers. This gives us the ability to explain the reduction of power conversion efficiency of solar cells made from air-light exposed absorbers. From the voltage dependent capacitance step of this interface defect we can deduce the formerly unknown position of the Fermi level at the hetero junction in equilibrium which is close to mid-gap. Simulation of dark J-V curves allows a refinement of the parameter of this absorber/buffer interface defect, resulting in a defect density of $N_{d,IF} \approx 3.5 \cdot 10^{11} \text{ cm}^{-2}$ as well as capture cross sections of $\sigma_n \approx 4 \cdot 10^{-16} \text{ cm}^2$ for electrons and $\sigma_p \approx 3 \cdot 10^{-11} \text{ cm}^2$ for holes.

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5. Conclusion

The objective of this work was to disclose the decisive role of light during air exposure (AE) of bare CIGSe layers and its impact on complete solar cells. In this context the abbreviation ALE for air-light exposure was introduced. To discriminate between the effects induced by AE and ALE, bare CIGSe absorber layers were exposed to ambient (humid) air for identical time frames, but with (ALE) and without (AE) white light illumination. The crucial differences found for AE and ALE absorbers are summarized in the following enumeration.

1. With TRPL-measurements it was shown that ALE with high light intensities (1 sun) causes after a short time (10 min) a severe reduction by 2 orders of magnitude for the evaluated minority charge carrier lifetime. Reducing the ALE light intensity by a certain factor cannot be transferred to an extension of ALE-time by the same factor. Accordingly, ALE with 0.03 suns for 10 min elicits equally a severe lifetime reduction of up to 1 order of magnitude in TRPL measurements. In contrast, even after 12 h storage of CIGSe absorbers in ambient (humid) air without illumination, almost no reduction in TRPL-lifetime is observed.
2. The investigation of CIGSe surfaces via XPS after ALE and AE with identical time frames revealed in the case of the ALE sample a higher concentration of Na and O at the very surface. Further, it could be shown that ALE effects a shifting of the Na 1s and O 1s signal peaks to lower binding energies. These peak shifts have been attributed to a chemical reaction of O and Na at the CIGSe surface, forming a detrimental Na-O-CIGSe complex as suggested by Heske et al. [46]

After identifying the ALE-effect on bare CIGSe absorber layers, solar cells made from ALE absorbers became the subject of investigations. Generally, reduced J-V-parameter (except J_{sc}) are obtained on devices with ALE absorbers, indicating that the detrimental surface modification found with XPS is not removed throughout processing the buffer (and window) layer. The reduction in J-V-parameter depends on the ALE-time and light intensity, but not on the ALE light dose. Correspondingly, it was shown that a constant ALE light dose under varying ALE-times and light intensities gives different degrees of J-V-parameter reduction. With the result that the longest ALE-time in combination with the lowest light intensity causes the highest decrease in J-V-parameter, pointing towards a kinetically inhibited reaction during ALE. In this work the highest reductions in J-V-parameter due to ALE have been observed with $\Delta V_{oc} \approx -140$ mV, $\Delta FF \approx -10\%$, and $\Delta \eta \approx -5\%$. By means of $V_{oc}(T)$ - and

$V_{OC}(t)$ -measurements these reductions were traced to dominant recombination at the absorber/buffer interface. The reason for increased interface recombination could be related to the occurrence of an interface defect signature obtained on ALE devices in voltage dependent admittance spectroscopy. In comparison, for non-ALE samples no dominant interface recombination were deduced from $V_{OC}(T)$ - and $V_{OC}(t)$ -measurements. Thus, no signature of an interface defect was detected in voltage dependent admittance spectroscopy of non-ALE solar cells.

In the further course it could be shown that after applying a HLS for several hours under open-circuit conditions recovers the inferior J-V-parameter of ALE cells comparable to the level of non-ALE cells. However, after DA the J-V-parameter relaxes back to the former inferior state. By a repeated application of HLS the solar improves again, indicating a metastable characteristic of the HLS and DA state. A similar behaviour was also observed for solar cells with non-ALE absorbers. For these samples the metastable character was referred to a change of the absorber doping density (increased after HLS, reduced after DA.) The increased absorber doping density was considered responsible for the reduced J_{SC} after HLS due to a shortened depletion width within the absorber. Consequently, HLS has a detrimental effect on the performance of non-ALE solar cells. The improving effect of HLS on ALE devices could be referred to a spatially redistribution of Sodium. In this context, GDOES depth profiles revealed a HLS induced accumulation of Na at the absorber/buffer interface. In combination with the vanishing of the interface defect response in voltage dependent admittance spectroscopy, a passivating role was concluded for Sodium. If the redistribution of Na is also responsible for the increased absorber doping after HLS is addressed to future work. Finally, the properties of the detrimental defect states at the absorber/buffer interface caused by ALE were uncovered by 1 dimensional device simulations. This interface defect was found to be of acceptor type levelled on $E_d - E_V = 0.3$ eV with a density of $N_d = 3.5 \cdot 10^{11}$ cm⁻². The energetic distance to E_V of this defect level matches well the activation energy of the often observed N2-signature in admittance spectroscopy of the literature [106, 183]. If the here found interface signature could also be responsible for the N2-bulk signature is still under debate.

The results of this work are relevant for manufactures and laboratories, which are working with bare CIGSe layers under ambient conditions. On the other hand the ALE effect should be regarded in device development. As observed by Reichardt et al. [184] replacing the CdS buffer layer by Zn(O,OH) creates a photo-induced oxygenation of Se at the absorber/buffer interface due to X-ray irradiation.

6. Outlook

Proposals for future works concerning the ALE effect are given with the following key notes.

- In this study the soda lime glass substrate was acting as the source for Sodium incorporation into the CIGSe layer. A more modern method is the incorporation of Sodium by a NaF post-deposition treatment. Preliminary results reveal equally a strong reduction of TRPL-lifetimes after ALE (see Figure 6 on page 21). But, the J-V-parameter of complete solar cells appeared to be unaffected by ALE. The reasons are still unclear.
- Further, doping of CIGSe with Na and additional heavier alkaline metals (K, Cs, Rb) is a prerequisite for achieving highly efficient solar cells. In the case of Potassium, from XPS and SIMS measurements a KInSe_2 layer is found on the CIGSe surface [7]. In spite of the changed surface chemistry, TRPL measurements in Figure 26 reveal likewise a significant lifetime reduction after ALE for CIGSe layers with additional doping of heavier alkaline dopants (K, Cs, Rb). However, due to the lack of non-ALE absorbers, acting as references, solar cells have not been fabricated from these absorbers. Accordingly, if the TRPL-lifetime reductions in Figure 26 translate as well into inferior performances of complete solar cells have not yet been verified.

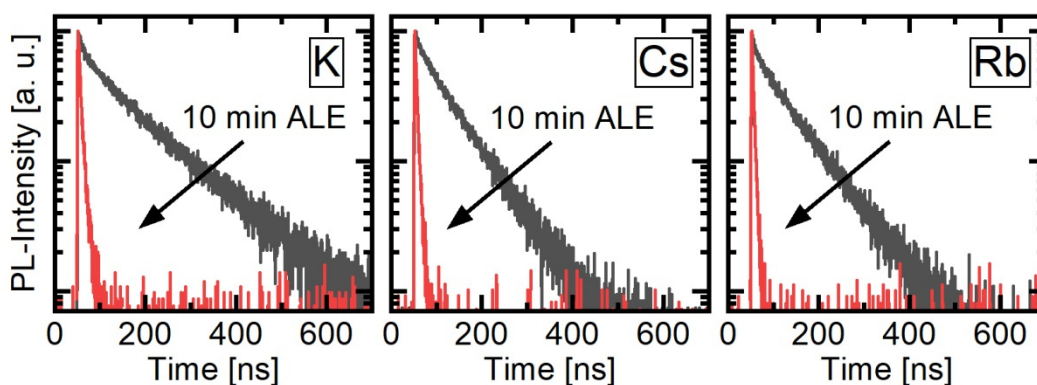


Figure 26 TRPL-transients before (black) and after 10 min ALE (red) of 3 CIGSe layers differing in the additional doping element K, Cs, and Rb. The light intensity during ALE was $0.1 \text{ W}\cdot\text{cm}^{-2}$. Na-doping of the CIGSe layers took place via in-diffusion from the SLG substrate at high substrate temperatures. Incorporation of K, Cs, and Rb was achieved by PDT.

- UPS measurements seem to be suitable to enlightening the transport phenomena of minority charge carriers during TRPL measurements. By determining the surface band

bending and Fermi-level position with UPS, a simulation model for the description of the strong lifetime reduction in TRPL experiments could be established. This gives deeper insights into the status of ALE CIGSe layers before depositing the CdS buffer layer. And, may be counteractions to revise the ALE effect can be developed.

- To uncover the role of excited charge carriers on the ALE reaction, ALE with photon energies smaller than the CIGSe band gap could be performed. As light sources IR-lasers or IR-LEDs with a narrow line width should be chosen. Because, it was found that ALE with white light illumination through to different long-pass filters delivered no consistent results in TRPL-measurements. So that the strongest lifetime reduction was observed on the sample illuminated with the longest wavelength range of the white light source.
- Temperature dependent ALE with low light intensities should give the ability to determine the activation energy and may be the kinetic inhibition of ALE reactions.

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A. Appendixes

A.1. Potential curve of a n-n⁺-hetero-junction

Using the Schottky approximation fails in the case of deriving the potential curve for a junction with two equal doped layers like an n-n⁺-junction. The reason is that on the higher n⁺-doped side (here the low resistive window = lrw) the depletion of majority charge carriers will not create a positive space charge with the host doping density $N_{D,lrw}$. On the other hand the space charge region within the moderate n-doped layer (here the high resistive window = hrw) is generated by electrons diffused from the n⁺-region into the n-region. With the interface located at $z = 0$ and under the assumption that the Debye length λ_D is much smaller than the width of the layer, the Poisson equation of each space charge region reads to

$$-\frac{d^2\varphi_{hrw}}{dz^2} = \frac{dE_{z,hrw}}{dz} = \frac{\rho_{hrw}(z)}{\varepsilon_{hrw}} = \frac{q(N_{D,hrw} - n(z))}{\varepsilon_{hrw}} \text{ for } z \leq 0, \quad \text{A.1}$$

$$-\frac{d^2\varphi_{lrw}}{dz^2} = \frac{dE_{z,lrw}}{dz} = \frac{\rho_{lrw}(z)}{\varepsilon_{lrw}} = \frac{q(N_{D,lrw} - n(z))}{\varepsilon_{lrw}} \text{ for } z > 0.$$

Under the assumption of $\lambda_{D,hrw}, \lambda_{D,lrw} \ll d_{hrw}, d_{lrw}$ both layers can be considered as extended to infinity. Then, in the case of impurity exhaustion, the electron densities are $n(-\infty) \approx N_{D,hrw}$ and $n(+\infty) \approx N_{D,lrw}$. The boundary conditions of the electric fields are $E_{z,hrw}(-\infty) \approx 0$ and $E_{z,lrw}(+\infty) \approx 0$. Per definition the electric potential is set to 0 for $z \rightarrow -\infty$ giving $\varphi_{hrw}(-\infty) \approx 0$. In the following an analytical solution of equation A.1 is exemplary derived for the accumulation region of the hrw-layer. With the above given boundary conditions of the electron densities and the electrostatic potential. Further by applying the chain rule for the derivative of the electric field equation A.1 can be reformulated to

$$-\frac{d^2}{dz^2} \varphi_{hrw}(z) = -E_{hrw}(z) \cdot \frac{dE_{hrw}(z)}{d\varphi_{hrw}(z)} = \frac{qN_{D,hrw}}{\varepsilon_{hrw}} \left(1 - \exp\left\{ \frac{q\varphi_{hrw}(z)}{k_B T} \right\} \right). \quad \text{A.2}$$

Integration of equation A.2 and using the boundary conditions $E_{z,hrw}(-\infty) \approx 0$, $\varphi_{hrw}(-\infty) \approx 0$ gives

$$\frac{[E_{hrw}(z)]^2}{2} = \frac{qN_{D,hrw}}{\varepsilon_{hrw}} \left(\frac{k_B T}{q} \left(\exp \left\{ \frac{q\varphi_{hrw}(z)}{k_B T} \right\} - 1 \right) - \varphi_{hrw}(z) \right). \quad \text{A.3}$$

With a series expansion of the exponential term

$$\exp \left\{ \frac{q\varphi_{hrw}(z)}{k_B T} \right\} \approx 1 + \frac{q}{k_B T} \varphi_{hrw}(z) + \frac{1}{2} \left[\frac{q}{k_B T} \varphi_{hrw}(z) \right]^2 \quad \text{A.4}$$

equation A.3 can be simplified to

$$\left[\frac{d}{dz} \varphi_{hrw}(z) \right]^2 = \frac{q^2 N_{D,hrw}}{k_B T \varepsilon_{hrw}} [\varphi_{hrw}(z)]^2 = \frac{1}{\lambda_{D,hrw}^2} [\varphi_{hrw}(z)]^2 \quad \text{A.5}$$

with $\varphi_{hrw}(-\infty) \approx 0$ the solution of equation A.5 is

$$\varphi_{hrw}(z) = C_1 \exp \left\{ \frac{z}{\lambda_{D,hrw}} \right\} \text{ for } z \leq 0. \quad \text{A.6}$$

For the low resistive window one will find

$$\varphi_{lrw}(z) = \Delta\varphi_w - C_2 \exp \left\{ -\frac{z}{\lambda_{D,lrw}} \right\} \text{ for } z > 0, \quad \text{A.7}$$

where $\Delta\varphi_w$ correspond to the complete potential drop over the junction of the 2 window layers (see equation 2.18). The constants C_1 and C_2 can be determined from the continuity of the electric field $\varepsilon_{hrw} \cdot E_{hrw}(0) = \varepsilon_{lrw} \cdot E_{lrw}(0)$ and the electrostatic potential $\varphi_{hrw}(0) = \varphi_{lrw}(0)$ at the metallurgical interface. Finally the potential curves in the particular region are resulting to

$$\begin{aligned} \varphi_{hrw}(z) &= \Delta\varphi_w \cdot \frac{\varepsilon_{lrw} \lambda_{D,hrw}}{\varepsilon_{lrw} \lambda_{D,hrw} + \varepsilon_{hrw} \lambda_{D,lrw}} \exp \left\{ \frac{z}{\lambda_{D,hrw}} \right\} \text{ for } z \leq 0, \\ \varphi_{lrw}(z) &= \Delta\varphi_w \left(1 - \frac{\varepsilon_{hrw} \lambda_{D,lrw}}{\varepsilon_{lrw} \lambda_{D,hrw} + \varepsilon_{hrw} \lambda_{D,lrw}} \exp \left\{ -\frac{z}{\lambda_{D,lrw}} \right\} \right) \text{ for } z > 0. \end{aligned} \quad \text{A.8}$$

A.2. General properties of simulation models

Table A - 1 Overview of default device and simulation parameter, the reference temperature of physical quantities is $T = 300$ K.

Physical quantity	$B_{rad,a}$ [$\text{cm}^3 \cdot \text{s}^{-1}$]	$B_{rad,b}, B_{rad,w}$ [$\text{cm}^3 \cdot \text{s}^{-1}$]	$v_{th,p}, v_{th,n}$ [$\text{cm} \cdot \text{s}^{-1}$]	R_S [$\Omega \cdot \text{cm}^2$]	R_{Sh} [$\Omega \cdot \text{cm}^2$]
Value	$5 \cdot 10^{-11}$	--	10^7	$1.5 \cdot 10^{-2}$	$4 \cdot 10^3$
Numerical quantity	N discretisation levels	j confidence interval			
Value	100	7 (tail) 6 (gaussian)			

Table A - 2 Temperature dependency of physical variables for solar cells simulated under varying temperatures.

General quantity	$v_{th,p}, v_{th,n}$	$N_{C,v}$	R_S	R_{Sh}	
Proportionality	$T^{1/2}$	$T^{3/2}$	const.	const.	
Absorber	$B_{rad,a}$	μ_p	μ_n	Defects	
				σ_p	σ_n
Proportionality	const.	$T^{3/2}$	const.	T^1	T^1
Buffer, window	μ_p, μ_n	Defects			
		σ_p, σ_n			
Proportionality	const.	const.			

Table A - 3 Optical properties of the particular layers of simulated solar cells.

Layer	Back contact Mo	Absorber CIGSe	Buffer CdS	Window		Front contact Ni/Al
				i-ZnO	ZnO:Al	
Absorption	0	Calculated from Table B.1 in Ref. [74] with $x = 0.23$	Calculated from Table B.2 in Ref. [74]		0	
Reflectivity, Interference	0	0	0	0	0	

A.3. Physical quantities: Default simulation model

Table A - 4 Numerical values of the physical layer properties of the default simulation model used in section 2 and 3. Energy level of interface states are referred to the band edges of the CIGSe absorber. (A) indicates default properties for acceptor like states and (D) for donor like states.

Properties	Layer	Back contact	Absorber	Interface	Buffer	Window		Front contact
						i-ZnO	ZnO:Al	
d [μm]		Mo	CIGSe	CIGSe/CdS	CdS	0.05	0.3	Ni/Al
Φ_{m}, χ_e [eV]		Flat band ^{a)}	4.5	--	4.4	4.5	4.5	Flat band ^{a)}
E_g [eV]		--	1.15	--	2.4	3.3	3.4	--
ϵ_r		--	13.6	--	10	9	9	--
N_C [cm^{-3}]		--	$7 \cdot 10^{17}$	--	$4 \cdot 10^{18}$	$4 \cdot 10^{18}$	$4 \cdot 10^{18}$	--
N_V [cm^{-3}]		--	$1.5 \cdot 10^{19}$	--	$9 \cdot 10^{18}$	$9 \cdot 10^{18}$	$9 \cdot 10^{18}$	--
μ_n [$\text{cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$]		--	10	--	20	20	20	--
μ_p [$\text{cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$]		--	10	--	20	20	20	--
$N_{A,D}$ [cm^{-3}]		--	$7 \cdot 10^{15}$ (A)	--	$4 \cdot 10^{15}$ (D)	$1.71 \cdot 10^{18}$ (D)	$2 \cdot 10^{18}$ (D)	--
Defect properties								
N_d [cm^{-3}], $N_{d,IF}$ [cm^{-2}]		--	10^{13} (D)	10^{11} (A, D)	$3 \cdot 10^{15}$ (A)	10^{18} (A)	10^{16} (A)	--
$E_d - E_V$ [eV]		--	Midgap	Midgap	Midgap	Midgap	Midgap	--
E_{char} [eV]		--	Discrete	Discrete	Discrete	Discrete	Discrete	--
σ_n [cm^2]		--	10^{-12}	10^{-15} (A), 10^{-12} (D)	10^{-15}	10^{-15}	10^{-15}	--
σ_p [cm^2]		--	$5 \cdot 10^{-15}$	10^{-12} (A), 10^{-15} (D)	10^{-12}	10^{-12}	10^{-12}	--
τ_{n0} [ns]		--	10	--	33	0.1	10	--
τ_{p0} [ns]		--	2000	--	$3.3 \cdot 10^{-2}$	10^{-4}	10^{-2}	--
Recombination velocities								
S_{n0} [$\text{cm} \cdot \text{s}^{-1}$]		10^4	$5.1 \cdot 10^3$	10^3 (A), 10^6 (D)	$4 \cdot 10^3$	$7.2 \cdot 10^4$	$7.2 \cdot 10^3$	10^7
S_{p0} [$\text{cm} \cdot \text{s}^{-1}$]		10^7	$3.6 \cdot 10^2$	10^6 (A), 10^3 (D)	$1.3 \cdot 10^5$	$2.3 \cdot 10^6$	$2.3 \cdot 10^5$	10^7

^{a)} Flat band denotes a variable metal work function Φ_m adjusted to the majority carrier Fermi level with the result that no band bending occurs at the metal contacts.

A.4. Physical quantities: Simulation model of Paper 4

Table A - 5 Numerical values of the physical layer properties of the extended simulation model used in paper 4 (section 4.4). Energy level of interface states are referred to the band edges of the CIGSe absorber. (G) means Gaussian distributed, and (T) means tail like distributed.

Properties	Layer	Back contact	Interfacial layer	Absorber					Interface		
				MoSe _x	CIGSe	D1	D2	A _{IF}		D _{IF}	
d [μm]		Mo	MoSe _x	CIGSe	2.77					CIGSe/CdS	--
Φ _{in} , χ _e [eV]		5.5	4.5	4.5							--
E _g [eV]		--	1.15	1.15							--
ε _r		--	13.6	13.6							--
N _C [cm ⁻³]		--	7·10 ¹⁷	7·10 ¹⁷							--
N _V [cm ⁻³]		--	5·10 ¹⁵	1.5·10 ¹⁹							--
μ _n [cm ² ·V ⁻¹ ·s ⁻¹]		--	10	10							--
μ _p [cm ² ·V ⁻¹ ·s ⁻¹]		--	10	10							--
N _{A,D} [cm ⁻³]		--	10 ¹⁵ (D)	7·10 ¹⁵ (A)							--
Defects		--	Acceptor	A1	A2	D1	D2	A _{IF}	D _{IF}		
N _d [cm ⁻³], N _{d,IF} [cm ⁻²]		--	10 ¹³	3·10 ¹⁶	4·10 ¹⁶	10 ¹³	1.5·10 ¹⁶	3.5·10 ¹¹	2.86·10 ¹¹		
E _d - E _v [eV]		--	Midgap	0	0.45	Midgap	0.965	0.3	0.965		
E _{char} [eV]		--	Discrete	0.08 (T)	0.3 (G)	Discrete	0.035 (G)	0.15 (G)	0.035 (G)		
σ _n [cm ²]		--	10 ⁻¹⁵	10 ⁻¹⁷	10 ⁻¹⁷	10 ⁻¹²	2·10 ⁻¹³	10 ⁻¹⁷	2·10 ⁻¹³		
σ _p [cm ²]		--	5·10 ⁻¹²	10 ⁻¹⁴	10 ⁻¹⁴	5·10 ⁻¹⁵	10 ⁻¹⁷	3·10 ⁻¹¹	10 ⁻¹⁷		
τ _{n0} [ns]		--	10 ⁴	3.3·10 ²	2.5·10 ²	10	3.3·10 ⁻²	6.7·10 ⁻⁴	--		
τ _{p0} [ns]		--	2	0.33	0.25	2·10 ³	6.7·10 ²	6.7·10 ⁴	--		
S _{n0} [cm·s ⁻¹]		10 ⁴	--	--	--	--	--	35	2.7·10 ⁵		
S _{p0} [cm·s ⁻¹]		10 ⁷	--	--	--	--	--	10 ⁸	29		
Transition		--	0/-	0/-	0/-	0/+	0/+	0/-	0/+		0/+

The physical properties of the device for simulating voltage dependent admittance spectra and J-V curves in Paper 4 (section 4.4) are given in Table A - 5. Parameters of the window layers (CdS, i-ZnO, AZO) are identical to the default model in Table A - 4 and for this reason not listed in Table A - 5.

A.5. Overview samples used for ALE experiments

Table A - 6 List of samples used for the verification and evaluation of the ALE impact on CIGSe absorbers, up to complete solar cells.

Designation	Methods	Comments, Observations
CIGSe2016-01-08-1	TRPL	ALE under low light intensity with TRPL laser and high light intensity with sun simulator
CIGSe2016-01-09-1	TRPL, GDOES	Accumulation of Na at the very surface after ALE of bare CIGSe absorber
CIGSe2016-01-10-1	TRPL	Trial recovery of ALE effect by DA of absorber in atmosphere
CIGSe2016-01-11-1	TRPL, GDOES	Repetition Na accumulation at the very surface after ALE of bare CIGSe absorber
CIGSe2016-01-12-1	TRPL	ALE after DA of bare absorber
CIGSe2016-01-13-1	TRPL	ALE as a function of low light intensities with TRPL laser
CIGSe2016-01-14-1	TRPL, GDOES	ALE effect after illumination in vacuum
CIGSe2016-07-27-1	TRPL	Trial recovery of ALE effect by CBD-CdS
CIGSe2016-08-05-1	TRPL	ALE on CIGSe layers without Na
CIGSe2016-10-18-1	TRPL, XPS, J-V	Accumulation of Na and O at the CIGSe surface and deterioration of J-V-parameter of complete solar cells due to ALE (Paper1)
CIGSe2016-11-21-1	TRPL, XPS, J-V, GDOES	Repetition Na and O accumulation at the CIGSe surface after ALE (Paper1)
CIGSe2017-03-14-1	TRPL, J-V, GDOES, $V_{oc}(T)$, $V_{oc}(t)$	Smaller activation energy of J_0 than the CIGSe band gap energy and decreasing V_{oc} transient for devices with ALE-absorber (Paper1)
CIGSe2017-04-04-1	TRPL, J-V, GDOES, $V_{oc}(T)$, $V_{oc}(t)$, VAS	Impact of ALE and CdS on TRPL-transients Recovery of solar cells with ALE absorbers by HLS (Paper3) Detection of interface states due to ALE with voltage dependent admittance spectroscopy (Paper3) Partial recovery of ALE induced TRPL lifetime reduction after rinsing the bare CIGSe absorber with $(NH_4)_2S$
CIGSe2017-06-22-1	TRPL, GDOES	HLS on CdS covered CIGSe absorbers with and without ALE treatment Na accumulation at the CIGSe/CdS interface after HLS ALE on CIGSe without Na ALE with photon energies below $E_{g,a}$

Designation	Methods	Comments, Observations
CIGSe2017-07-25-1	TRPL, J-V	TRPL lifetime reduction as a function of ALE light dose and intensity (Paper2) Metastable states after HLS and DA of complete solar cells (Paper2) Persistent reduction of TRPL lifetime after CdS deposition (Paper2) ALE with photon energies below $E_{g,a}$
CIGSe2017-09-13-1	TRPL, J-V, GDOES, $V_{oc}(T)$, $V_{oc}(t)$, VAS	Reproduction of detected interface states for solar cells with ALE absorbers in VAS Simulation of device characteristics (Paper4)
CIGSe2017-11-08-1	TRPL, XPS	Investigation of the impact of humidity during ALE (only with XPS) ALE as a function of photon energy
CIGSe2017-11-10-1	TRPL, XPS, J-V, GDOES, $V_{oc}(T)$, $V_{oc}(t)$, C-V, VAS	Investigation of the impact of humidity during ALE (only with XPS) Investigation as fabricated and HLS state on complete solar cells
CIGSe2018-01-30-1	TRPL, J-V	Investigation of metastable character, applying HLS, forward and reverse bias (J-V) ALE of absorbers with NaF-PDT
CIGSe2018-04-10-1 CIGSe2018-04-11-1 CIGSe2018-04-12-1 CIGSe2018-04-13-1	TRPL	ALE on CIGSe with PDT: KF RbF CsF without
CIGSe2018-06-27-1	TRPL, J-V	Investigation of metastable character, applying HLS, forward and reverse bias (TRPL on complete solar cells) Impact of ALE on CIGSe absorbers without Na
CIGSe2018-06-27-1	TRPL, J-V, GDOES, $V_{oc}(T)$, $V_{oc}(t)$	Repetition TRPL lifetime reduction as a function of ALE light dose and intensity Investigation of metastable character, applying HLS, forward and reverse bias ($V_{oc}(T)$, $V_{oc}(t)$)

Methods, abbreviations:

C-V	Capacitance as a function of voltage at fixed temperature and frequency
DA	Annealing in darkness
GDOES	Glow-discharge optical emission spectroscopy
HLS	Heat light soaking
J-V	Measurement of J-V-characteristics
PDT	Post-deposition treatment
TRPL	Time-resolved photoluminescence
VAS	Voltage dependent admittance spectroscopy (Capacitance as a function of voltage, frequency, and temperature)
$V_{oc}(T)$	Measurement of V_{oc} as a function of temperature
$V_{oc}(t)$	Measurement of V_{oc} as a function of time under red light illumination
XPS	X-Ray photoelectron emission spectroscopy

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Eidesstattliche Erklärung (Declaration on oath)

Hiermit erkläre ich, dass ich die vorliegende Arbeit selbstständig und ausschließlich mit den von mir angegebenen Quellen und Hilfsmitteln verfasst habe. Ferner versichere ich, dass ich alle wörtlichen und sinngemäßen Zitate als solche kenntlich gemacht habe.

Halle, 25.08.2021

Unterschrift: Holsch